

#3

Access DB# 175449

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Sm J. Lee Examiner #: 76060 Date: 12-28-02
Art Unit: 1752 Phone Number 301 21333 Serial Number: 10/673,332
Mail Box and Bldg/Room Location: 9D66 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Plz. See Bib.

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

Plz. search for a polymer which

has ① repeating unit of Formula (2)

and

② repeating unit which contains a ~~substituent~~

polymerizable gp. represented by formula (A)

shown
as in Cl. #1

SCIENTIFIC REFERENCE BR
Sci & Tech Inf. Ctr

JAN 03 2003

Pat. & T.M. Office

STAFF USE ONLY

Searcher: <u>2#</u>	Type of Search	Vendors and cost where applicable
Searcher Phone #: _____	NA Sequence (#) _____	STN <u>\$819.88</u>
Searcher Location: _____	AA Sequence (#) _____	Dialog _____
Date Searcher Picked Up: _____	Structure (#) <u>2</u>	Questel/Orbit _____
Date Completed: <u>1/4/06</u>	Bibliographic _____	Dr.Link _____
Searcher Prep & Review Time: <u>30</u>	Litigation _____	Lexis/Nexis _____
Clerical Prep Time: <u>30</u>	Fulltext _____	Sequence Systems _____
Online Time: <u>140</u>	Patent Family _____	WWW/Internet _____
	Other _____	Other (specify) _____

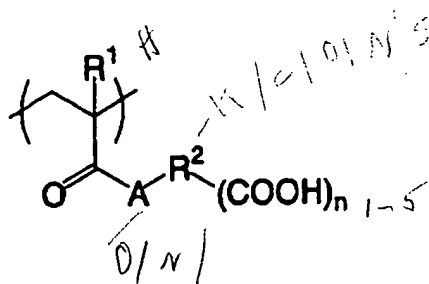
AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

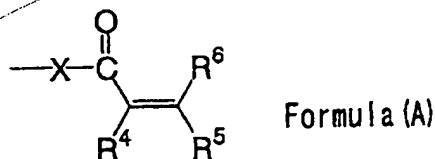
LISTING OF CLAIMS:

Claim 1. (currently amended): A polymerizable composition comprising a binder polymer having a repeating unit represented by the following formula (I) and a repeating unit having a radical-polymerizable group represented by the following formula (A) ~~or (B)~~, an infrared absorbent, a polymerization initiator and a polymerizable compound,

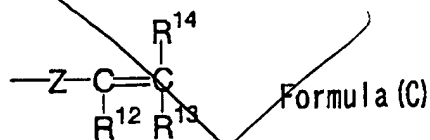
Formula (I)



wherein R¹ represents a hydrogen atom or a methyl group; R² represents a linking group which includes ~~two~~ one or more atoms selected from the group consisting of a carbon atom, a hydrogen atom, an oxygen atom, a nitrogen atom and a sulfur atom and has a number of atoms of 2 to ~~8230~~; A represents an oxygen atom or -NR³- in which R³ represents a hydrogen atom or a monovalent hydrocarbon group having 1 to 10 carbon atoms; and n represents an integer of 1 to 5;



wherein R⁴, R⁵ and R⁶ each independently represent a hydrogen atom, or a monovalent substituent; and X represents an oxygen atom, a sulfur atom or N-R¹⁵ in which R¹⁵ represents a hydrogen atom or monovalent organic group;



wherein R¹², R¹³ and R¹⁴ each independently represent a hydrogen atom, or a monovalent substituent; and Z represents an oxygen atom, a sulfur atom or N-R¹⁵ or a phenylene group, in which R¹⁵ represents a hydrogen atom or a monovalent organic group.

Claim 2. (previously presented): The polymerizable composition according to claim 1, wherein the number of atoms constituting a skeleton of the linking group represented by R² in the binder polymer having the repeating unit represented by formula (I) is 1 to 30.

Claim 3. (previously presented): The polymerizable composition according to claim 1, wherein the binder polymer is a copolymer comprising at least the unit represented by



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BIBDATASHEET

CONFIRMATION NO. 2251

Bib Data Sheet

SERIAL NUMBER 10/673,332	FILING DATE 09/30/2003 RULE	CLASS 430	GROUP ART UNIT 1752	ATTORNEY DOCKET NO. Q77298
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APPLICANTS

Atsushi Sugasaki, Shizuoka-ken, JAPAN;
 Kazuto Kunita, Shizuoka-ken, JAPAN;
 Kazuhiro Fujimaki, Shizuoka-ken, JAPAN;

** CONTINUING DATA *****
 None SJL

** FOREIGN APPLICATIONS *****
 JAPAN 2002-287920 09/30/2002
 JAPAN 2003-038288 02/17/2003
 JAPAN 2003-100575 04/03/2003 } SJL

IF REQUIRED, FOREIGN FILING LICENSE GRANTED
 ** 12/18/2003

Foreign Priority claimed <input checked="" type="checkbox"/> yes <input type="checkbox"/> no	STATE OR COUNTRY JAPAN	SHEETS DRAWING 1	TOTAL CLAIMS 20	INDEPENDENT CLAIMS 3
35 USC 119 (a-d) conditions met <input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after Allowance				
Verified and Acknowledged Examiner's Signature <i>[Signature]</i> Initials SJL				

ADDRESS
 23373
 SUGHRUE MION, PLLC
 2100 PENNSYLVANIA AVENUE, N.W.
 SUITE 800
 WASHINGTON, DC
 20037

TITLE
 Polymerizable composition and planographic printing plate precursor

FILING FEE	FEES: Authority has been given in Paper	<input type="checkbox"/> All Fees <input type="checkbox"/> 1.16 Fees (Filing) <input type="checkbox"/> 1.17 Fees (Processing Ext. of
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=> d his ful

(FILE 'HOME' ENTERED AT 09:03:18 ON 04 JAN 2006)

FILE 'HCAPLUS' ENTERED AT 09:03:36 ON 04 JAN 2006

E US20040072101/PN

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D ALL
SEL RN

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OR 658705-94-3/BI OR 676349-35-2/BI OR 676349-36-3/BI
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OR 676349-76-1/BI OR 676349-77-2/BI OR 676349-78-3/BI
OR 676349-79-4/BI OR 676349-80-7/BI)
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D 1-40 CRN STR

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L3 STR
L4 STR

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L6 26 SEA SSS SAM L3 AND L5
D QUE STAT
L7 50 SEA SSS SAM L4 AND L5
D QUE STAT
L8 26 SEA SSS SAM L3 AND L4 AND L5
D QUE STAT

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L9 STR L3

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L11 32335 SEA SSS FUL L9 AND L5
SAV L11 LEE332/A

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L13 STR L3

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D QUE STAT
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D QUE STAT

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L17 STR L3

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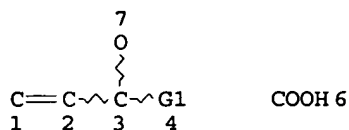
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 L22 6 SEA ABB=ON PLU=ON L21 AND L2
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 L27 18 SEA ABB=ON PLU=ON L24
 L28 3 SEA ABB=ON PLU=ON L22
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 L29 926 SEA ABB=ON PLU=ON PLANOG?
 L30 1 SEA ABB=ON PLU=ON L29 AND L25
 D SCAN
 L31 19025 SEA ABB=ON PLU=ON PRINT? (2A) (PLATE OR PLATES)
 L32 59 SEA ABB=ON PLU=ON L31 AND L25
 L33 52631 SEA ABB=ON PLU=ON (IR OR INFRA(A)RED) (2A) ABSOR?
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 L36 20 SEA ABB=ON PLU=ON (L26 OR L27 OR L28)
 L37 76 SEA ABB=ON PLU=ON L36 OR L35
 L38 56 SEA ABB=ON PLU=ON L37 NOT L36
 L39 0 SEA ABB=ON PLU=ON L1 AND L38
 L40 1 SEA ABB=ON PLU=ON L1 AND L37
 L41 8 SEA ABB=ON PLU=ON L34 OR L30
 L42 1 SEA ABB=ON PLU=ON L1 AND L41
 L43 7 SEA ABB=ON PLU=ON L41 AND L38
 L44 8 SEA ABB=ON PLU=ON L41 AND L35
 L45 1 SEA ABB=ON PLU=ON L41 AND L36
 L46 68 SEA ABB=ON PLU=ON L37 NOT L41
 L47 49 SEA ABB=ON PLU=ON L46 NOT L36
 L48 19 SEA ABB=ON PLU=ON L46 NOT L47
 D QUE STAT L47
 L49 45 SEA ABB=ON PLU=ON BINDER? AND L37
 L50 44 SEA ABB=ON PLU=ON L49 AND (L29 OR L31 OR L33)
 L51 49 SEA ABB=ON PLU=ON L43 OR L50
 L52 56 SEA ABB=ON PLU=ON L51 OR L36
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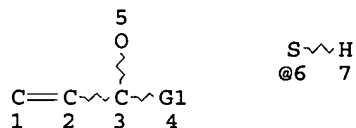
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 DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
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 NUMBER OF NODES IS 6

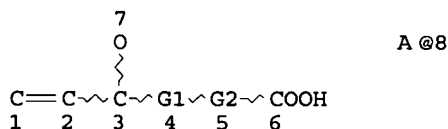
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 L16 STR



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 DEFAULT MLEVEL IS ATOM
 DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
 RING(S) ARE ISOLATED OR EMBEDDED
 NUMBER OF NODES IS 7

STEREO ATTRIBUTES: NONE
 L17 STR



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 REP G2=(1-20) 8
 NODE ATTRIBUTES:
 NSPEC IS RC AT 8
 CONNECT IS E1 RC AT 7
 DEFAULT MLEVEL IS ATOM
 DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
 RING(S) ARE ISOLATED OR EMBEDDED
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 L21 2107 SEA FILE=REGISTRY SUB=L19 SSS FUL L16
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L53 ANSWER 1 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2005:960457 Document No. 143:257094 Photopolymerizable composition containing binder polymer having carboxylic acid group and lithographic printing master plate with high sensitivity to laser beam. Sugasaki, Atsushi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2005234385 A2, 20050902, 94 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2004-45303 20040220.

AB Disclosed is a photopolymerizable composition comprising a binder polymer [CH-CR1(C(:O)-A-R2-(COOH)n)] (R11 = H, Me; R2 = bonding group with total atom number 2-82; A = O, etc.; R3 = H, C1-10 monovalent hydrocarbon; and n = 1-5), a sensitizing dye having the maximum absorption at 300-600 nm, a polymerization initiator, and a polymerizable compound

IT 676349-36-3

RL: NUU (Other use, unclassified); USES (Uses)

(binder polymer; photopolymerizable composition containing binder polymer having carboxylic acid group for lithog. printing master plate)

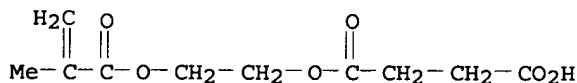
RN 676349-36-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

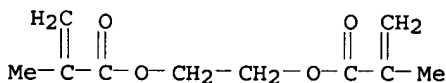
CMF C10 H14 O6



CM 2

CRN 97-90-5

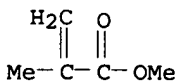
CMF C10 H14 O4



CM 3

CRN 80-62-6

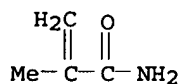
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



IC ICM G03F007-033

ICS C08F220-10; C08F220-54; G03F007-00; G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT 93441-11-3 676349-36-3 709037-26-3 791625-79-1
 863495-66-3 863495-67-4 863495-68-5 863495-69-6
 863495-71-0 863495-72-1 863495-73-2 863495-74-3
 863495-75-4 863495-76-5 863495-77-6 863495-78-7
 863495-80-1 863495-81-2 863495-82-3 863495-84-5
 863495-85-6 863495-86-7

RL: NUU (Other use, unclassified); USES (Uses)

(binder polymer; photopolymerizable composition containing binder
 polymer having carboxylic acid group for lithog. printing
 master plate)

L53 ANSWER 2 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2005:822657 Document No. 143:219492 Processing of lithographic
 printing plate using washing solution containing preservative and
 chelating agent. Nagase, Hiroyuki (Fuji Photo Film Co., Ltd.,
 Japan). Jpn. Kokai Tokkyo Koho JP 2005221615 A2 20050818, 46 pp.
 (Japanese). CODEN: JKXXAF. APPLICATION: JP 2004-27852 20040204.

AB The method comprises steps for (a) imagewise exposing a neg.
 working lithog. printing plate material having a light-sensitive
 layer containing an IR absorber, an ethylenically unsatd. monomer, a
 polymerization initiator, and a polymer binder on Al support and (b)
 developing it, in which an exposed material is processed with the
 washing bath containing a preservative and a chelating agent before
 and after the development. The method prolongs days for the
 exchange of the bath, preventing precipitation and providing improved
 processing stability.

IT 658705-94-3

RL: TEM (Technical or engineered material use); USES (Uses)

(binder; processing of lithog. printing plate using washing
 solution containing preservative and chelating agent)

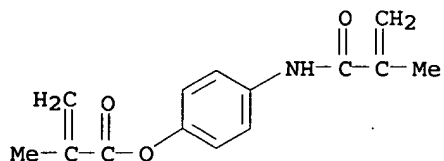
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and
 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate
 (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

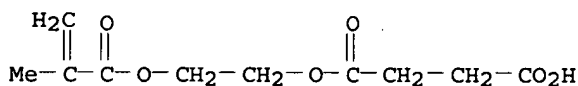
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CM 2

CRN 20882-04-6

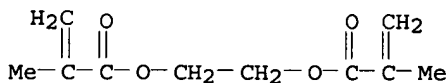
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F007-00

ICS G03F007-11; G03F007-32; G03F007-38

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 658705-94-3

RL: TEM (Technical or engineered material use); USES (Uses)
 (binder; processing of lithog. printing plate using washing
 solution containing preservative and chelating agent)

L53 ANSWER 3 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2005:302458 Document No. 142:382209 Photopolymerizable photoimaging
 resin compositions for image-forming layer of lithographic
 printing plates. Kunita, Kazuto (Fuji Photo Film Co., Ltd.,
 Japan). Jpn. Kokai Tokkyo Koho JP 2005091617 A2 20050407, 98 pp.
 (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-323410 20030916.

AB The composition contains 2 kinds of alkali-solubilizable
 radically-crosslinkable polymers, wherein one of the polymer has
 styrene groups and alkali-solubilizable groups in the side chain
 and wherein the other polymer has (meth)acryl groups and
 alkali-solubilizable groups in the side chain. The composition shows
 high sensitivity and good storageability and provides good
 developing characteristics.

IT 676349-54-5

RL: TEM (Technical or engineered material use); USES (Uses)
 (resin in photopolymerizable photoimaging resin compns.)

RN 676349-54-5 HCAPLUS

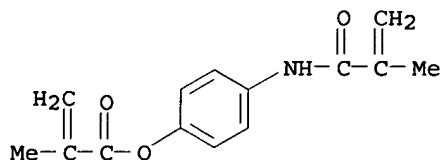
CM 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-
 propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl
 bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-

propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

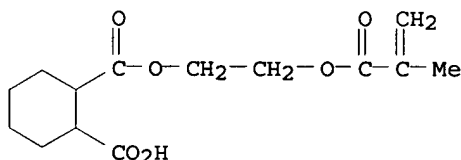
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CM 2

CRN 51252-88-1

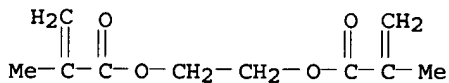
CMF C14 H20 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F007-038

ICS C08F290-08; G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 37

IT 50583-46-5 207730-92-5 491080-47-8 657414-44-3 657414-50-1

676349-54-5 761432-20-6 790685-25-5 790685-30-2

791124-32-8 849435-05-8 849435-06-9 849435-07-0

849435-09-2 849435-10-5 849435-11-6 849435-12-7

849435-52-5 849435-53-6 849435-54-7 849435-56-9

849435-59-2 849435-61-6

RL: TEM (Technical or engineered material use); USES (Uses)
(resin in photopolymerizable photoimaging resin compns.)

L53 ANSWER 4 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2005:212591 Document No. 142:306466 Photopolymerizable photoimaging composition and negatively-working directly-imaging lithographic printing plate precursors therefrom. Fujimaki, Kazuhiro (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP

2005062482 A2 20050310, 81 pp. (Japanese). CODEN: JKXXAF.
 APPLICATION: JP 2003-~~292530~~ 20030812.

AB The title composition contains a radical polymerization initiator, a radical polymerization co-initiator of ≤ 1.10 V oxidation potential, an IR-absorber, and radically polymerizable compds. The composition shows high sensitivity and good storageability and provides highly durable layers.

IT 847565-07-5
 RL: TEM (Technical or engineered material use); USES (Uses)
 (radically polymerizable compds. in composition)

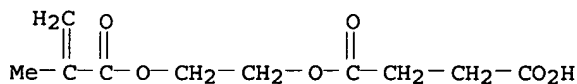
RN 847565-07-5 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2-methyl-2-propenamide and 2-propenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

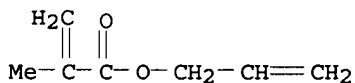
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CRN 96-05-9

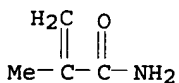
CMF C7 H10 O2



CM 3

CRN 79-39-0

CMF C4 H7 N O



IC ICM G03F007-029
 ICS C08F002-44; C08F002-50; G03F007-004; G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 110992-87-5 603959-43-9 835902-38-0
 RL: TEM (Technical or engineered material use); USES (Uses)
 (IR-absorber in composition)

IT 29570-58-9 80937-22-0 91105-84-9 761432-20-6
 847565-07-5 847573-65-3
 RL: TEM (Technical or engineered material use); USES (Uses)
 (radically polymerizable compds. in composition)

L53 ANSWER 5 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN
 2005:209978 Document No. 142:306465 Photopolymerizable photoimaging
 composition and negatively-working directly-imaging lithographic
 printing plate precursors made thereof. Fujimaki, Kazuhiro (Fuji
 Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP
 2005062478 A2 20050310, 81 pp. (Japanese). CODEN: JKXXAF.
 APPLICATION: JP 2003-292453 20030812.

AB The title composition contains a compound with an amino groups and
 hydroxy groups, an IR-absorber, a radical
 polymerization initiator, and ethylenic unsatd. compds. The composition shows
 high sensitivity and good storageability and provides highly
 durable layers.

IT 847565-07-5

RL: TEM (Technical or engineered material use); USES (Uses)
 (ethylenic unsatd. compds. in composition)

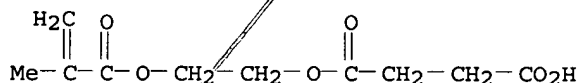
RN 847565-07-5 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with 2-methyl-2-propenamide and 2-propenyl
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

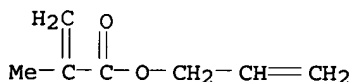
CMF C10 H14 O6



CM 2

CRN 96-05-9

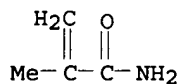
CMF C7 H10 O2



CM 3

CRN 79-39-0

CMF C4 H7 N O



IC ICM G03F007-004

ICS C08F002-44; G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)

IT 110992-87-5 835902-38-0

RL: TEM (Technical or engineered material use); USES (Uses)
 (IR-absorber in composition)

IT 761432-20-6 847565-07-5

RL: TEM (Technical or engineered material use); USES (Uses)
 (ethylenic unsatd. compds. in composition)

L53 ANSWER 6 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2005:75760 Document No. 142:144139 Positive-working lithographic plates with high latitude, sensitivity, and scratch resistance and resin compositions therefor. Tsuchimura, Toshitaka (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2005024646 A2 20050127, 90 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-187138 20030630.

AB The compns. comprise IR absorbers, alkali soluble resins, and polymers having (XCnH2n+1Y) units (X = trivalent linking group; Y = polar group; n = 6-40). Lithog. plates equipped with recording layers comprising the compns. are useful for direct IR laser platemaking.

IT 824967-95-5P

RL: IMF (Industrial manufacture); MOA (Modifier or additive use); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (pos.-working lithog. plates with high latitude and scratch resistance containing specific polymers with polar group-terminated alkyl branches)

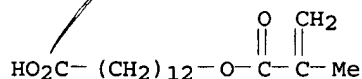
RN 824967-95-5 HCAPLUS

CN Tridecanoic acid, 13-[(2-methyl-1-oxo-2-propenyl)oxy]-, polymer with 2-methyl-2-propenoic acid and octadecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 194025-68-8

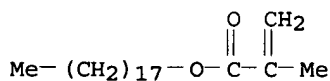
CMF C17 H30 O4



CM 2

CRN 32360-05-7

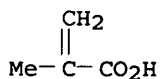
CMF C22 H42 O2



CM 3

CRN 79-41-4

CMF C4 H6 O2



IC ICM G03F007-033
ICS C08F020-34; G03F007-00; G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38

IT 134127-48-3
RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)
(IR absorbers; pos.-working lithog. plates with high latitude and scratch resistance containing specific polymers with polar group-terminated alkyl branches)

IT 824967-94-4P 824967-95-5P 824967-97-7P 824967-99-9P
824968-01-6P 824968-03-8P 824968-05-0P 824968-06-1P
824968-07-2P 824968-09-4P 824968-11-8P 824968-13-0P
824968-14-1P 824968-15-2P
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos.-working lithog. plates with high latitude and scratch resistance containing specific polymers with polar group-terminated alkyl branches)

L53 ANSWER 7 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN
2004:1128831 Document No. 142:65373 Photosensitive composition for computer-to-plate lithographic printing plate. Nakamura, Ippei; Kawauchi, Ikuo (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004361483 A2 20041224, 47 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-156800 20030602.

AB Disclosed is the photosensitive composition comprising (A) a polymer compound having a unit having an acid group bonded to the side chain via an organic bonding group and a unit having an amide and/or amino group in the side chain and (B) an IR absorber
. Further, composition contains (C) an alkali-soluble resin.

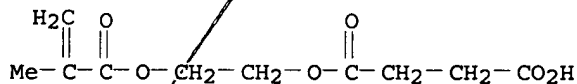
IT 810675-04-8 810675-05-9 810675-06-0
RL: NUU (Other use, unclassified); USES (Uses)
(photosensitive composition for computer-to-plate lithog. printing plate)

RN 810675-04-8 HCAPLUS
CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with ethyl 2-methyl-2-propenoate and 2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

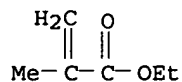
CMF C10 H14 O6



CM 2

CRN 97-63-2

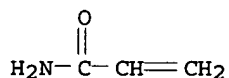
CMF C6 H10 O2



CM 3

CRN 79-06-1

CMF C3 H5 N O



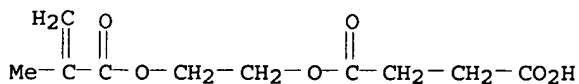
RN 810675-05-9 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with butyl 2-propenoate and 2-methyl-2-propenamide
 (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

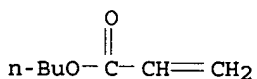
CMF C10 H14 O6



CM 2

CRN 141-32-2

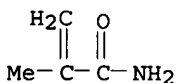
CMF C7 H12 O2



CM 3

CRN 79-39-0

CMF C4 H7 N O



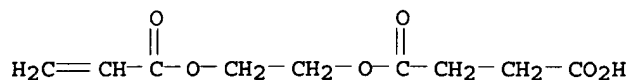
RN 810675-06-0 HCAPLUS

CN Butanedioic acid, mono[2-[(1-oxo-2-propenyl)oxy]ethyl] ester,
 polymer with butyl 2-methyl-2-propenoate and 2-propenamide (9CI)
 (CA INDEX NAME)

CM 1

CRN 50940-49-3

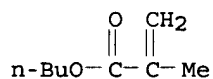
CMF C9 H12 O6



CM 2

CRN 97-88-1

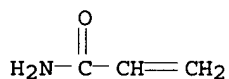
CMF C8 H14 O2



CM 3

CRN 79-06-1

CMF C3 H5 N O



IC ICM G03F007-033

ICS G03F007-004; G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

ST photosensitive compn lithog printing plate polymer IR absorber

IT Optical materials

(IR absorbers; photosensitive composition for computer-to-plate lithog. printing plate)

IT IR materials

(absorbers; photosensitive composition for computer-to-plate lithog. printing plate)

IT 134127-48-3 205744-92-9

RL: NUU (Other use, unclassified); USES (Uses)

(IR absorber; photosensitive composition for computer-to-plate lithog. printing plate)

IT 810675-04-8 810675-05-9 810675-06-0

810675-07-1 810675-08-2 810675-09-3 810675-10-6

RL: NUU (Other use, unclassified); USES (Uses)

(photosensitive composition for computer-to-plate lithog. printing plate)

L53 ANSWER 8 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:993597 Document No. 141:417981 Polymer compositions and heat-mode positive or negative lithographic plate materials using

them with excellent sensitivity and scratch resistance.
 Tsuchimura, Toshitaka (Fuji Photo Film Co., Ltd., Japan). Jpn.
 Kokai Tokkyo Koho JP 2004325508 A2 20041118, 90 pp. (Japanese).
 CODEN: JKXXAF. APPLICATION: JP 2003-115985 20030421.

AB The materials have recording layers containing polymers having units
 $X(\text{COOH})(\text{C}_n\text{H}_{2n+1})$ (X = tetravalent linking group; $n = 6-40$) and
IR absorbers and varying solubility to alkaline aqueous
 solns. by IR laser exposure, thus giving pos. lithog. plates with
 good development latitude.

IT 792936-98-2

RL: TEM (Technical or engineered material use); USES (Uses)
 (recording layer; heat-mode lithog. plates with good IR
 sensitivity and scratch resistance using polymers bearing
 carboxyl groups and long-chain alkyl groups)

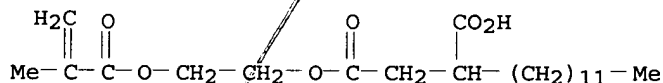
RN 792936-98-2 HCAPLUS

CN Butanedioic acid, dodecyl-, 4-[2-[(2-methyl-1-oxo-2-
 propenyl)oxy]ethyl] ester, polymer with 2-methyl-2-propenoic acid
 (9CI) (CA INDEX NAME)

CM 1

CRN 125697-14-5

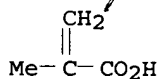
CMF C22 H38 O6



CM 2

CRN 79-41-4

CMF C4 H6 O2



IC ICM G03F007-033

ICS G03F007-00; G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)
 Section cross-reference(s): 38

IT Optical materials

(**IR absorbers**, recording layer; heat-mode
 lithog. plates with good IR sensitivity and scratch resistance
 using polymers bearing carboxyl groups and long-chain alkyl
 groups)

IT **IR materials**

(**absorbers**, recording layer; heat-mode lithog. plates
 with good IR sensitivity and scratch resistance using polymers
 bearing carboxyl groups and long-chain alkyl groups)

IT 134127-48-3

RL: TEM (Technical or engineered material use); USES (Uses)

(**IR absorber**, recording layer; heat-mode
 lithog. plates with good IR sensitivity and scratch resistance
 using polymers bearing carboxyl groups and long-chain alkyl
 groups)

IT 792936-94-8 792936-96-0 792936-97-1 **792936-98-2**
 792936-99-3 792937-01-0 792937-02-1 792937-03-2
 792937-05-4 792937-06-5 792937-07-6 792942-36-0
 RL: TEM (Technical or engineered material use); USES (Uses)
 (recording layer; heat-mode lithog. plates with good IR
 sensitivity and scratch resistance using polymers bearing
 carboxyl groups and long-chain alkyl groups)

L53 ANSWER 9 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN
 2004:963457 Document No. 141:417960 Polymerizable composition and
 its application in making original plate of lithographic printing
 plates. Kakino, Tatsuki; Kunita, Kazuto (Fuji Photo Film Co.,
 Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004317804 A2 20041111,
 84 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-111768
 20030416.

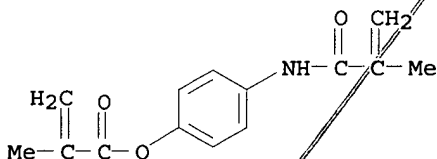
AB Title composition comprises (A) an alkali-soluble polymer with mol. weight
 distribution <2.5, (B) polymerizable compds., (C) polymerization
 initiators, and, preferably, a photosensitizing dye.

IT **676349-54-5**
 RL: POF (Polymer in formulation); TEM (Technical or engineered
 material use); USES (Uses)
 (polymerizable composition for lithog. printing plates)

RN 676349-54-5 HCAPLUS
 CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-
 propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl
 bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-
 propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

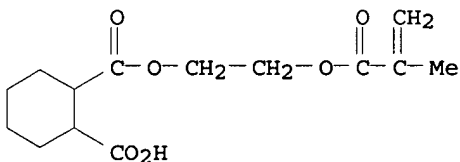
CM 1

CRN 86229-45-0
 CMF C14 H15 N O3



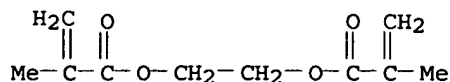
CM 2

CRN 51252-88-1
 CMF C14 H20 O6



CM 3

CRN 97-90-5
 CMF C10 H14 O4



IC ICM G03F007-038

ICS G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 49736-69-8 50583-46-5 207730-91-4 207730-92-5 657414-36-3

676349-54-5 681127-05-9 761432-20-6 782483-55-0

790685-25-5 790685-26-6 790685-28-8 790685-29-9

790685-30-2 790685-31-3

RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)

(polymerizable composition for lithog. printing plates)

L53 ANSWER 10 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:963412 Document No. 141:417958 Polymerizable compositions and negative-working lithographic printing plates using them with excellent laser sensitivity and print resistance. Kakino, Ryuki; Kunita, Kazuto (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004317543 A2 20041101, 84 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-107397 20030411.

AB The comps. contain alkali-soluble star polymers (bearing radically polymerizable groups, preferably), polymerizable compds., polymerization initiators, and optionally sensitizer dyes.

IT 658705-94-3

RL: TEM (Technical or engineered material use); USES (Uses)

(star-branched, binder; neg. lithog. plates having

photosensitive layers containing alkali-soluble star polymers with good laser sensitivity and print resistance)

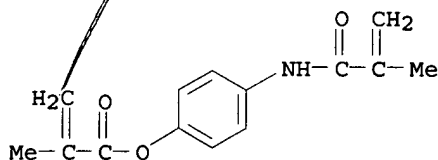
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

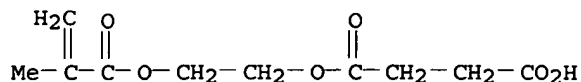
CMF C14 H15 N O3



CM 2

CRN 20882-04-6

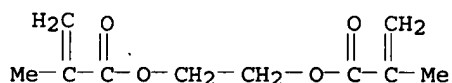
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F007-032

ICS G03F007-00; G03F007-038

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT 657414-36-3 657414-44-3 657414-46-5 658050-90-9

658705-94-3 701960-47-6 782483-51-6 782483-55-0

791124-32-8 791124-33-9 791124-35-1

RL: TEM (Technical or engineered material use); USES (Uses)

(star-branched, binder; neg. lithog. plates having photosensitive layers containing alkali-soluble star polymers with good laser sensitivity and print resistance)

L53 ANSWER 11 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:904409 Document No. 141:386420 Photosensitive composition and its application in making original plate of lithographic printing plate. Murota, Yasufumi; Goto, Takahiro (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004302206 A2 20041028, 35 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-95900 20030331.

AB Title composition comprises an IR-absorbing agent, a polymerization initiator, polymerizable compds., binder polymers, a carboxyl-containing compound having weight-average mol. weight <3000, and a pigment having a maximum absorption in the range of 450-750 nm. An original plate of a lithog. printing plate is obtained by laminating a substrate, a photosensitive layer formed from the above composition, and a protection layer.

IT 658705-94-3

RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)

(photosensitive composition for making original plate of lithog. printing plate)

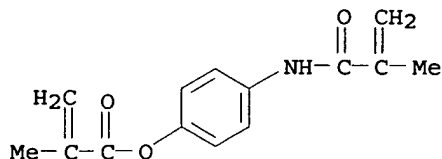
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

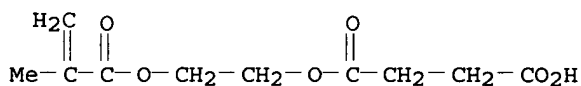
CMF C14 H15 N O3



CM 2

CRN 20882-04-6

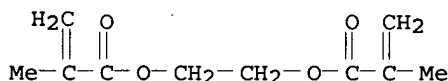
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F007-004

ICS G03F007-00; G03F007-029; G03F007-11

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 293329-29-0 658705-94-3

RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)

(photosensitive composition for making original plate of lithog. printing plate)

L53 ANSWER 12 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:904408 Document No. 141:386419 Photosensitive composition and its application in making original plate of lithographic printing plate. Murota, Yasufumi; Goto, Takahiro (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004302205 A2 20041028, 31 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-95899 20030331.

AB Title composition comprises an IR-absorbing agent, a polymerization initiator, polymerizable compds., binder polymers, and a pigment which is obtained by coating the pigment with a resin material and has a maximum absorption in the range of 450-750 nm. An original plate of a lithog. printing plate is obtained by laminating a substrate, a photosensitive layer formed from the above composition, and a protection layer.

IT 658705-94-3

RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)

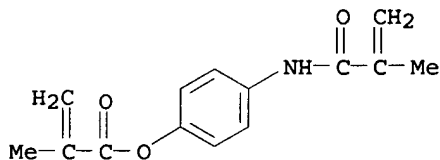
(photosensitive composition containing resin-coated pigment for making original plate of lithog. printing plate)

RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

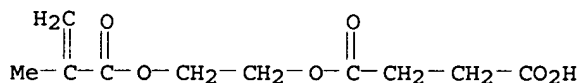
CM 1

CRN 86229-45-0
CMF C14 H15 N O3



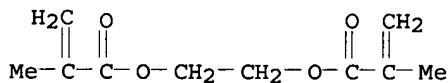
CM 2

CRN 20882-04-6
CMF C10 H14 O6



CM 3

CRN 97-90-5
CMF C10 H14 O4



IC ICM G03F007-004

ICS G03F007-00; G03F007-11

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 293329-29-0 658705-94-3

RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)

(photosensitive composition containing resin-coated pigment for making original plate of lithog. printing plate)

L53 ANSWER 13 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:904401 Document No. 141:386417 Photopolymerizable resin composition for negative-working lithographic printing plate precursors. Kakino, Ryuki; Kunita, Kazuto (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004302184 A2 20041028, 90 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-95552 20030331.

AB The title composition contains an alkali-solubilizable block copolymer, polymerizable compds., and a polymerization initiator, wherein the resin

has at least one repeating unit having an alkali-solubilizable group. The title composition provides printing plate precursor of good development characteristics and printing plate of high printing durability.

IT 658705-94-3P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(block copolymer resin in photopolymerizable resin composition)

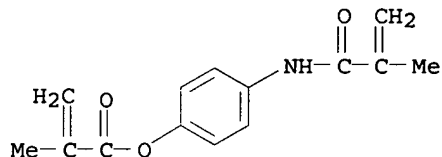
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

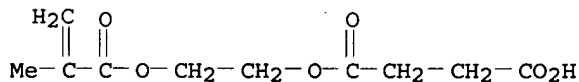
CMF C14 H15 N O3



CM 2

CRN 20882-04-6

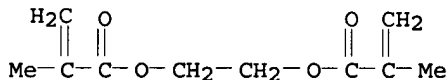
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F007-038

ICS C08F290-12; G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 35, 37

IT 49736-69-8DP, dehydrobrominated 49736-69-8P 50583-46-5DP, dehydrobrominated 50583-46-5P 657414-36-3P 657414-37-4P

657414-50-1P 658050-90-9P 658705-94-3P 681127-05-9P

782483-51-6P 782483-54-9P 782483-55-0P 782496-94-0P

RL: SPN (Synthetic preparation); TEM (Technical or engineered

material use); PREP (Preparation); USES (Uses)
(block copolymer resin in photopolymerizable resin composition)

L53 ANSWER 14 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:904378 Document No. 141:386414 Photopolymerizable resin composition for negative-working lithographic printing plate precursors. Kakino, Ryuki; Kunita, Kazuto (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004302077 A2 20041028, 89 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-94320 20030331.

AB The title composition contains a alkali-solubilizable polymer, polymerizable compds., and a polymerization initiator, wherein the polymer is a graft polymer. The composition is suitable for exposed with a laser beam.

IT 658705-94-3P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photopolymerizable resin composition for lithog. printing plate precursors)

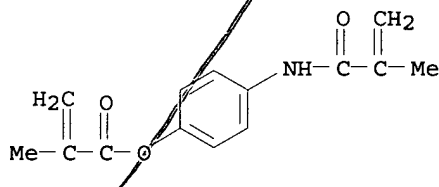
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

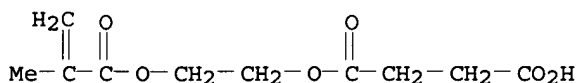
CMF C14 H15 N O3



CM 2

CRN 20882-04-6

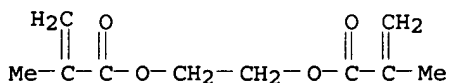
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F007-038
ICS C08F290-12; G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 37
IT 49736-69-8P 657414-36-3P 657414-37-4P 657414-39-6P
657414-44-3P 657414-50-1P 658050-90-9P 658705-81-8P
658705-94-3P 681127-05-9P 782483-51-6P 782483-54-9P
782483-55-0P 782483-56-1P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photopolymerizable resin composition for lithog. printing plate precursors)

L53 ANSWER 15 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN
2004:837357 Document No. 141:340428 Photosensitive composition and lithographic printing plate precursor. Murota, Yasubumi (Fuji Photo Film Co., Ltd., Japan). Eur. Pat. Appl. EP 1467250 A2 20041013, 39 pp. DESIGNATED STATES: R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR. (English). CODEN: EPXXDW. APPLICATION: EP 2004-8640 20040408. PRIORITY: JP 2003-106677 20030410.

AB Disclosed is a photosensitive composition for lithog. printing plate, containing an IR absorber, a borate compound, a polymerizable compound, a binder polymer, and a compound having a weight average mol. weight of $\leq 3,000$ and containing at least one carboxylic acid group. According to the invention, it is possible to provide a photosensitive composition having high sensitivity and good storage stability (unprocessed stock storability) and useful as a photosensitive layer of a neg. working lithog. printing plate precursor. Also, it is possible to provide a neg. working lithog. printing plate precursor capable of being recorded with high sensitivity by IR laser and having excellent storage stability (unprocessed stock storability) and printing resistance.

IT 658705-94-3
RL: TEM (Technical or engineered material use); USES (Uses)
(photosensitive composition and lithog. printing plate precursor)

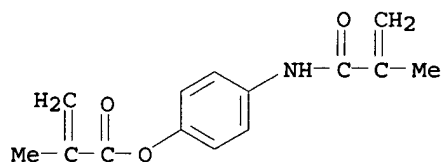
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

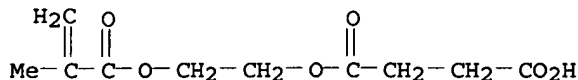
CRN 86229-45-0

CMF C14 H15 N O3



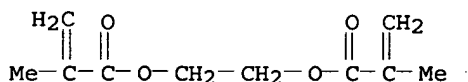
CM 2

CRN 20882-04-6
CMF C10 H14 O6



CM 3

CRN 97-90-5
CMF C10 H14 O4



IC ICM G03F007-004

ICS B41C001-10

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

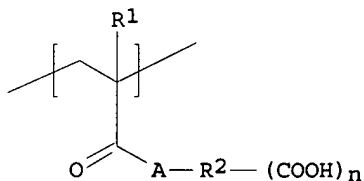
IT 88-99-3, 1,2-Benzenedicarboxylic acid, uses 103-01-5 119-80-2
528-44-9, 1,2,4-Benzenetricarboxylic acid 1137-73-1 4282-31-9,
2,5-Thiophenedicarboxylic acid 15522-59-5 29570-58-9,
Dipentaerythritol hexaacrylate 91105-84-9 183745-11-1
191726-69-9 199127-03-2 293329-29-0 658705-94-3
676349-80-7

RL: TEM (Technical or engineered material use); USES (Uses)
(photosensitive composition and lithog. printing plate precursor)

L53 ANSWER 16 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:741946 Document No. 141:251476 IR laser-sensitive negatively working presensitized lithography plate with suppressed formation of ablation. Goto, Takahiro (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004252202 A2 20040909, 47 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-43086 20030220.

GI



I

AB The lithog. plate for exposure using IR laser at laser output ≥ 6 W per print face and exposure energy ≤ 150 mJ/cm² has a support having thereon ≥ 1 photosensitive layers which lose solubility toward alkali developers by exposure to 750-1400 nm light and a protective layer in this order. Preferably, the

photosensitive layers contain IR absorbers, polymerization initiators, polymerizable compds., and binder polymers bearing repeating units represented by the general formula I (R1 = H, Me; R2 = linkage with atomic number excluding substituents 2-20 and comprising C, H, O, N, S, and halo; A = O, NR3; R3 = H, C1-10 hydrocarbyl; n = 1-5 integer).

IT 658705-94-3

RL: TEM (Technical or engineered material use); USES (Uses)
(binder for photosensitive layer; IR laser-sensitive neg.
working presensitized lithog. plate with suppressed formation
of ablation)

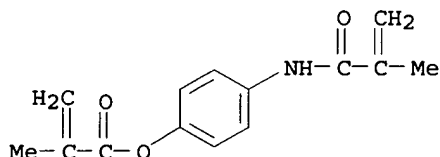
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and
4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate
(9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

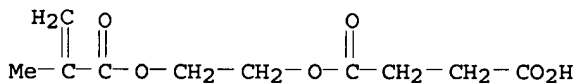
CMF C14 H15 N O3



CM 2

CRN 20882-04-6

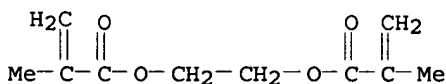
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F007-00

ICS G03F007-004; G03F007-033; G03F007-11

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
Other Reprographic Processes)
Section cross-reference(s): 38

IT 658705-94-3

RL: TEM (Technical or engineered material use); USES (Uses)

(binder for photosensitive layer; IR laser-sensitive neg. working presensitized lithog. plate with suppressed formation of ablation)

L53 ANSWER 17 OF 27 HCAPLUS COPYRIGHT/2006 ACS on STN

2004:739299 Document No. 141:251470 Photosensitive compositions for negative-working presensitized lithographic plates with high sensitivity for IR laser direct imaging. Goto, Takahiro (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004252288 A2 20040909, 49 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-44094 20030221.

AB The compns. comprise IR absorbers, sulfonium salt polymerization catalysts, polymerizable compds., binder polymers, and compds. chosen from activated halogen compds., oxime ester compds., and borate compds. The presensitized lithog. plates have (a) photosensitive layers containing the compns., and (b) protective layers on supports in this order. The plates show good storage stability, and give lithog. plates with good printing durability.

IT 658705-94-3

RL: TEM (Technical or engineered material use); USES (Uses)

(binder polymer in photosensitive layer; photosensitive compns. containing activated halogen compds., oxime ester compds., and/or borate compds for neg.-working presensitized lithog. plates)

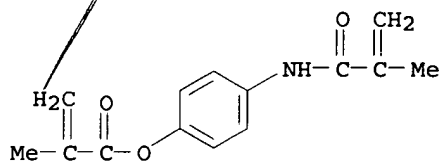
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

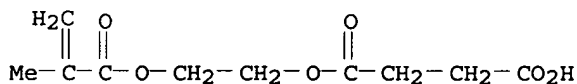
CMF C14 H15 N O3



CM 2

CRN 20882-04-6

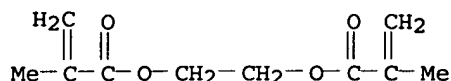
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F007-033
ICS C08F020-28; C08F020-36; G03F007-00; G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

IT 658705-94-3
RL: TEM (Technical or engineered material use); USES (Uses)
(binder polymer in photosensitive layer; photosensitive compns. containing activated halogen compds., oxime ester compds., and/or borate compds for neg.-working presensitized lithog. plates)

L53 ANSWER 18 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN
2004:739265 Document No. 141:251464 Photosensitive lithographic plate obtained by using laser-sensitive photopolymerizable layer. Shiraishi, Yuichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004252079 A2 20040909, 31 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-41467/20030219.

AB The plate is made of (a) an intermediate layer containing an alkaline aqueous solution-soluble compound involving unsatd. double bond on side chains and (b) a photopolymerizable layer, which are formed in this order on a hydrophilic surface layer of a support. An image can be drawn by laser beam irradiation on the material in computer-to plate process, which provides the lithog. plate giving printed images without fog on nonimage area.

IT 658705-94-3
RL: TEM (Technical or engineered material use); USES (Uses)
(alkaline aqueous solution-soluble intermediate layer; in photosensitive lithog. plate using laser-sensitive photopolymerizable layer)

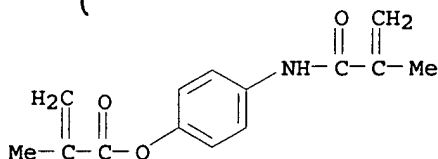
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

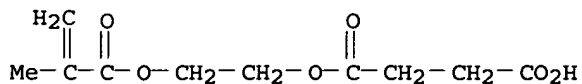
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CM 2

CRN 20882-04-6

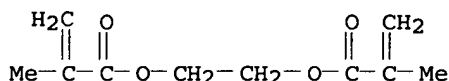
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F007-11

ICS G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT 50583-46-5 90216-38-9 135706-48-8 227098-91-1 401902-00-9

401902-40-7 632335-76-3 632335-80-9 658705-94-3

732303-43-4 752258-35-8 752258-36-9 752258-39-2

752258-40-5 752258-41-6 752258-42-7

RL: TEM (Technical or engineered material use); USES (Uses)

(alkaline aqueous solution-soluble intermediate layer; in photosensitive lithog. plate using laser-sensitive photopolymerizable layer)

L53 ANSWER 19 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:700331 Document No. 141:215689 Planographic printing plate

precursor. Goto, Takahiro (Fuji Photo Film Co., Ltd., Japan).

Eur. Pat. Appl. EP 1450207 A1 20040825, 62 pp. DESIGNATED STATES:

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC,

PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK.

(English). CODEN: EPXXDW. APPLICATION: EP 2004-3611 20040218.

PRIORITY: JP 2003-43085 20030220.

AB A planog. printing plate precursor includes: a substrate; a photosensitive layer containing an IR absorber, a polymerization initiator, a polymerizable compound and a binder polymer; and a protective layer containing a UV absorber, disposed in this order. The photosensitive layer exhibits reduction in solubility in an alkaline developing solution upon being exposed to light having a wavelength of 750-1400 nm.

IT 658705-94-3

RL: TEM (Technical or engineered material use); USES (Uses)

(binder; planog. printing plate precursor containing)

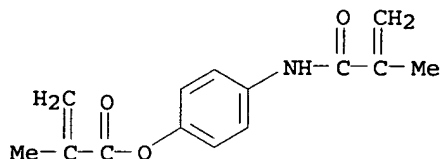
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)aminophenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

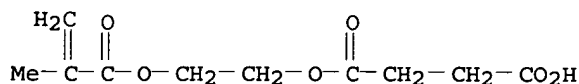
CMF C14 H15 N O3



CM 2

CRN 20882-04-6

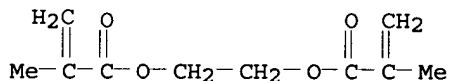
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F007-09

ICS B41M005-36; B41C001-10

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT 25035-81-8, Methyl methacrylate-methacrylic acid-styrene copolymer 658705-94-3

RL: TEM (Technical or engineered material use); USES (Uses)
(binder; planog. printing plate precursor containing)

L53 ANSWER 20 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:700263 Document No. 141:215686 Photosensitive composition and planographic printing plate precursor using the same. Goto, Takahiro (Fuji Photo Film Co., Ltd., Japan). Eur. Pat. Appl. EP 1449653 A2 20040825, 55 pp. DESIGNATED STATES: R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK. (English). CODEN: EPXXDW. APPLICATION: EP 2004-3846 20040220. PRIORITY: JP 2003-44090 20030221.

AB The present invention provides a photosensitive composition including an IR absorbing agent, a sulfonium salt polymerization initiator, a polymerizable compound, a binder polymer and a compound having a weight average mol. weight of 3000 or less and having at least one carboxylic acid group, as well as a planog. printing plate precursor containing the photosensitive composition in a photosensitive layer on a substrate.

IT 658705-94-3

RL: TEM (Technical or engineered material use); USES (Uses)
(binder; photosensitive composition for planog. printing plate

precursor)

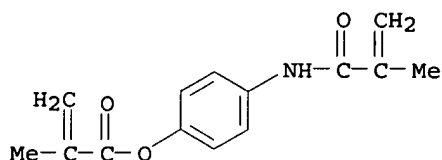
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and
 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate
 (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

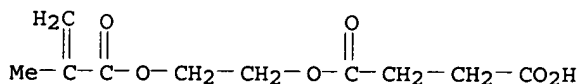
CMF C14 H15 N O3



CM 2

CRN 20882-04-6

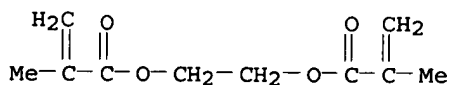
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM B41C001-10

ICS G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)

Section cross-reference(s): 38

IT 152048-40-3 658705-94-3

RL: TEM (Technical or engineered material use); USES (Uses)
 (binder; photosensitive composition for planog. printing plate
 precursor)

L53 ANSWER 21 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:700260 Document No. 141:215684 Photosensitive composition and
 planographic printing plate precursor using the same. Goto,
 Takahiro (Fuji Photo Film Co., Ltd., Japan). Eur. Pat. Appl. EP
 1449650 A2 20040825, 58 pp. DESIGNATED STATES: R: AT, BE, CH,
 DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT,
 LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK. (English).

CODEN: EPXXDW. APPLICATION: EP 2004-3843 20040220. PRIORITY: JP 2003-44091 20030221.

AB The present invention provides a photosensitive composition including an IR absorbing agent, a sulfonium salt polymerization initiator, a polymerizable compound having a urethane skeleton and a binder polymer, as well as a planog. printing plate precursor containing the photosensitive composition in a photosensitive layer on a substrate.

IT 658705-94-3

RL: CAT (Catalyst use); USES (Uses)

(binder; photosensitive composition for planog. printing plate precursor containing)

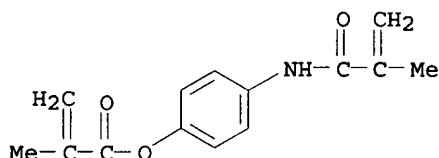
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

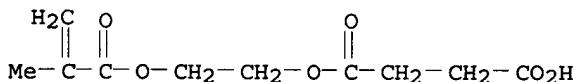
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CM 2

CRN 20882-04-6

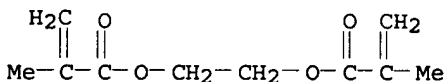
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CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM B41C001-10

ICS G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

IT 658705-94-3

RL: CAT (Catalyst use); USES (Uses)

(binder; photosensitive composition for planog. printing plate precursor containing)

L53 ANSWER 22 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:632378 Document No. 141:181994 Negative-working presensitized lithographic plates for direct laser platemaking, and their platemaking. Kondo, Shunichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004219667 A2 20040805 34 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2003-6332 20030114.

AB The lithog. plate comprises, an aluminum support, a photopolymerizable photosensitive layer, and an oxygen-shielding layer, wherein the photosensitive layer contain an aqueous-alkali-solution-soluble polymers bearing ethylenic unsatd. groups on side chains and having acid values of 0.7-2.0 and glass transition point of $\leq 120^\circ$, a photopolymn. initiator, and an ethylenic monomer. The plate is imagewise exposed to light, heated at $50-140^\circ$ for increasing in sensitivity, and then developed with aqueous alkali solution developers. The presensitized lithog. plate shows high sensitivity and storage stability and provides high discriminating patterns without remaining developing residues.

IT 676349-36-3

RL: TEM (Technical or engineered material use); USES (Uses) (binders, in photoimaging layers; (direct laser) platemaking on neg.-working presensitized lithog. plates having photoimaging layer containing alkali-soluble polymer binders)

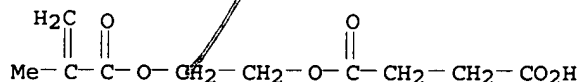
RN 676349-36-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

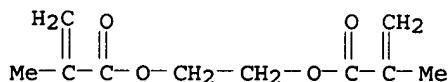
CMF C10 H14 O6



CM 2

CRN 97-90-5

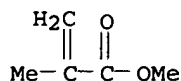
CMF C10 H14 O4



CM 3

CRN 80-62-6

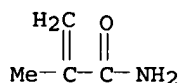
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



IC ICM G03F007-00

ICS G03F007-038; G03F007-11; G03F007-38

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT 676349-36-3 681127-05-9 732303-43-4 732303-46-7

732303-47-8 732303-48-9 732303-49-0 732303-50-3

732303-51-4 732303-52-5

RL: TEM (Technical or engineered material use); USES (Uses)
 (binders, in photoimaging layers; (direct laser) platemaking on
 neg.-working presensitized lithog. plates having photoimaging
 layer containing alkali-soluble polymer binders)

L53 ANSWER 23 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:510155 Document No. 141:62133 Polymerizable composition and
 lithographic printing plate precursor. Shimada, Kazuto (Fuji
 Photo Film Co., Ltd., Japan). Eur. Pat. Appl. EP 1431032 A1

20040623, 73 pp. DESIGNATED STATES: R: AT, BE, CH, DE, DK, ES,
 FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO,
 MK, CY, AL, TR, BG, CZ, EE, HU, SK. (English). CODEN: EPXXDW.
 APPLICATION: EP 2003-29206/20031218. PRIORITY: JP 2002-366539
 20021218; JP 2003-202951/20030729.

AB The present invention relates to polymerizable composition for lithog.
 printing plate precursor containing: (A) a binder polymer; (B) a
 compound having a polymerizable unsatd. group; and (C) a compound
 which has a triarylsulfonium salt structure and in which a sum of
 Hammett's consts. of all substituents bonded to the aryl skeleton
 is larger than 0.46.

IT 658705-94-3

RL: PRP (Properties); TEM (Technical or engineered material use);
 USES (Uses)

(binder; polymerizable composition for lithog. printing plate
 precursor containing)

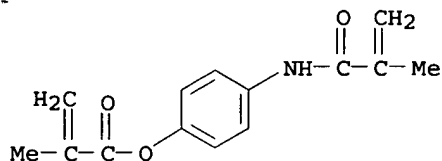
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and
 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate
 (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

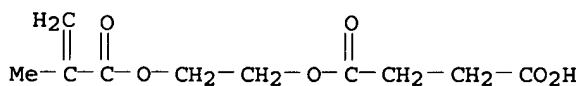
CMF C14 H15 N O3



CM 2

CRN 20882-04-6

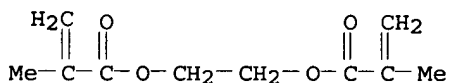
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM B41C001-10

ICS B41M005-40; G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT 134490-11-2 658705-94-3 709037-25-2 709037-26-3

RL: PRP (Properties); TEM (Technical or engineered material use);

USES (Uses)

(binder; polymerizable composition for lithog. printing plate precursor containing)

L53 ANSWER 24 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2004:260988 Document No. 140:312029 Polymerizable composition and

planographic printing plate precursor. Sugasaki, Atsushi;

Kunita, Kazuto; Fujimaki, Kazuhiro (Fuji Photo Film Co., Ltd.,

Japan). Eur. Pat. Appl. EP 1403043 A2 20040331, 113 pp.

DESIGNATED STATES: R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI,

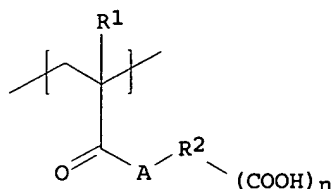
LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG,

CZ, EE, HU, SK. (English). CODEN: EPXXDW. APPLICATION: EP

2003-22142 20030930. PRIORITY: JP 2002-287920 20020930; JP

2003-38288 20030217; JP 2003-100575 20030403.

GI



I

AB The present invention provides a **planog.** printing plate precursor including on a support a photosensitive layer that contains a polymerizable composition containing a specific binder polymer having a repeating unit of formula I (R1 = H, Me; R2 = linking group which includes two or more atoms selected from carbon atom, hydrogen, oxygen, nitrogen, sulfur and has a number of atoms of 2-82; A = O, -NR3-, R3 = H, monovalent C1-10-hydrocarbon; n = 1-5), an **IR absorbent**, a polymerization initiator and a polymerizable compound. The invention also provides a **planog.** printing plate precursor provided with a specific photosensitive layer with respect to an alkaline developer. The object of the present invention is to provide a **planog.** printing plate precursor that is excellent in printing durability and image formation, as well as to provide a polymerizable composition that is suitably used for a photosensitive layer of the **planog.** printing plate precursor.

IT 658705-94-3 676349-35-2 676349-36-3
 676349-37-4 676349-39-6 676349-41-0
 676349-42-1 676349-43-2 676349-45-4
 676349-47-6 676349-48-7 676349-51-2
 676349-52-3 676349-54-5 676349-56-7
 676349-57-8 676349-58-9 676349-59-0
 676349-60-3 676349-61-4 676349-62-5
 676349-63-6 676349-64-7 676349-65-8
 676349-66-9 676349-67-0 676349-69-2
 676349-70-5 676349-72-7

RL: PRP (Properties); TEM (Technical or engineered material use);
 USES (Uses)

(polymerizable composition and **planog.** printing plate precursor)

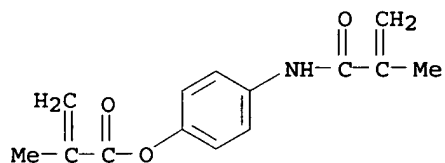
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 86229-45-0

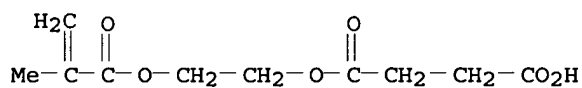
CMF C14 H15 N O3



CM 2

CRN 20882-04-6

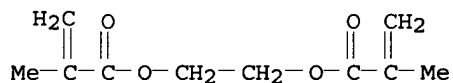
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



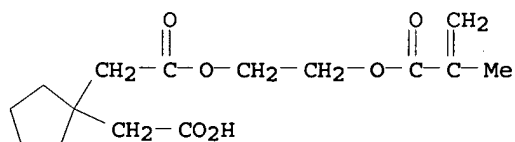
RN 676349-35-2 HCAPLUS

CN 1,1-Cyclopentanediyl diacetic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 393546-18-4

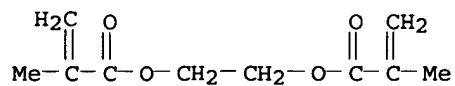
CMF C15 H22 O6



CM 2

CRN 97-90-5

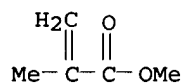
CMF C10 H14 O4



CM 3

CRN 80-62-6

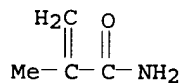
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



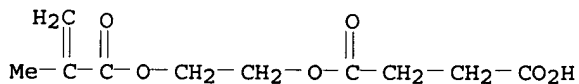
RN 676349-36-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate),
 methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA
 INDEX NAME)

CM 1

CRN 20882-04-6

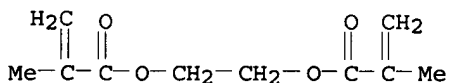
CMF C10 H14 O6



CM 2

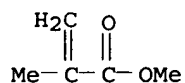
CRN 97-90-5

CMF C10 H14 O4



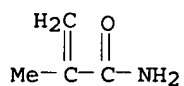
CM 3

CRN 80-62-6
CMF C5 H8 O2



CM 4

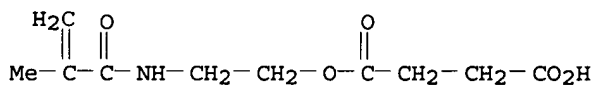
CRN 79-39-0
CMF C4 H7 N O



RN 676349-37-4 HCAPLUS
CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)amino]ethyl]
ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate),
methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA
INDEX NAME)

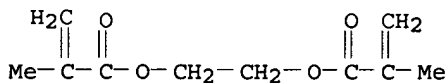
CM 1

CRN 86126-56-9
CMF C10 H15 N O5



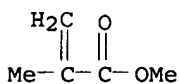
CM 2

CRN 97-90-5
CMF C10 H14 O4

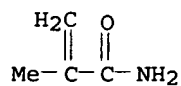


CM 3

CRN 80-62-6
CMF C5 H8 O2

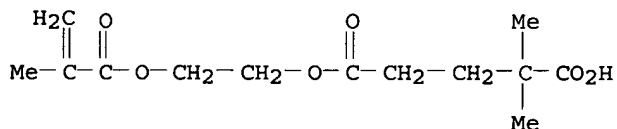


CM 4

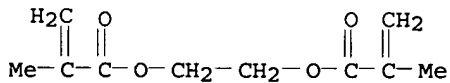
CRN 79-39-0
CMF C4 H7 N O

RN 676349-39-6 HCAPLUS
 CN Pentanedioic acid, 2,2-dimethyl-, 5-[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

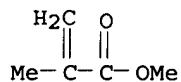
CM 1

CRN 676349-38-5
CMF C13 H20 O6

CM 2

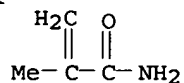
CRN 97-90-5
CMF C10 H14 O4

CM 3

CRN 80-62-6
CMF C5 H8 O2

CM 4

CRN 79-39-0
CMF C4 H7 N O



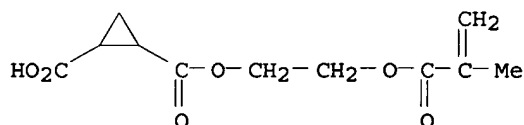
RN 676349-41-0 HCAPLUS

CN 1,2-Cyclopropanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 676349-40-9

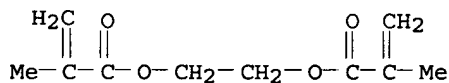
CMF C11 H14 O6



CM 2

CRN 97-90-5

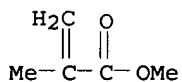
CMF C10 H14 O4



CM 3

CRN 80-62-6

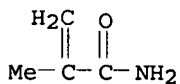
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



RN 676349-42-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1,2-ethanediyl ester, polymer with

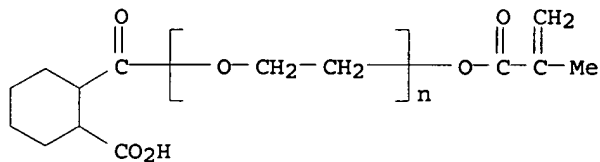
α -[(2-carboxycyclohexyl)carbonyl]- ω -[(2-methyl-1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 237073-56-2

CMF (C2 H4 O)_n C12 H16 O5

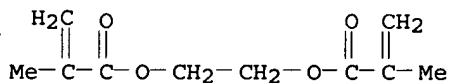
CCI PMS



CM 2

CRN 97-90-5

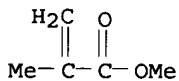
CMF C10 H14 O4



CM 3

CRN 80-62-6

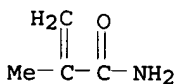
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O

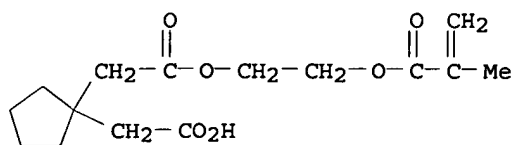


RN 676349-43-2 HCAPLUS

CN 1,1-Cyclopentanediadicetic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)aminol]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

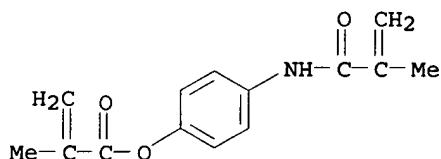
CM 1

CRN 393546-18-4
CMF C15 H22 O6



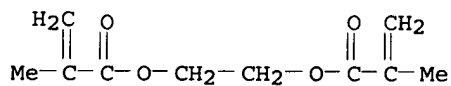
CM 2

CRN 86229-45-0
CMF C14 H15 N O3



CM 3

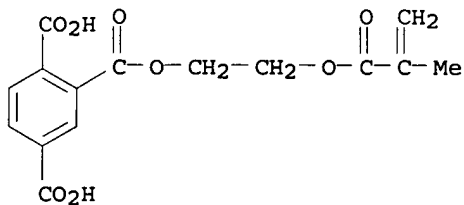
CRN 97-90-5
CMF C10 H14 O4



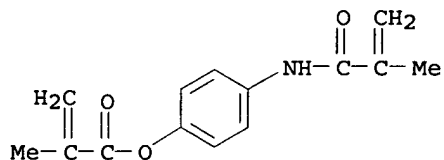
RN 676349-45-4 HCAPLUS
CN 1,2,4-Benzenetricarboxylic acid, 2-[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

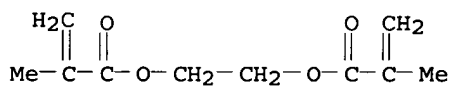
CRN 676349-44-3
CMF C15 H14 O8



CM 2

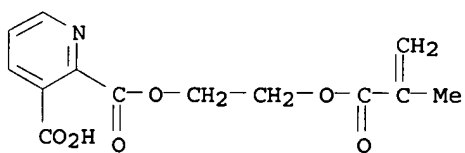
CRN 86229-45-0
CMF C14 H15 N O3

CM 3

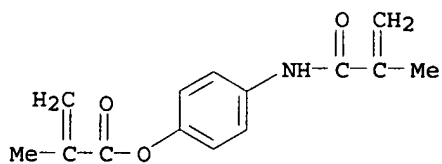
CRN 97-90-5
CMF C10 H14 O4

RN 676349-47-6 HCAPLUS
CN 2,3-Pyridinedicarboxylic acid, 2-[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

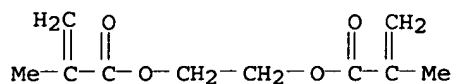
CM 1

CRN 676349-46-5
CMF C13 H13 N O6

CM 2

CRN 86229-45-0
CMF C14 H15 N O3

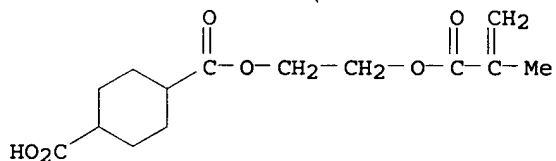
CM 3

CRN 97-90-5
CMF C10 H14 O4

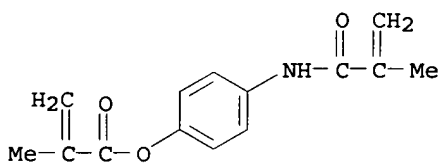
RN 676349-48-7 HCAPLUS

CN 1,4-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate and 2-methyl-2-propenoic acid (9CI) (CA INDEX NAME)

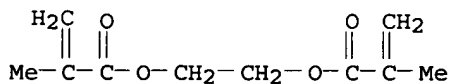
CM 1

CRN 123431-02-7
CMF C14 H20 O6

CM 2

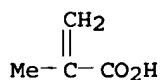
CRN 86229-45-0
CMF C14 H15 N O3

CM 3

CRN 97-90-5
CMF C10 H14 O4

CM 4

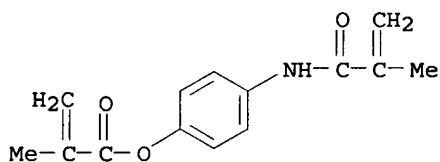
CRN 79-41-4
CMF C4 H6 O2



RN 676349-51-2 HCAPLUS
CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)amino]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

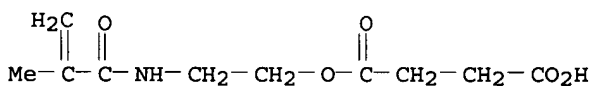
CM 1

CRN 86229-45-0
CMF C14 H15 N O3



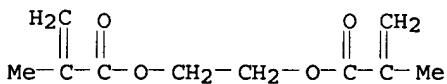
CM 2

CRN 86126-56-9
CMF C10 H15 N O5



CM 3

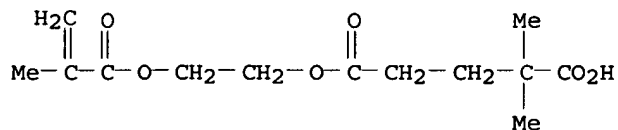
CRN 97-90-5
CMF C10 H14 O4



RN 676349-52-3 HCAPLUS
CN Pentanedioic acid, 2,2-dimethyl-, 5-[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

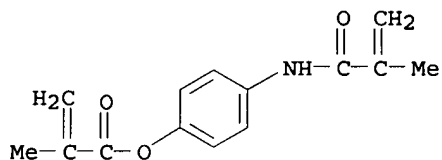
CM 1

CRN 676349-38-5
CMF C13 H20 O6



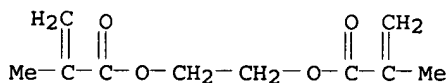
CM 2

CRN 86229-45-0
CMF C14 H15 N O3



CM 3

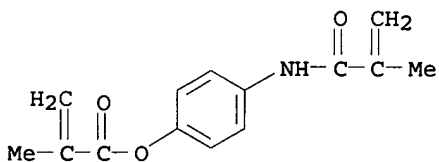
CRN 97-90-5
CMF C10 H14 O4



RN 676349-54-5 HCAPLUS
CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

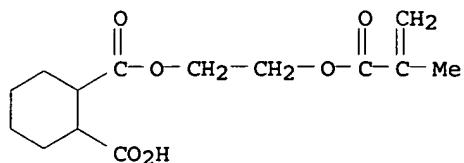
CRN 86229-45-0
CMF C14 H15 N O3



CM 2

CRN 51252-88-1

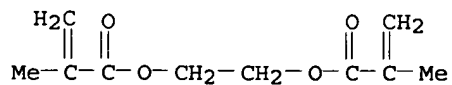
CMF C14 H20 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



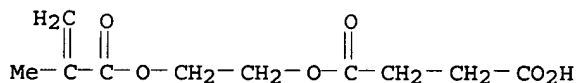
RN 676349-56-7 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and
 N-(4-methoxyphenyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

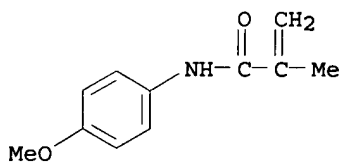
CMF C10 H14 O6



CM 2

CRN 7274-71-7

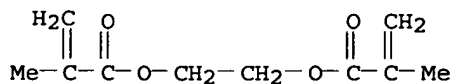
CMF C11 H13 N O2



CM 3

CRN 97-90-5

CMF C10 H14 O4



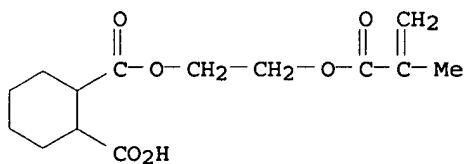
RN 676349-57-8 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and N-(4-methoxyphenyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 51252-88-1

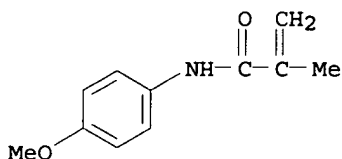
CMF C14 H20 O6



CM 2

CRN 7274-71-7

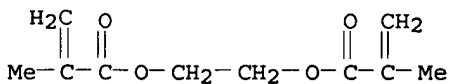
CMF C11 H13 N O2



CM 3

CRN 97-90-5

CMF C10 H14 O4



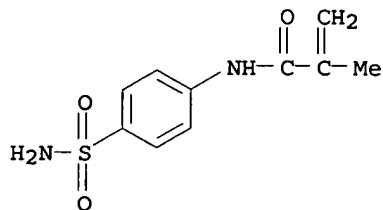
RN 676349-58-9 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-[4-(aminosulfonyl)phenyl]-2-methyl-2-propenamide and 1,2-ethanediyl bis(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

CRN 56992-87-1

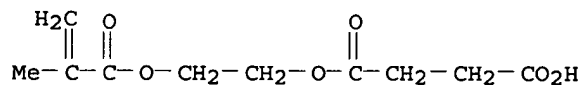
CMF C10 H12 N2 O3 S



CM 2

CRN 20882-04-6

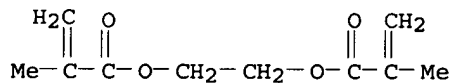
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



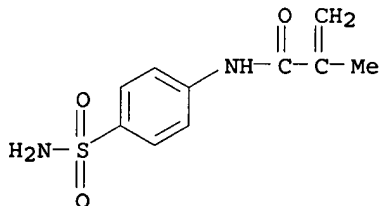
RN 676349-59-0 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-[4-(aminosulfonyl)phenyl]-2-methyl-2-propenamide and 1,2-ethanediyl bis(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

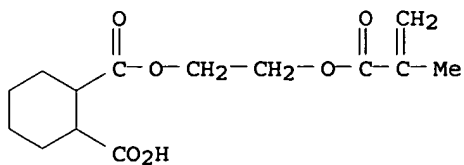
CRN 56992-87-1

CMF C10 H12 N2 O3 S



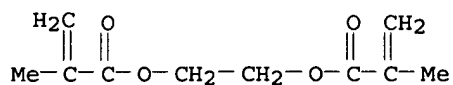
CM 2

CRN 51252-88-1
CMF C14 H20 O6



CM 3

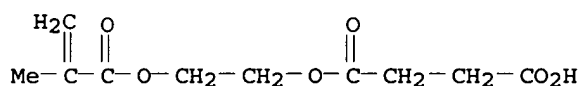
CRN 97-90-5
CMF C10 H14 O4



RN 676349-60-3 HCAPLUS
CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), N-(4-methoxyphenyl)-2-methyl-2-propenamide and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

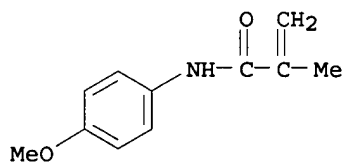
CM 1

CRN 20882-04-6
CMF C10 H14 O6



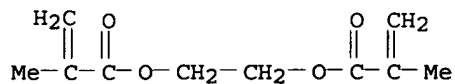
CM 2

CRN 7274-71-7
CMF C11 H13 N O2



CM 3

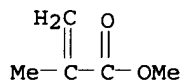
CRN 97-90-5
CMF C10 H14 O4



CM 4

CRN 80-62-6

CMF C5 H8 O2



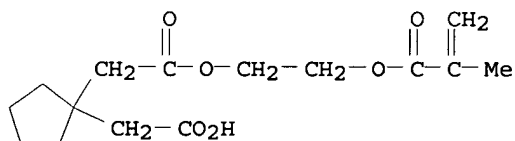
RN 676349-61-4 HCAPLUS

CN 1,1-Cyclopentanediacetic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2-propenamide and 2-propenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 393546-18-4

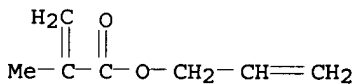
CMF C15 H22 O6



CM 2

CRN 96-05-9

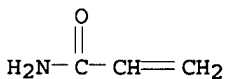
CMF C7 H10 O2



CM 3

CRN 79-06-1

CMF C3 H5 N O



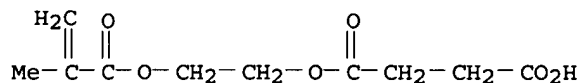
RN 676349-62-5 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-methyl-2-propenamide and 2-(2-propenyloxy)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

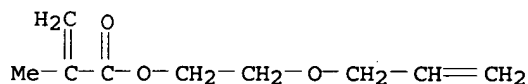
CMF C10 H14 O6



CM 2

CRN 16839-48-8

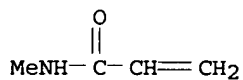
CMF C9 H14 O3



CM 3

CRN 1187-59-3

CMF C4 H7 N O



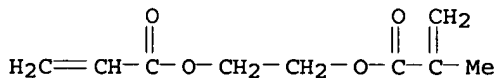
RN 676349-63-6 HCAPLUS

CN Butanedioic acid, mono[2-[(1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N,N-dimethyl-2-propenamide and 2-[(1-oxo-2-propenyl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 69040-48-8

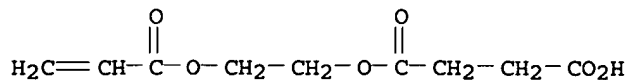
CMF C9 H12 O4



CM 2

CRN 50940-49-3

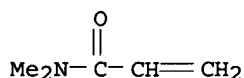
CMF C9 H12 O6



CM 3

CRN 2680-03-7

CMF C5 H9 N O



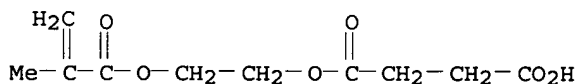
RN 676349-64-7 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with N-(1-methylethyl)-2-propenamide and 2-propenyl
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

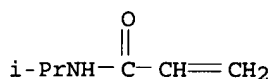
CMF C10 H14 O6



CM 2

CRN 2210-25-5

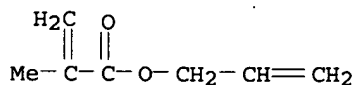
CMF C6 H11 N O



CM 3

CRN 96-05-9

CMF C7 H10 O2



RN 676349-65-8 HCAPLUS

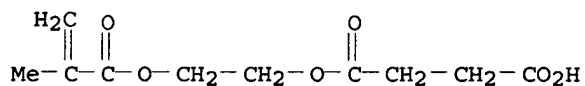
CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with 2-methyl-N-(1-methylethyl)-2-propenamide and
 2-(2-propenyloxy)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX

NAME)

CM 1

CRN 20882-04-6

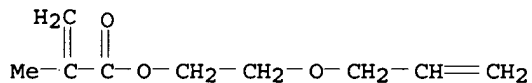
CMF C10 H14 O6



CM 2

CRN 16839-48-8

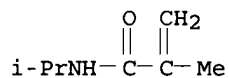
CMF C9 H14 O3



CM 3

CRN 13749-61-6

CMF C7 H13 N O



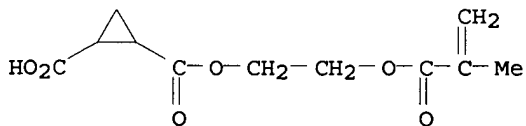
RN 676349-66-9 HCAPLUS

CN 1,2-Cyclopropanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-cyclohexyl-2-propenamide and 2-[(1-oxo-2-propenyl)amino]ethyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

CM 1

CRN 676349-40-9

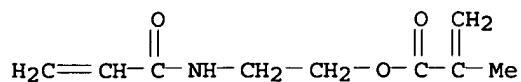
CMF C11 H14 O6



CM 2

CRN 56148-24-4

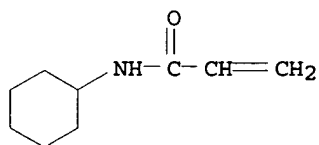
CMF C9 H13 N O3



CM 3

CRN 3066-72-6

CMF C9 H15 N O



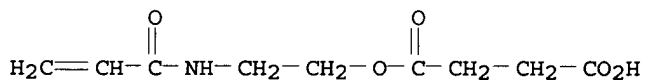
RN 676349-67-0 HCAPLUS

CN Butanedioic acid, mono[2-[(1-oxo-2-propenyl)amino]ethyl] ester,
polymer with 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 3-butenate
and N-(phenylmethyl)-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 159349-94-7

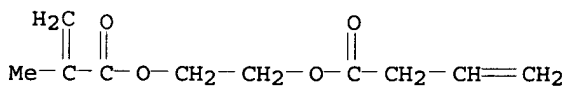
CMF C9 H13 N O5



CM 2

CRN 127584-57-0

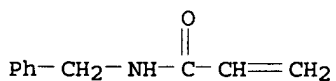
CMF C10 H14 O4



CM 3

CRN 13304-62-6

CMF C10 H11 N O



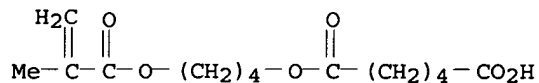
RN 676349-69-2 HCAPLUS

CN Hexanedioic acid, mono[4-[(2-methyl-1-oxo-2-propenyl)oxy]butyl] ester, polymer with N-phenyl-2-propenamide and 2-propenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 676349-68-1

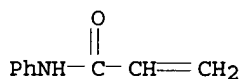
CMF C14 H22 O6



CM 2

CRN 2210-24-4

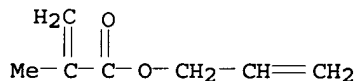
CMF C9 H9 N O



CM 3

CRN 96-05-9

CMF C7 H10 O2



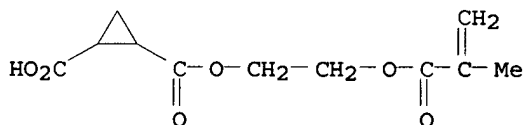
RN 676349-70-5 HCAPLUS

CN 1,2-Cyclopropanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N,N-di-2-propenyl-2-propenamide and 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 3-butenate (9CI) (CA INDEX NAME)

CM 1

CRN 676349-40-9

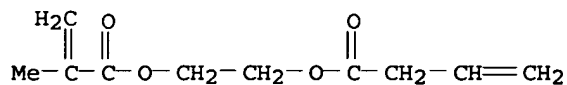
CMF C11 H14 O6



CM 2

CRN 127584-57-0

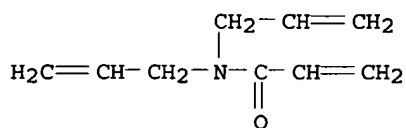
CMF C10 H14 O4



CM 3

CRN 3085-68-5

CMF C9 H13 N O



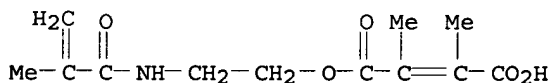
RN 676349-72-7 HCAPLUS

CN 2-Butenedioic acid, 2,3-dimethyl-, mono[2-[(2-methyl-1-oxo-2-propenyl)amino]ethyl] ester, polymer with N-cyclopentyl-2-propenamide and 2-[(1-oxo-2-propenyl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 676349-71-6

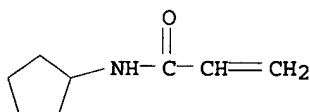
CMF C12 H17 N O5



CM 2

CRN 188026-02-0

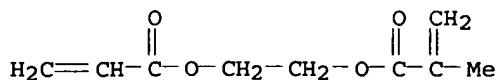
CMF C8 H13 N O



CM 3

CRN 69040-48-8

CMF C9 H12 O4



IC ICM B41C001-10
ICS G03F007-033

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST polymerizable compn **planog** printing plate precursor

IT Printing plates
(**planog.**; polymerizable composition and **planog.** printing plate precursor)

IT 658705-94-3 676349-35-2 676349-36-3
676349-37-4 676349-39-6 676349-41-0
676349-42-1 676349-43-2 676349-45-4
676349-47-6 676349-48-7 676349-51-2
676349-52-3 676349-54-5 676349-56-7
676349-57-8 676349-58-9 676349-59-0
676349-60-3 676349-61-4 676349-62-5
676349-63-6 676349-64-7 676349-65-8
676349-66-9 676349-67-0 676349-69-2
676349-70-5 676349-72-7
RL: PRP (Properties); TEM (Technical or engineered material use);
USES (Uses)
(polymerizable composition and **planog.** printing plate precursor)

IT 24504-22-1 120307-06-4 127820-39-7 253585-83-0 377780-83-1
676349-74-9 676349-76-1 676349-77-2 676349-78-3
676349-79-4 676349-80-7
RL: CAT (Catalyst use); USES (Uses)
(polymerization initiator; polymerizable composition and **planog.** printing plate precursor)

L53 ANSWER 25 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN
2004:136476 Document No. 140:190012 Thermosensitive/ photosensitive resin composition. Fujimaki, Kazuhiro (Fuji Photo Film Co., Ltd., Japan). Eur. Pat. Appl. EP 1389521 A2 20040218, 133 pp.
DESIGNATED STATES: R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK. (English). CODEN: EPXXDW. APPLICATION: EP 2003-17680 20030814. PRIORITY: JP 2002-237509 20020816; JP 2002-275439 20020920.

AB The present invention provides a resin composition that includes (A) a polymer compound that has, on a side chain of a main chain polymer, through a linkage group containing a hydrogen-bonding group and a ring structure, a terminal ethylenic unsatd. bond, and is soluble or swelling in water or an alkali aqueous solution, and (B) a compound that generates radicals when exposed to light or heat. The invention further provides a thermosensitive and/or photosensitive composition that includes (A') a polymer compound that has a non-acidic hydrogen-bonding group on a side chain and is soluble or swelling in water or an alkali aqueous solution, and (B') a compound that generates radicals when exposed to light or heat.

IT 658705-94-3
RL: PRP (Properties); TEM (Technical or engineered material use);
USES (Uses)
(thermosensitive photosensitive resin composition for **planog.** printing plate containing)

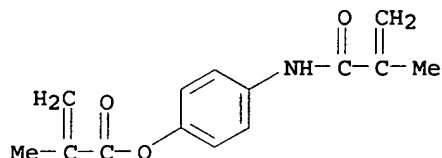
RN 658705-94-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]

ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 4-[(2-methyl-1-oxo-2-propenyl)amino]phenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

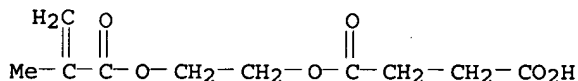
CM 1

CRN 86229-45-0
CMF C14 H15 N O3



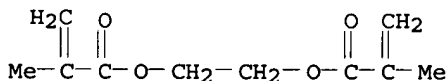
CM 2

CRN 20882-04-6
CMF C10 H14 O6



CM 3

CRN 97-90-5
CMF C10 H14 O4



IC ICM B41C001-10

ICS B41M005-36; G03F007-033

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 35, 38

IT 658705-81-8 658705-83-0 658705-85-2 658705-87-4
658705-89-6 658705-90-9 658705-91-0 658705-93-2
658705-94-3 658705-95-4 658705-96-5 658705-97-6
658705-98-7 658705-99-8 658706-00-4 658706-01-5
658706-03-7 658706-05-9 658706-06-0 658706-08-2
658706-09-3

RL: PRP (Properties); TEM (Technical or engineered material use);
USES (Uses)

(thermosensitive photosensitive resin composition for planographic printing plate containing)

L53 ANSWER 26 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN

2003:723567 Document No. 139:237767 Manufacture of negatively lithographic printing original plates. Aoshima, Keitaro (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP

2003260881 A2 20030916, 24 pp. (Japanese). CODEN: JKXXAF.
APPLICATION: JP 2002-62219 20020307.

AB In manufacture of the plates by formation of recording layers giving hydrophobic regions by exposure to IR laser light, the plates are cut by using cutting slitters having interval of upper edges and lower edges 0-30 μ m. The plates show good crack resistance in cutting and no stains at edge parts.

IT 595585-09-4P, 2-Hydroxyethyl methacrylate-methacrylic acid-N-(p-sulfamoylphenyl)methacrylamide copolymer carbamate with 2-methacryloyloxyethyl isocyanate
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(recording layers; cutting in manufacture of IR laser-sensitive neg. lithog. original plates with good edge-stain resistance)

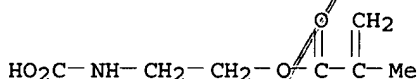
RN 595585-09-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with N-[4-(aminosulfonyl)phenyl]-2-methyl-2-propenamide and 2-hydroxyethyl 2-methyl-2-propenoate, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

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CRN 96571-20-9

CMF C7 H11 N O4



CM 2

CRN 446036-51-7

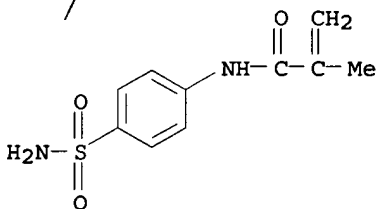
CMF (C10 H12 N2 O3 S . C6 H10 O3 . C4 H6 O2)x

CCI PMS

CM 3

CRN 56992-87-1

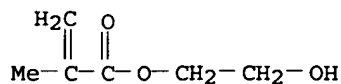
CMF C10 H12 N2 O3 S



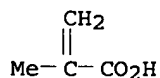
CM 4

CRN 868-77-9

CMF C6 H10 O3



CM 5

CRN 79-41-4
CMF C4 H6 O2

IC ICM B41N001-08
ICS B23D019-06; G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 134127-48-3 182749-66-2 197087-00-6 221661-30-9
RL: TEM (Technical or engineered material use); USES (Uses)
(IR absorbers in recording layers; cutting in manufacture of IR laser-sensitive neg. lithog. original plates with good edge-stain resistance)

IT 595585-09-4P, 2-Hydroxyethyl methacrylate-methacrylic acid-N-(p-sulfamoylphenyl)methacrylamide copolymer carbamate with 2-methacryloyloxyethyl isocyanate
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(recording layers; cutting in manufacture of IR laser-sensitive neg. lithog. original plates with good edge-stain resistance)

L53 ANSWER 27 OF 27 HCAPLUS COPYRIGHT 2006 ACS on STN
1993:581744 Document No. 119:181744 Study of acrylic adhesive surface behavior by FTIR-ATR. 2. Kawabe, Masayoshi (Nitto Denko Co., Ltd., Toyohashi, 441-31, Japan), Nippon Setchaku Gakkaishi, 29(8), 361-5 (Japanese) 1993. CODEN: NSEGE7. ISSN: 0916-4812.

AB Following the recent success in surface and interface evaluation technol. by FTIR attenuated total reflection and FTIR absorption spectroscopy applied to an acrylic polymer with many carboxyl groups to detect carbonyl group depth-profile, the functional group orientation was analyzed. The surface layer was rich with more ester group than carboxyl group, and at the air interface, depth-profile of carboxyl group was changed. The carboxyl group penetrated into the adhesive layer.

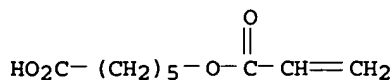
IT 131954-12-6
RL: PRP (Properties)
(adhesives, surface anal. of, Fourier transform IR method for)

RN 131954-12-6 HCAPLUS

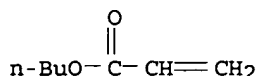
CN Hexanoic acid, 6-[(1-oxo-2-propenyl)oxy]-, polymer with butyl 2-propenoate and 2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

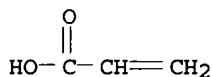
CRN 93365-33-4
CMF C9 H14 O4



CM 2

CRN 141-32-2
CMF C7 H12 O2

CM 3

CRN 79-10-7
CMF C3 H4 O2

CC 36-5 (Physical Properties of Synthetic High Polymers)
 Section cross-reference(s): 38, 80
 ST acrylic adhesive surface behavior analysis; Fourier transform IR
 analysis adhesive; **IR absorption** analysis
 acrylic adhesive; carboxyl depth profile acrylic adhesive;
 caprolactone acrylate copolymer adhesive analysis; butyl acrylate
 copolymer adhesive analysis
 IT 131954-12-6
 RL: PRP (Properties)
 (adhesives, surface anal. of, Fourier transform IR method for)

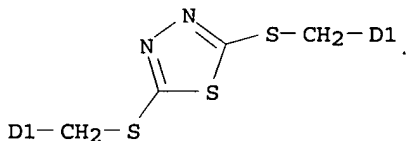
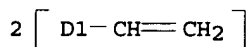
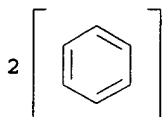
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L55 ANSWER 1 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 2005:1023833 Document No. 143:315485 Polymerizable compositions with
 high sensitivity and good storage stability, and their image
 recording materials useful for presensitized lithographic plates.
 Kunita, Kazuto (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai
 Tokkyo Koho JP 2005257955 A2 20050922, 108 pp. (Japanese).
 CODEN: JKXXAF. APPLICATION: JP 2004-68180 20040310.
 AB The compns. contain radically crosslinkable alkali-soluble polymers
 having styrene groups and alkali-soluble groups in side chains, and
 Tg ≥60°. The image recording materials are useful
 for computer to plate (CTP) systems, and give lithog.
 plates with good printing durability.
 IT 864742-13-2
 RL: TEM (Technical or engineered material use); USES (Uses)
 (binder polymer; polymerizable compns. containing
 binder polymers having styrene groups and alkali-soluble
 groups, and specific Tg useful for presensitized lithog.
 plates)

RN 864742-13-2 HCAPLUS
 CN 2-Propenoic acid, 2-carboxyethyl ester, polymer with
 2,5-bis[[(ethenylphenyl)methyl]thio]-1,3,4-thiadiazole and
 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

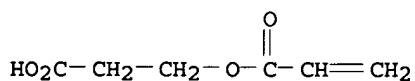
CM 1

CRN 462637-08-7
 CMF C20 H18 N2 S3
 CCI IDS



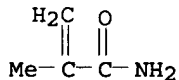
CM 2

CRN 24615-84-7
 CMF C6 H8 O4



CM 3

CRN 79-39-0
 CMF C4 H7 N O

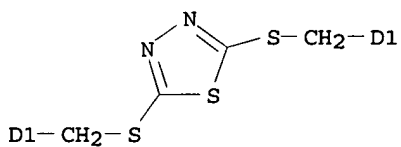
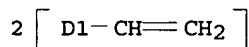
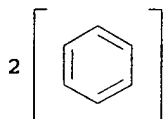


IT 864742-26-7P 864742-27-8P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered
 material use); PREP (Preparation); USES (Uses)
 (polymerizable compns. containing binder polymers having
 styrene groups and alkali-soluble groups, and specific Tg useful
 for presensitized lithog. plates)

RN 864742-26-7 HCAPLUS
 CN 2-Propenoic acid, 2,2-bis[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl ester, polymer with 2,5-bis[[(ethenylphenyl)methyl]thio]-1,3,4-thiadiazole, 2-carboxyethyl 2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

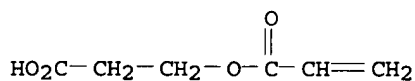
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CRN 462637-08-7
 CMF C20 H18 N2 S3
 CCI IDS



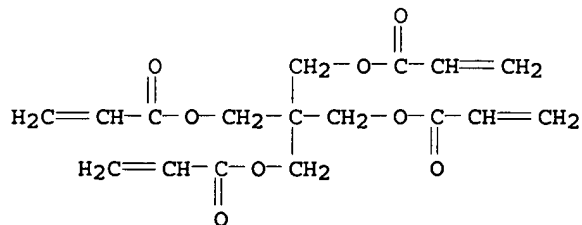
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CRN 24615-84-7
 CMF C6 H8 O4



CM 3

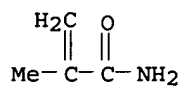
CRN 4986-89-4
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CM 4

CRN 79-39-0

CMF C4 H7 N O



RN 864742-27-8 HCAPLUS

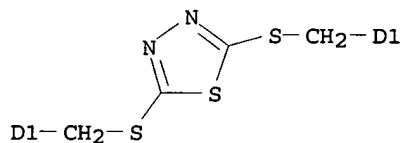
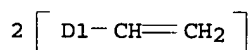
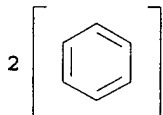
CN 2-Propenoic acid, 2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl ester, polymer with 2,5-bis[[[(ethenylphenyl)methyl]thio]-1,3,4-thiadiazole, 2-carboxyethyl 2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 462637-08-7

CMF C20 H18 N2 S3

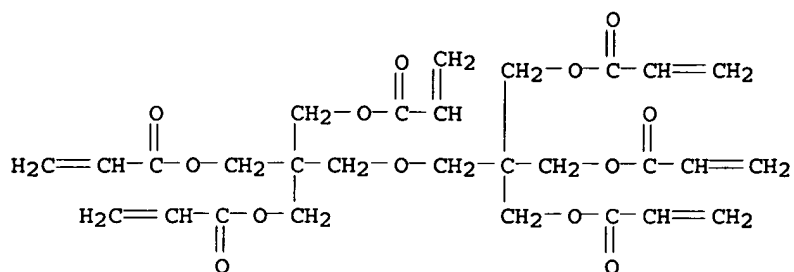
CCI IDS



CM 2

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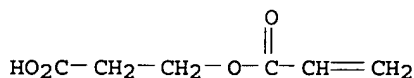
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CM 3

CRN 24615-84-7

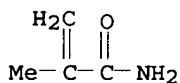
CMF C6 H8 O4



CM 4

CRN 79-39-0

CMF C4 H7 N O



IC ICM G03F007-038

ICS C08F290-12; G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38

IT Photoimaging materials

(photopolymerizable; polymerizable compns. containing **binder** polymers having styrene groups and alkali-soluble groups, and specific Tg useful for presensitized lithog. plates)

IT Lithographic plates

(presensitized; polymerizable compns. containing **binder** polymers having styrene groups and alkali-soluble groups, and specific Tg useful for presensitized lithog. plates)

IT 864739-16-2 864742-12-1 **864742-13-2** 864742-14-3
 864742-15-4 864742-16-5 864742-19-8 864742-21-2
 864742-22-3 864742-23-4 864952-92-1

RL: TEM (Technical or engineered material use); USES (Uses)
 (**binder** polymer; polymerizable compns. containing **binder** polymers having styrene groups and alkali-soluble groups, and specific Tg useful for presensitized lithog. plates)

IT 4986-89-4, Pentaerythritol tetraacrylate 29570-58-9 51248-94-3
 56361-55-8

RL: TEM (Technical or engineered material use); USES (Uses)
(monomer; polymerizable compns. containing **binder**
polymers having styrene groups and alkali-soluble groups, and
specific Tg useful for presensitized lithog. plates)

IT 864739-17-3P 864742-24-5P 864742-25-6P **864742-26-7P**
864742-27-8P 864742-28-9P 864742-29-0P 864742-30-3P
864742-31-4P 864742-32-5P 864742-33-6P 864742-34-7P
864952-93-2P

RL: IMF (Industrial manufacture); TEM (Technical or engineered
material use); PREP (Preparation); USES (Uses)
(polymerizable compns. containing **binder** polymers having
styrene groups and alkali-soluble groups, and specific Tg useful
for presensitized lithog. plates)

L55 ANSWER 2 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
2004:904098 Document No. 141:372824 Polymerizable compositions for
recording layers of negatively lithographic **printing**
original **plates**. Sugasaki, Atsushi; Kunita, Kazuto
(Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP
2004300315 A2 20041028, 94 pp. (Japanese). CODEN: JKXXAF.
APPLICATION: JP 2003-96224 20030331.

AB The compns. comprise (A) **binder** polymers showing glass
transition temperature <80° or having ≥2 allyl
group-containing side chains, (B) ethylenically unsatd. bond-containing
compds., and (C) radical polymerization initiators. The compns.
polymerizable by light or heat give recording layers with good
printability and high sensitivity for IR laser light.

IT **779351-43-8P**
RL: IMF (Industrial manufacture); RCT (Reactant); TEM (Technical
or engineered material use); PREP (Preparation); RACT (Reactant or
reagent); USES (Uses)
(**binders**; polymerizable compns. for laser recording
layers of neg. lithog. original plates)

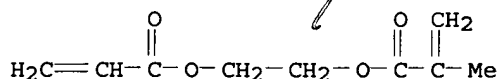
RN 779351-43-8 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
ester, polymer with methyl 2-methyl-2-propenoate,
2-methyl-2-propenoic acid and 2-[(1-oxo-2-propenyl)oxy]ethyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 69040-48-8

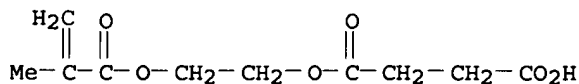
CMF C9 H12 O4



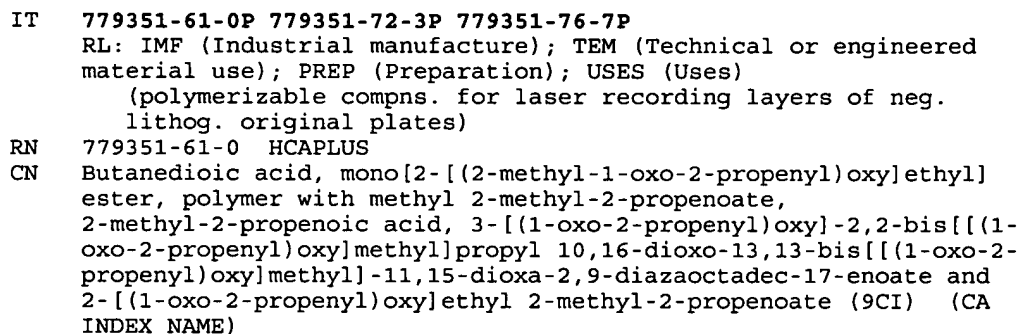
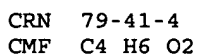
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CRN 20882-04-6

CMF C10 H14 O6



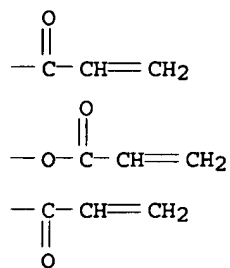
CRN . 80-62-6
CMF C5 H8 O2



CRN 77001-81-1
CMF C36 H48 N2 O16

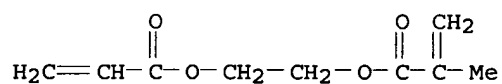
$$\begin{array}{c} \text{O} \\ \parallel \\ \text{H}_2\text{C}=\text{CH}-\text{C}-\text{O}-\text{CH}_2 \\ | \\ \text{H}_2\text{C}=\text{CH}-\text{C}(=\text{O})-\text{O}-\text{CH}_2-\text{C}-\text{CH}_2-\text{O}-\text{C}(=\text{O})-\text{NH}-(\text{CH}_2)_6-\text{NH}-\text{C}(=\text{O})-\text{O}-\text{CH}_2-\text{C}-\text{CH}_2- \\ | \qquad \qquad \qquad | \\ \text{H}_2\text{C}=\text{CH}-\text{C}(=\text{O})-\text{O}-\text{CH}_2 \qquad \qquad \qquad \text{CH}_2-\text{O}- \end{array}$$

PAGE 1-B



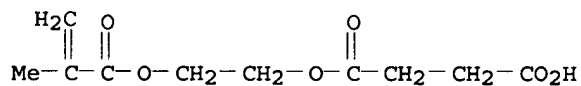
CM 2

CRN 69040-48-8
 CMF C9 H12 O4



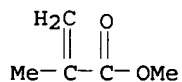
CM 3

CRN 20882-04-6
 CMF C10 H14 O6



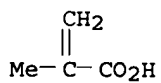
CM 4

CRN 80-62-6
 CMF C5 H8 O2



CM 5

CRN 79-41-4
 CMF C4 H6 O2



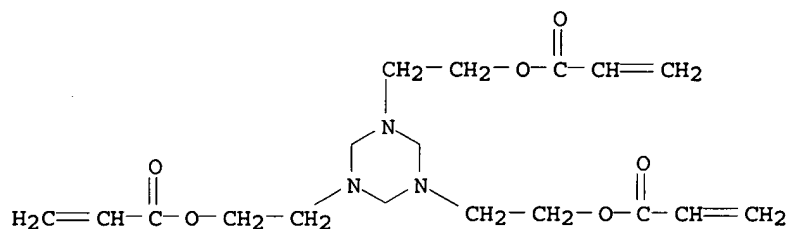
RN 779351-72-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with methyl 2-methyl-2-propenoate,
 2-methyl-2-propenoic acid, 2-[(1-oxo-2-propenyl)oxy]ethyl
 2-methyl-2-propenoate and 1,3,5-triazine-1,3,5(2H,4H,6H)-triyetri-
 2,1-ethanediyl tri-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 135985-48-7

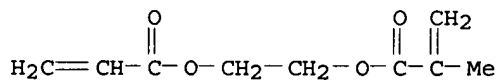
CMF C18 H27 N3 O6



CM 2

CRN 69040-48-8

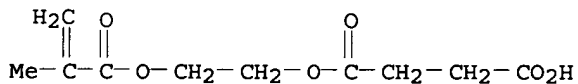
CMF C9 H12 O4



CM 3

CRN 20882-04-6

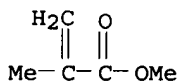
CMF C10 H14 O6



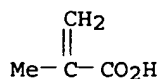
CM 4

CRN 80-62-6

CMF C5 H8 O2



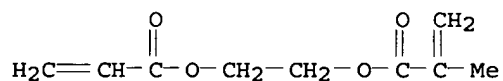
CM 5

CRN 79-41-4
CMF C4 H6 O2

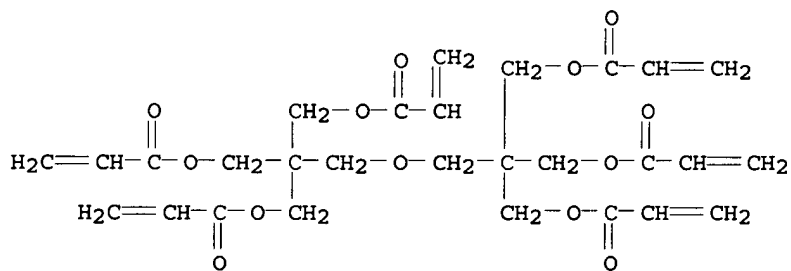
RN 779351-76-7 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with methyl 2-methyl-2-propenoate, 2-methyl-2-propenoic acid, 2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate and 2-[(1-oxo-2-propenyl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

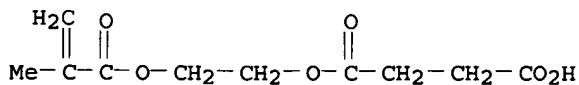
CM 1

CRN 69040-48-8
CMF C9 H12 O4

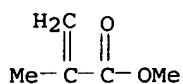
CM 2

CRN 29570-58-9
CMF C28 H34 O13

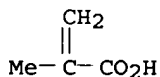
CM 3

CRN 20882-04-6
CMF C10 H14 O6

CM 4

CRN 80-62-6
CMF C5 H8 O2

CM 5

CRN 79-41-4
CMF C4 H6 O2

IC ICM C08F290-12
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 ST lithog printing plate allyl binder
 polymer; laser lithog plate binder glass transition temp
 IT **Binders**
 (polymerizable compns. for laser recording layers of neg. lithog. original plates)
 IT 135706-48-8P 141680-06-0P 393545-66-9P 779351-38-1P
 779351-39-2P 779351-40-5P 779351-41-6P 779351-42-7P
779351-43-8P 779351-45-0P 779351-47-2P 779351-49-4P
 779351-50-7P 779351-51-8P
 RL: IMF (Industrial manufacture); RCT (Reactant); TEM (Technical or engineered material use); PREP (Preparation); RACT (Reactant or reagent); USES (Uses)
 (binders; polymerizable compns. for laser recording layers of neg. lithog. original plates)
 IT 779351-53-0P 779351-54-1P 779351-55-2P 779351-56-3P
 779351-57-4P 779351-58-5P 779351-59-6P 779351-60-9P
779351-61-0P 779351-62-1P 779351-63-2P 779351-64-3P
 779351-65-4P 779351-66-5P 779351-67-6P 779351-68-7P
 779351-69-8P 779351-70-1P 779351-71-2P **779351-72-3P**
 779351-73-4P 779351-74-5P 779351-75-6P **779351-76-7P**
 779351-77-8P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (polymerizable compns. for laser recording layers of neg. lithog. original plates)
 L55 ANSWER 3 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 2004:250272 Document No. 140:278467 Presensitized lithographic printing plate materials with excellent sensitivity, development properties, and wear and chemical resistance. Takagi, Hiroshi (Konica Minolta Holdings Inc., Japan). Jpn. Kokai Tokkyo Koho JP 2004093763 A2 20040325, 27 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2002-253174 20020830.
 AB The materials consist of substrates and ≥1

photopolymerizable layers containing ethylenically unsatd. monomers, photopolymn. initiators, and polymeric **binders** which are obtained by reacting copolymers of carboxyl-containing monomers and OH-containing monomers (A) and ethylenically unsatd. compds. bearing isocyanate groups reactive to the OH groups in A.

IT 674777-00-5P, Ethyl methacrylate-2-hydroxyethyl methacrylate-methacrylic acid-methyl methacrylate copolymer carbamate with 2-methacryloyloxyethyl isocyanate
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(**binder**; presensitized lithog. **printing** plate materials with good sensitivity, development properties, and wear and chemical resistance)

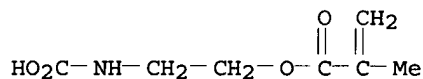
RN 674777-00-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with ethyl 2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

CM 1

CRN 96571-20-9

CMF C7 H11 N O4



CM 2

CRN 66536-23-0

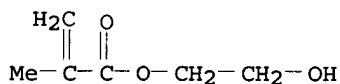
CMF (C6 H10 O3 . C6 H10 O2 . C5 H8 O2 . C4 H6 O2)x

CCI PMS

CM 3

CRN 868-77-9

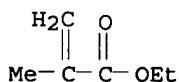
CMF C6 H10 O3



CM 4

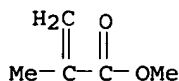
CRN 97-63-2

CMF C6 H10 O2



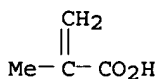
CM 5

CRN 80-62-6
CMF C5 H8 O2



CM 6

CRN 79-41-4
CMF C4 H6 O2



- IC ICM G03F007-038
ICS G03F007-00; G03F007-11; G03F007-38
- CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
- ST presensitized lithog **printing plate** wear
resistance; lithog plate polymer **binder** chem resistance;
unsatd acrylic polymer **binder** lithog plate
- IT Polyamides, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(O-barrier layer; presensitized lithog. **printing plate** materials with good sensitivity, development properties, and wear and chemical resistance)
- IT Polyoxyalkylenes, preparation
Polyurethanes, preparation
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic; presensitized lithog. **printing plate** materials with good sensitivity, development properties, and wear and chemical resistance)
- IT **Binders**
(polymeric; presensitized lithog. **printing plate** materials with good sensitivity, development properties, and wear and chemical resistance)
- IT Abrasion-resistant materials
Chemically resistant materials
(presensitized lithog. **printing plate** materials with good sensitivity, development properties, and wear and chemical resistance)
- IT Lithographic plates
(presensitized; presensitized lithog. **printing plate** materials with good sensitivity, development properties, and wear and chemical resistance)
- IT 51394-53-7, AQ-Nylon P 70 104922-10-3, Gohsenol GL 05
RL: TEM (Technical or engineered material use); USES (Uses)
(O-barrier layer; presensitized lithog. **printing plate** materials with good sensitivity, development properties, and wear and chemical resistance)
- IT 674777-00-5P, Ethyl methacrylate-2-hydroxyethyl methacrylate-methacrylic acid-methyl methacrylate copolymer

carbamate with 2-methacryloyloxyethyl isocyanate 674777-01-6P, Ethyl methacrylate-2-hydroxyethyl methacrylate-methacrylic acid-methyl methacrylate copolymer carbamate with vinyl isocyanate 674777-02-7P, Ethyl methacrylate-2-hydroxyethyl methacrylate-methacrylic acid-methyl methacrylate copolymer carbamate with methacryloyl isocyanate 674777-03-8P, Ethyl methacrylate-2-hydroxyethyl methacrylate-methacrylic acid-methyl methacrylate copolymer carbamate with m-isopropenyl- α,α' -dimethylbenzyl isocyanate

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(binder; presensitized lithog. **printing plate** materials with good sensitivity, development properties, and wear and chemical resistance)

IT 1312-76-1, Potassium silicate

RL: NUU (Other use, unclassified); USES (Uses)

(developer; presensitized lithog. **printing plate** materials with good sensitivity, development properties, and wear and chemical resistance)

IT 822-06-ODP, Hexamethylene diisocyanate, reaction products with hydroxyethyl methacrylate and hydroxyethylpiperidine 868-77-9DP, reaction products with hexamethylene diisocyanate and hydroxyethylpiperidine 1484-84-ODP, 2-(2-Hydroxyethyl)piperidine, reaction products with hexamethylene diisocyanate and hydroxyethyl methacrylate 85887-85-OP, Light Acrylate TMP 6EO3A homopolymer 392662-16-7P, Light Acrylate TMP 6EO3A-NK Oligo U 4HA copolymer

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(presensitized lithog. **printing plate** materials with good sensitivity, development properties, and wear and chemical resistance)

IT 7429-90-5, Aluminum, uses

RL: TEM (Technical or engineered material use); USES (Uses)

(rough-surfaced, anodized, and undercoated, substrate; presensitized lithog. **printing plate** materials with good sensitivity, development properties, and wear and chemical resistance)

L55 ANSWER 4 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1999:205409 Document No. 130:259567 Oil-based ink-jet printing-type ink and method of making lithographic **printing plate** using same. Kato, Eiichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 11078226 A2 19990323 Heisei, 33 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1997-252191 19970917.

AB The ink has oil-dispersed particle resin prepared by copolymn. of: (1) a mono-functional monomer insol. in non-aqueous solvent after polymerization; (2) a monomer having a side ≥ 8 carbon chain soluble in non-aqueous solvent; and (3) a dispersion stabilizing resin soluble in non-aqueous solvent. The lithog. **printing plate** is made by; (1) printing an image on a lithog. **printing plate** original having an image-receiving layer having zinc oxide and a binder on a water-resistant support; and (2) desensitizing the non-image part of the plate. The ink provides excellent dispersibility, storage stability, and printing durability. The **printing plates** provides high quality image and excellent printing durability.

IT 221653-54-9P

RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(particle resin for oil based-based ink-jet printing-type ink

for lithog. printing plate)

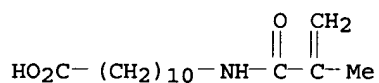
RN 221653-54-9 HCAPLUS

CN Undecanoic acid, 11-[(2-methyl-1-oxo-2-propenyl)amino]-, polymer
 with docosyl 2-propenoate, methyl 2-methyl-2-propenoate, methyl
 2-propenoate, 2-propenoic acid and tridecyl 2-methyl-2-propenoate,
 graft (9CI) (CA INDEX NAME)

CM 1

CRN 59178-93-7

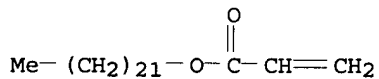
CMF C15 H27 N O3



CM 2

CRN 18299-85-9

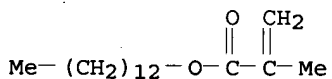
CMF C25 H48 O2



CM 3

CRN 2495-25-2

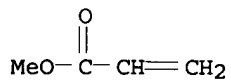
CMF C17 H32 O2



CM 4

CRN 96-33-3

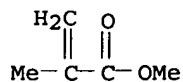
CMF C4 H6 O2



CM 5

CRN 80-62-6

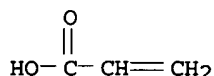
CMF C5 H8 O2



CM 6

CRN 79-10-7

CMF C3 H4 O2



- IC ICM B41M005-00
ICS B41C001-10; B41N001-14; C09D011-02
- CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
- ST Oil ink jet **printing** lithog **plate** latex resin particle
- IT Ink-jet printing
Lithographic plates
(oil-based ink-jet printing-type ink for lithog. **printing plate**)
- IT Inks
(oil-based; oil-based ink-jet printing-type ink for lithog. **printing plate**)
- IT 39332-53-1, Methyl methacrylate-acrylic acid-methacrylic acid copolymer 60472-57-3D, Methyl methacrylate-methacrylic acid-methyl acrylate-styrene copolymer, reaction products with 4-cyano pentanoic acid 184970-55-6, Methyl methacrylate-acrylic acid-lauryl acrylate-N-vinyl-2-pyrrolidone copolymer 188951-11-3, Methyl methacrylate-styrene-methyl acrylate-2-mercaptobenzoic acid copolymer 221653-56-1, Methyl methacrylate-acrylic acid-methyl acrylate-N-propylacrylamide copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(**binder for lithog. printing plate**)
- IT 104922-28-3P, Mono(2-methacryloyloxy)ethyl glutarate-octadecyl methacrylate copolymer ester with allyl alcohol 220728-45-0P 220728-51-8P 221654-03-1P, Dodecyl methacrylate-glycidyl methacrylate-octadecyl methacrylate copolymer ester with 3-acryloyloxy propionic acid
RL: PNU (Preparation, unclassified); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(dispersion stabilizing resin for oil based ink-jet printing-type ink for lithog. **printing plate**)
- IT 1314-13-2, Zinc oxide, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(lithog. **printing plate**)
- IT 221653-63-0P 221653-64-1P 221653-66-3P 221653-67-4P
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(oil-based ink-jet printing-type ink for lithog. **printing plate**)
- IT 9003-20-7P, Vinyl acetate homopolymer 55778-35-3P, Octadecyl

methacrylate-vinyl acetate copolymer 161641-25-4P, Methyl
 acrylate-methyl methacrylate-octadecyl acrylate copolymer
 221653-31-2P, Vinyl acetate-vinyl oleate graft copolymer
 221653-32-3P, Vinyl acetate-octadecyl vinyl ether graft copolymer
 221653-33-4P, Vinyl acetate-Hexyl (methacryloyl)ethylsuccinate
 graft copolymer 221653-34-5P 221653-35-6P 221653-36-7P
 221653-38-9P 221653-39-0P 221653-40-3P 221653-41-4P
 221653-42-5P 221653-44-7P 221653-46-9P 221653-47-0P
 221653-50-5P 221653-52-7P 221653-54-9P 221653-58-3P
 221653-59-4P 221653-61-8P

RL: PNU (Preparation, unclassified); TEM (Technical or engineered
 material use); PREP (Preparation); USES (Uses)
 (particle resin for oil based-based ink-jet printing-type ink
 for lithog. printing plate)

L55 ANSWER 5 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1996:659173 Document No. 125:288810 Manufacture of lithographic
 printing plate by electrophotographic process.

Kato, Eiichi (Fuji Photo Film Co Ltd, Japan). Jpn. Kokai Tokkyo
 Koho JP 08194341 A2 19960730 Heisei, 79 pp. (Japanese). CODEN:
 JKXXAF. APPLICATION: JP 1995-19897 19950113.

AB The process comprises forming a toner image on a peelable
 electrophotog. photoreceptor by using an electrophotog. process,
 electrodepositing a layer made up of ≥ 2 types of resin
 particles with different Tg (glass transition temperature) on the toner
 image to form a 1st transfer layer, applying a layer made up of
 resin particles with a higher Tg to form a 2nd transfer layer,
 transferring the toner image and the 1st and 2nd transfer layers
 to a receptor, and removing the 1st and 2nd transfer layers in the
 non-image section by a chemical process. The resin particles may
 contain F and/or Si, and are dispersed in a non-aqueous solvent.

IT 182558-61-8, Acrylic acid-2-carboxyethyl acrylate-methyl
 acrylate-methyl methacrylate copolymer
 RL: NUU (Other use, unclassified); PEP (Physical, engineering or
 chemical process); PROC (Process); USES (Uses)
 (manufacture of lithog. printing plate by
 electrophotog. process)

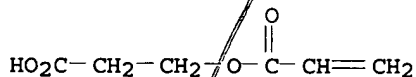
RN 182558-61-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with
 2-carboxyethyl 2-propenoate, methyl 2-propenoate and 2-propenoic
 acid (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7

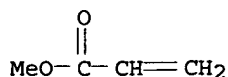
CMF C6 H8 O4



CM 2

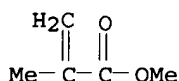
CRN 96-33-3

CMF C4 H6 O2



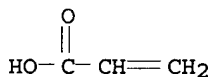
CM 3

CRN 80-62-6
CMF C5 H8 O2



CM 4

CRN 79-10-7
CMF C3 H4 O2



- IC ICM G03G013-26
ICS G03G013-16
- CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
- ST lithog **printing plate** electrophotog process
manuf; resin particle lithog **printing plate**
- IT Electrophotography
Lithographic plates
(manufacture of lithog. **printing plate** by electrophotog. process)
- IT Siloxanes and Silicones, uses
RL: NUU (Other use, unclassified); USES (Uses)
(manufacture of lithog. **printing plate** by electrophotog. process)
- IT 182829-01-2
RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)
(**binder resin**; manufacture of lithog. **printing plate** by electrophotog. process)
- IT 25639-21-8D, thioethoxycarbonylethyl methacrylate terminated
29014-80-0, Dodecyl methacrylate- methacrylic acid copolymer
182558-54-9 182558-79-8
RL: MOA (Modifier or additive use); USES (Uses)
(dispersion stabilizing resin; manufacture of lithog. **printing plate** by electrophotog. process)
- IT 67923-67-5, Acrylic acid-ethyl acrylatemethyl acrylate-methyl methacrylate copolymer
RL: NUU (Other use, unclassified); USES (Uses)
(dispersion stabilizing resin; manufacture of lithog. **printing plate** by electrophotog. process)
- IT 3052-61-7, Benzyl-N,N-diethyldithiocarbamate 109473-77-0
155293-25-7

RL: MOA (Modifier or additive use); USES (Uses)
 (initiator; manufacture of lithog. printing plate
 by electrophotog. process)

IT 150551-83-0 150551-90-9 150551-91-0 150551-93-2
 158320-07-1 182558-56-1 182558-84-5D,
 thioethoxycarbonylaminoethyl methacrylate terminated
 RL: MOA (Modifier or additive use); USES (Uses)
 (manufacture of lithog. printing plate by
 electrophotog. process)

IT 166594-77-0, Acrylic acid- benzyl methacrylate- 2-methoxyethyl
 methacrylate copolymer
 RL: MOA (Modifier or additive use); PEP (Physical, engineering or
 chemical process); PROC (Process); USES (Uses)
 (manufacture of lithog. printing plate by
 electrophotog. process)

IT 25035-26-1, Crotonic acid-vinyl acetate-vinyl propionate copolymer
 25766-25-0, Vinyl acetate- vinyl butanoate- crotonic acid
 copolymer 27155-22-2, Acrylic acidmethyl acrylatemethyl
 methacrylate copolymer 30475-53-7D, Methacrylic acidphenyl
 methacrylate copolymer, carboxy-terminated 40045-04-3, Acrylic
 acid-ethyl methacrylate-glycidyl methacrylate copolymer
 65697-21-4D, Benzyl methacrylate; methacrylic acid copolymer,
 carboxy-terminated 155161-71-0, Acrylic acid-benzyl
 methacrylate-methyl methacrylate copolymer 155161-74-3, Benzyl
 methacrylate-glycidyl methacrylate-methacrylic acid copolymer
 166594-75-8D, thioethylmethacrylate terminated 172598-64-0
 182558-57-2, Acrylic acid-2-butoxyethyl methacrylate-crotonic
 acid-methyl methacrylate-vinyl acetate-vinyl propionate copolymer
 182558-58-3 182559-23-5 182559-26-8, Methyl
 methacrylate-acrylic acid-2-sulfoethyl methacrylate copolymer
 182559-29-1 182559-31-5 182559-33-7 182559-34-8
 182559-35-9 182559-36-0 182559-37-1
 RL: NUU (Other use, unclassified); USES (Uses)
 (manufacture of lithog. printing plate by
 electrophotog. process)

IT 26936-24-3, Methyl acrylatemethyl methacrylate-methacrylic acid
 copolymer 73248-83-6, 2,2,3,4,4,4-Hexafluorobutyl
 methacrylate-methyl methacrylate copolymer 130030-47-6, Acrylic
 acid-benzyl methacrylate-ethyl acrylate copolymer 150624-89-8
 157966-19-3 161552-54-1 169046-28-0 169046-29-1
 169046-30-4 169046-32-6 182558-60-7 182558-61-8,
 Acrylic acid-2-carboxyethyl acrylate-methyl acrylate-methyl
 methacrylate copolymer 182558-63-0 182558-65-2, Acrylic
 acid-2-butoxyethyl acrylate-ethyl methacrylate-methyl
 methacrylate-2-hydroxyethyl acrylate copolymer 182558-67-4
 182558-68-5 182558-69-6 182558-71-0 182558-73-2
 182558-75-4 182558-76-5 182558-78-7 182558-80-1
 182558-81-2D, thioethoxycarbonylethyl methacrylate terminated
 182558-82-3D, thioethylmethacrylate terminated 182558-83-4D,
 3-cyanobutanoyloxyethyl acrylate terminated 182558-85-6, Acrylic
 acid-2-ethoxyethyl acrylate-methyl acrylate copolymer
 182558-86-7 182558-87-8 182558-88-9 182558-89-0
 182558-90-3 182558-91-4 182558-92-5 182558-93-6
 182558-94-7 182558-95-8 182558-97-0 182558-99-2
 182559-02-0 182559-04-2 182559-12-2 182559-14-4
 RL: NUU (Other use, unclassified); PEP (Physical, engineering or
 chemical process); PROC (Process); USES (Uses)
 (manufacture of lithog. printing plate by
 electrophotog. process)

IT 25135-39-1P, Acrylic acid-ethyl acrylatemethyl methacrylate
 copolymer 25302-81-2P, Acrylic acid-methyl acrylate copolymer
 58991-34-7P 155161-64-1P, Acrylic acid- diethylene glycol

monomethyl ether methacrylate- methyl methacrylate copolymer
 169045-58-3P, 2-Carboxyethyl acrylate-methyl acrylate-methyl
 methacrylate copolymer 169045-70-9P 182558-59-4P
 182558-62-9P, Acrylic acid-2-methoxyethyl acrylate-methyl
 acrylate-methyl methacrylate-methacrylic acid copolymer
 182558-64-1P, Acrylic acid-ethyl methacrylate-2-hydroxyethyl
 acrylate copolymer 182558-66-3P
 RL: RCT (Reactant); SPN (Synthetic preparation); PREP
 (Preparation); RACT (Reactant or reagent)
 (manufacture of lithog. printing plate by
 electrophotog. process)

L55 ANSWER 6 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1995:248297 Document No. 122:147178 Electrophotographic lithographic
 printing plate master. Kato, Eiichi; Tashiro,
 Hiroshi; Oda, Akihisa; Ishii, Kazuo (Fuji Photo Film Co Ltd,
 Japan). Jpn. Kokai Tokkyo Koho JP 06095441 A2 19940408 Heisei,
 201 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1993-19360
 19930111. PRIORITY: JP 1992-20694 19920110; JP 1992-102519
 19920330; JP 1992-127900 19920422; JP 1992-175944 19920611; JP
 1992-177762 19920612; JP 1992-182834 19920618; JP 1992-219553
 19920728.

AB The title plate master has a photo-conductive layer containing a
 binder resin that has a crosslinking structure and
 contains groups capable of giving ≥ 1 group selected from
 CO_2H , SO_3H , SO_2H , and PO_3H_2 . The plate master further contains
 the other types of binder resins besides the above
 crosslinked binder resin. The plate master shows
 superior printing performance and is free of background stains.

IT 159676-19-4P

RL: DEV (Device component use); SPN (Synthetic preparation); PREP
 (Preparation); USES (Uses)

(binder resin for electrophotog. lithog.
 printing plate master)

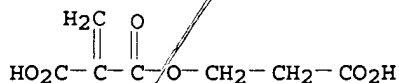
RN 159676-19-4 HCAPLUS

CN Propanedioic acid, methylene-, mono(2-carboxyethyl) ester, polymer
 with 2-chlorophenyl 2-methyl-2-propenoate and ethyl
 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

CRN 159676-18-3

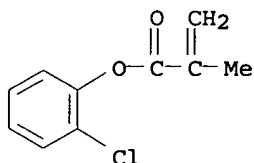
CMF C7 H8 O6



CM 2

CRN 18967-23-2

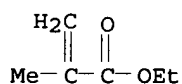
CMF C10 H9 Cl O2



CM 3

CRN 97-63-2

CMF C6 H10 O2



IC ICM G03G013-28
ICS G03G005-05; G03G005-06; G03G005-08; G03G005-09

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST electrophotog lithog **printing plate** master **binder**

IT Lithographic plates
(electrophotog. making lithog. **printing plate** master containing specified **binder**)

IT Electrophotography
(for making lithog. **printing plate** master containing specified **binder**)

IT 156623-29-9 156623-32-4 156623-33-5 156623-34-6
156623-35-7 156623-36-8 156623-37-9 156623-38-0
156623-39-1 156623-42-6 156623-43-7 156623-44-8
156623-45-9 156623-46-0 156623-47-1 156623-48-2
156623-49-3 156623-50-6 156623-51-7 156623-52-8
156623-53-9 156623-54-0 159676-20-7 159676-21-8
159676-22-9 159676-24-1 159676-25-2 159676-26-3
159676-27-4

RL: DEV (Device component use); USES (Uses)
(as **binder** resin used in electrophotog. lithog. **printing plate** master)

IT 25777-71-3 26355-01-1 30916-60-0 50450-03-8 75944-16-0
132258-49-2 156623-55-1 156623-57-3 156623-59-5
156623-60-8 156623-61-9 158079-08-4

RL: DEV (Device component use); USES (Uses)
(as crosslinkable compound contained in photo-conductive layer for electrophotog. lithog. **printing plate** master)

IT 77-58-7, Tin dibutyl dilaurate 85-44-9, Phthalic acid anhydride 94-36-0, Benzoyl peroxide, uses 95-57-8, o-Chloro phenol 96-05-9, Allyl methacrylate 526-95-4, Gluconic acid 926-63-6, N,N-Dimethylpropylamine 2530-83-8, 3-Glycidoxypentyl trimethoxy silane 4074-90-2 5593-70-4 13822-56-5, 3-Aminopropyl trimethoxy silane 156623-62-0

RL: DEV (Device component use); USES (Uses)
(as crosslinker contained in photo-conductive layer for electrophotog. lithog. **printing plate** master)

IT 155040-33-8 155040-34-9 155040-35-0 155040-36-1

RL: CAT (Catalyst use); USES (Uses)
 (as initiator for preparing binder resins used in
 electrophotog. lithog. printing plate
 master)

IT 9011-14-7DP, Methyl methacrylate homopolymer, terminated with
 carboxyl and 1,1-di-Ph hexyl 65697-21-4P, Benzyl
 methacrylate-methacrylic acid copolymer 89162-03-8P
 126969-70-8P 126969-71-9P 128338-05-6P, Benzyl methacrylate
 telomer with thiosalicylic acid 130094-33-6P 131808-63-4P
 131808-82-7P 131914-67-5P 135740-20-4P 135740-21-5P
 135740-22-6P 135740-24-8P 135740-26-0P 135740-31-7P
 135740-32-8P 135740-33-9P 135740-35-1P 135740-37-3P
 135740-41-9P 135740-43-1P 135836-14-5P 135942-52-8P
 138115-42-1P 138115-52-3P 138115-53-4P 138115-55-6P
 138115-56-7P 138115-57-8P 138115-58-9P 138115-59-0P
 138115-60-3P 138115-61-4P 138115-62-5P 138115-63-6P
 138115-64-7P 138123-83-8DP, Methacrylic acid-1-naphthyl
 methacrylate copolymer, carboxy-terminated 138136-29-5P
 138232-72-1P 139676-53-2P 142847-56-1P 143439-34-3P
 143646-28-0P 144278-66-0P 146817-57-4P 146817-58-5P
 149234-62-8DP, Benzyl methacrylate telomer with thioglycolic acid,
 reaction product with 4,4'-azo bis(4-cyano) valeric acid
 149234-72-0P 149234-89-9P 149234-90-2DP, hydrolyzed
 149234-95-7P 149234-98-0P 149234-99-1P 149235-39-2DP,
 reduced 149341-88-8P 154104-48-0P 154402-89-8DP, Benzyl
 methacrylate-butyl methacrylate-2-chlorophenyl methacrylate block
 graft copolymer, reduced 154402-90-1DP, hydrolyzed
 154402-91-2DP, hydrolyzed 154402-92-3DP, hydrolyzed
 154402-93-4DP, hydrolyzed 154402-94-5DP, hydrolyzed
 154402-95-6DP, hydrolyzed 154402-96-7DP, hydrolyzed
 154402-97-8DP, hydrolyzed 154402-98-9DP, hydrolyzed
 154402-99-0DP, hydrolyzed 154403-00-6DP, hydrolyzed
 154403-01-7DP, hydrolyzed 154403-02-8DP, hydrolyzed
 154403-03-9DP, hydrolyzed 154403-04-0DP, hydrolyzed
 154403-05-1DP, hydrolyzed 154460-60-3DP, Ethyl
 methacrylate-triphenylmethyl methacrylate block graft copolymer,
 hydrolyzed 155246-75-6P 155246-76-7P 155246-78-9P
 155246-79-0P 155246-80-3P 155246-82-5P 155246-84-7P
 155246-85-8P 155246-89-2P 155246-95-0P 155246-96-1P
 155246-98-3P 155247-00-0P 155247-02-2P 155247-08-8P
 155247-10-2DP, hydrolyzed 155247-11-3P 155247-14-6P
 155247-15-7P 155247-16-8P 155247-17-9P 155247-18-0P
 155247-19-1P 155247-20-4P 155247-21-5P 155247-22-6DP,
 reduced 155247-23-7P 155247-24-8P 155247-25-9P
 155247-26-0P 155247-27-1P 155247-28-2P 155247-29-3P
 155247-30-6P 155247-31-7P 155247-32-8P 155247-33-9P
 155247-34-0P 155247-35-1P 155247-36-2P 155324-45-1P
 155838-53-2P 155838-55-4P 155838-58-7P 155838-59-8P
 155838-60-1P 155838-61-2P 155838-62-3P 155838-63-4P
 155838-64-5P 155838-65-6P 155838-66-7P 155838-67-8P
 155838-68-9P 155838-69-0P 155838-70-3P 155838-71-4P
 155838-72-5P 155838-73-6P 155838-74-7P 155838-75-8P
 155898-91-2P 155898-92-3P 159319-71-8P 159676-17-2P
 159676-19-4P

RL: DEV (Device component use); SPN (Synthetic preparation); PREP
 (Preparation); USES (Uses)

(binder resin for electrophotog. lithog.
 printing plate master)

IT 1314-13-2, Zinc oxide, uses

RL: DEV (Device component use); USES (Uses)

(contained in photo-conductive layer for electrophotog. lithog.
 printing plate master)

- IT 138115-34-1DP, Ethyl methacrylate-triphenylmethyl methacrylate block copolymer, carboxy-terminated, ester with 2-hydroxyethyl methacrylate, hydrolyzed 138136-28-4DP, 2-Chloro-6-methylphenyl methacrylate-4-vinylphenoxy trimethyl silane block copolymer, reaction product with ethyleneoxide, ester with methacrylic acid chloride, hydrolyzed 138232-67-4DP, Benzyl methacrylate-butyl methacrylate block copolymer, reaction product with 4-bromomethylstyrene, reduced 138232-68-5DP, Acrylic acid-phenyl methacrylate block copolymer, terminated with 2-isocyanate Et methacrylate
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(macro-monomer for preparing binder resin used in electrophotog. lithog. printing plate master)
- IT 25212-88-8DP, Ethyl acrylate-methacrylic acid copolymer, hydroxy-terminated, ester with 4,4'-azo bis(cyano) valeric acid
RL: CAT (Catalyst use); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
(polymeric initiator for preparing binder resins used in electrophotog. lithog. printing plate master)
- IT 27155-22-2DP, Acrylic acid-methyl acrylate-methyl methacrylate copolymer, dimethyldithiocarbamoyl-terminated 28572-98-7DP, Ethyl methacrylate-methacrylic acid copolymer, dimethyldithiocarbamoyl-terminated 65697-22-5DP, Acrylic acid-benzyl methacrylate copolymer, dimethyldithiocarbamoyl-terminated 89162-02-7DP, dimethyldithiocarbamoyl-terminated 126969-71-9DP, alkyldithiocarboxy- or dialkyldithiocarbamoyl-terminated 126969-78-6DP, Acrylic acid-2-chloro-6-methylphenyl methacrylate copolymer, dimethyldithiocarbamoyl-terminated 131004-79-0DP, dimethyldithiocarbamoyl-terminated 141681-05-2DP, diethyldithiocarbamoyl-terminated 141681-10-9DP, diethyldithiocarbamoyl-terminated 144328-03-0DP, diethyldithiocarbamoyl-terminated 144407-88-5DP, diethyldithiocarbamoyl-terminated 149265-81-6DP, dimethyldithiocarbamoyl-terminated 149341-90-2DP, isopropyldithiocarboxy-terminated 152222-87-2DP, dimethyldithiocarbamoyl-terminated 152222-88-3DP, dimethyldithiocarbamoyl-terminated 152222-90-7DP, dimethyldithiocarbamoyl-terminated 152222-91-8DP, dimethyldithiocarbamoyl-terminated 152222-92-9DP, dimethyldithiocarbamoyl-terminated 152222-93-0DP, dimethyldithiocarbamoyl-terminated 152222-94-1DP, dimethyldithiocarbamoyl-terminated 152222-96-3DP, dimethyldithiocarbamoyl-terminated 152222-98-5DP, dimethyldithiocarbamoyl-terminated 152222-99-6DP, dimethyldithiocarbamoyl-terminated 152244-96-7DP, dimethyldithiocarbamoyl-terminated 152792-28-4DP, isopropyldithiocarboxy-terminated 152792-35-3DP, isopropyldithiocarboxy-terminated 153772-11-3DP, diethyldithiocarbamoyl-terminated 153772-12-4DP, diethyldithiocarbamoyl-terminated 153772-13-5DP, diethyldithiocarbamoyl-terminated 153772-14-6DP, diethyldithiocarbamoyl-terminated 153772-15-7DP, diethyldithiocarbamoyl-terminated 153772-16-8DP, diethyldithiocarbamoyl-terminated 153772-17-9DP, dimethyldithiocarbamoyl-terminated 153772-18-0DP, dimethyldithiocarbamoyl-terminated 153772-19-1DP, dimethyldithiocarbamoyl-terminated 153772-20-4DP, dimethyldithiocarbamoyl-terminated 153772-22-6DP, dimethyldithiocarbamoyl-terminated 153772-23-7DP,

dimethyldithiocarbamoyl-terminated 153772-24-8DP,
 dimethyldithiocarbamoyl-terminated 153772-25-9DP,
 dimethyldithiocarbamoyl-terminated 153772-26-0DP,
 dimethyldithiocarbamoyl-terminated 153772-27-1DP,
 isopropylidithiocarboxy-terminated 153772-28-2DP,
 isopropylidithiocarboxy-terminated 153772-29-3DP,
 isopropylidithiocarboxy-terminated 153832-26-9DP,
 alkylidithiocarboxy- or dialkylidithiocarbamoyl-terminated
 155161-47-0DP, dimethyldithiocarbamoyl-terminated 155161-48-1DP,
 dimethyldithiocarbamoyl-terminated 155161-49-2DP,
 dimethyldithiocarbamoyl-terminated 155241-62-6DP,
 dimethyldithiocarbamoyl-terminated
 RL: DEV (Device component use); SPN (Synthetic preparation); PREP
 (Preparation); USES (Uses)
 (star-type binder resin for electrophotog. lithog.
 printing plate master)

L55 ANSWER 7 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1994:496061 Document No. 121:96061 Electrophotographic lithographic
 printing plate having excellent water retension.

Kato, Eiichi (Fuji Photo Film Co Ltd, Japan). Jpn. Kokai Tokkyo
 Koho JP 05100463 A2 19930423 Heisei, 91 pp. (Japanese). CODEN:
 JKXXAF. APPLICATION: JP 1991-285495 19911007.

AB In the title electrophotog. lithog. printing
 plate comprising ≥ 1 photoconductor layer on a
 conductive support and an uppermost surface layer, the uppermost
 surface layer contains ≥ 1 kind of nonaq. dispersion resin
 particles (L) and the photoconductor layer contains ≥ 1 kind
 of resin (A) as a binder resin:. The nonaq. dispersion
 resin particles (L) are made of a copolymer obtained in a nonaq.
 solvent by dispersion polymerization of a monofunctional monomer (C),
 which is soluble in the nonaq. solvent but insol. upon polymerization and is
 capable of forming ≥ 1 functional group having ≥ 1
 COOH group upon decomposition, in the presence of a dispersion
 stabilizing resin which is soluble in the solvent containing F- and/or
 Si-bearing group in a repeating unit and. The resin (A) has
 weight-average mol. weight 1000-20,000 and is made of a repeating unit
 $[a_1HCCa_2(COOR_3)]$ [$a_1, 2 = H, halo, cyano, hydrocarbyl$; $R_3 =$
 $hydrocarbyl$] $\geq 30\%$, in which one end of the backbone chain
 is terminated with ≥ 1 polar moiety selected from PO_3H_2 ,
 SO_3H , $COOH$, $P(O)(OH)R_1$ [$R_1 = hydrocarbon$ or OR_2 ; $R_2 =$
 $hydrocarbyl$], and cyclic anhydride.

IT 149434-28-6P 154452-24-1P

RL: TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)

(preparation of, for electrophotog. materials for lithog. plate
 manufacture)

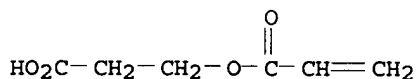
RN 149434-28-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, telomer with 2-mercaptoethanol and
 phenylbis(trifluoromethyl)silyl 2-methyl-2-propenoate,
 3-[(1-oxo-2-propenyl)oxy]propanoate (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7

CMF C6 H8 O4



CM 2

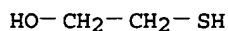
CRN 163255-66-1

CMF (C12 H10 F6 O2 Si . C4 H6 O2)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



CM 4

CRN 163255-65-0

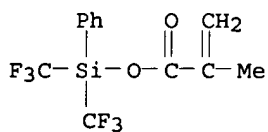
CMF (C12 H10 F6 O2 Si . C4 H6 O2)x

CCI PMS

CM 5

CRN 149072-54-8

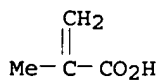
CMF C12 H10 F6 O2 Si



CM 6

CRN 79-41-4

CMF C4 H6 O2



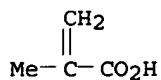
RN 154452-24-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl ester, telomer with 2-carboxyethyl 2-propenoate and 3-mercaptopropionic acid, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

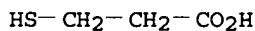
CRN 163149-10-8

CMF (C10 H9 F9 O2 . C6 H8 O4)x . C3 H6 O2 S

CM 3

CRN 107-96-0

CMF C3 H6 O2 S



CM 4

CRN 163148-86-5

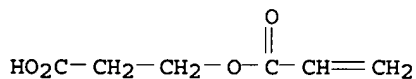
CMF (C10 H9 F9 O2 . C6 H8 O4)x

CCI PMS

CM 5

CRN 24615-84-7

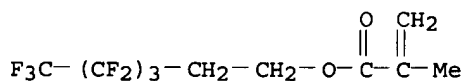
CMF C6 H8 O4



CM 6

CRN 1799-84-4

CMF C10 H9 F9 O2



IC ICM G03G005-147

ICS G03G005-05; G03G005-06; G03G013-28

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST electrophotog lithog **printing plate**

IT 9011-14-7DP, Methyl methacrylate homopolymer, carboxylated,
 terminated with diphenylhexane 31547-85-ODP, carboxy-terminated
 100904-38-9P 128338-04-5P 128338-05-6P, Benzyl
 methacrylate-thiosalicylic acid telomer 138059-23-1P
 138059-26-4P 138059-27-5P 138059-28-6P 138059-29-7P
 138059-30-0P 138059-31-1P 138059-32-2P 138059-33-3P

138059-34-4P 138059-35-5P 138059-36-6P 139357-81-6P
 139989-86-9P 139989-94-9P 142199-53-9P 145168-75-8P
 145168-89-4P 145168-94-1P 145169-02-4P 145169-03-5P
 145169-04-6P 145169-24-0P 145169-26-2P 145169-30-8P
 145807-38-1P 145807-40-5P 145807-41-6P 145807-51-8P
 145807-53-0P 145807-54-1P 145807-55-2P 145807-57-4P
 145807-62-1P 145807-63-2P 145807-64-3P 145807-65-4P
 145807-66-5P 145807-68-7P 145807-72-3P 145807-78-9P
 145807-80-3P 146115-83-5P 146188-26-3P 146716-90-7P
 146716-92-9P 146716-99-6P 146717-07-9P 149072-24-2DP,
 reaction product with 2-isocyanatoethyl methacrylate
 149072-28-6P 149072-31-1P 149072-33-3P 149072-36-6P
 149072-38-8P 149072-39-9P 149072-47-9P 149072-48-0P
 149072-49-1P 149072-50-4P 149072-52-6P 149072-53-7P
 149072-55-9P 149072-56-0P 149072-99-1P 149093-43-6P
 149093-44-7P 149093-46-9P 149093-47-0P 149265-85-0P
 149368-83-2P 149434-15-1P 149434-25-3P 149434-28-6P
 149658-55-9P 150103-52-9P 150103-59-6DP, reaction product with
 cyanoethyl methacrylate 154042-89-4P 154042-90-7P
 154042-92-9P 154042-93-0P 154042-94-1P 154042-95-2P
 154042-96-3P 154042-97-4P 154042-98-5P 154042-99-6P
 154043-00-2P 154043-01-3P 154043-02-4P 154043-03-5P
 154043-04-6P 154043-05-7P 154043-06-8P 154043-07-9P
 154043-08-0P 154043-09-1P 154043-10-4P 154043-11-5P
 154397-48-5P 154452-24-1P 154452-25-2P 154452-26-3P
 154452-28-5P 154483-07-5P

RL: TEM (Technical or engineered material use); PREP

(Preparation); USES (Uses)

(preparation of, for electrophotog. materials for lithog. plate
 manufacture)

L55 ANSWER 8 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1994:496060 Document No. 121:96060 Electrophotographic lithographic
printing plate having excellent water retention.

Kato, Eiichi (Fuji Photo Film Co Ltd, Japan). Jpn. Kokai Tokkyo

Koho JP 05100462 A2 19930423 Heisei, 89 pp. (Japanese). CODEN:

JKXXAF. APPLICATION: JP 1991-284154 19911004.

AB In the title electrophotog. lithog. **printing
 plate** comprising ≥ 1 photoconductor layer on a
 conductive support and an uppermost surface layer, the uppermost
 surface layer contains ≥ 1 kind of nonaq. dispersion resin
 particles (L) and the photoconductor layer contains ≥ 1 kind
 of resin (A) as a binder resin: The nonaq. dispersion
 resin particles (L) are made of a copolymer obtained in a nonaq.
 solvent by dispersion polymerization of a monofunctional monomer (C),
 which is soluble in the nonaq. solvent but insol. upon polymerization and is
 capable of forming ≥ 1 functional group having ≥ 1
 COOH group upon decomposition, in the presence of a dispersion
 stabilizing resin which is soluble in the solvent containing F- and/or
 Si-bearing group in a repeating unit. The resin (A) has weight-average
 mol. weight 1000-20,000 and is made of a repeating unit
 $[a_1HCCa_2(COOR_3)]$ [$a_1, 2 = H, halo, cyano, hydrocarbyl$; $R_3 =$
 $hydrocarbyl$] $\geq 30\%$ and a polymer component 0.5-15% containing
 ≥ 1 polar moiety selected from PO_3H_2 , SO_3H , $COOH$,
 $P(=O)(OH)R_1$ [$R_1 = hydrocarbyl$ or OR_2 ; $R_2 = hydrocarbyl$], and
 cyclic anhydrides.

IT 149434-28-6P 154452-24-1P

RL: TEM (Technical or engineered material use); PREP

(Preparation); USES (Uses)

(preparation of, for electrophotog. materials for lithog. plate
 manufacture)

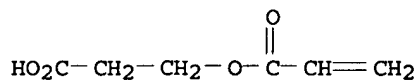
RN 149434-28-6 HCAPLUS

· CN 2-Propenoic acid, 2-methyl-, telomer with 2-mercaptoethanol and phenylbis(trifluoromethyl)silyl 2-methyl-2-propenoate, 3-[(1-oxo-2-propenyl)oxy]propanoate (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7

CMF C6 H8 O4



CM 2

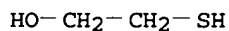
CRN 163255-66-1

CMF (C12 H10 F6 O2 Si . C4 H6 O2)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



CM 4

CRN 163255-65-0

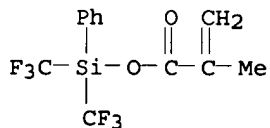
CMF (C12 H10 F6 O2 Si . C4 H6 O2)x

CCI PMS

CM 5

CRN 149072-54-8

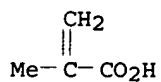
CMF C12 H10 F6 O2 Si



CM 6

CRN 79-41-4

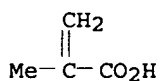
CMF C4 H6 O2



RN 154452-24-1 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl
 ester, telomer with 2-carboxyethyl 2-propenoate and
 3-mercaptopropanoic acid, 2-methyl-2-propenoate (9CI) (CA INDEX
 NAME)

CM 1

CRN 79-41-4
 CMF C4 H6 O2

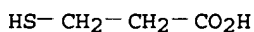


CM 2

CRN 163149-10-8
 CMF (C10 H9 F9 O2 . C6 H8 O4)x . C3 H6 O2 S

CM 3

CRN 107-96-0
 CMF C3 H6 O2 S

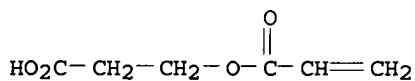


CM 4

CRN 163148-86-5
 CMF (C10 H9 F9 O2 . C6 H8 O4)x
 CCI PMS

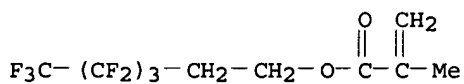
CM 5

CRN 24615-84-7
 CMF C6 H8 O4



CM 6

CRN 1799-84-4
 CMF C10 H9 F9 O2



IC ICM G03G005-147
 ICS G03G005-05; G03G005-06; G03G013-28
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)
 ST electrophotog lithog printing plate
 IT 65697-21-4P 65697-22-5P, Acrylic acid-benzyl methacrylate
 copolymer 126969-70-8P 126969-78-6P 130094-33-6P
 130952-79-3P 131808-63-4P 135740-18-0P 135740-30-6P
 135740-31-7P 135740-32-8P 135740-33-9P 135740-35-1P
 135740-36-2P 135740-37-3P 135740-38-4P 135740-39-5P
 135740-41-9P 135740-43-1P 135740-44-2P 135740-46-4P
 135770-63-7P 135820-62-1P 139663-63-1P 142648-25-7P
 145168-75-8P 145168-89-4P 145168-94-1P 145169-02-4P
 145169-03-5P 145169-04-6P 145169-24-0P 145169-26-2P
 145169-30-8P 145807-38-1P 145807-40-5P 145807-41-6P
 145807-51-8P 145807-53-0P 145807-54-1P 145807-55-2P
 145807-57-4P 145807-62-1P 145807-63-2P 145807-64-3P
 145807-65-4P 145807-66-5P 145807-68-7P 145807-72-3P
 145807-78-9P 145807-80-3P 146188-26-3DP, carboxy-terminated,
 ester with 2-hydroxyethyl methacrylate 146817-57-4P
 146817-58-5P 146817-61-0P 147524-36-5P 149072-24-2DP,
 reaction product with 2-isocyanatoethyl methacrylate
 149072-28-6P 149072-31-1P 149072-33-3P 149072-36-6P
 149072-38-8P 149072-39-9P 149072-47-9P 149072-48-0P
 149072-49-1P 149072-50-4P 149072-52-6P 149072-53-7P
 149072-55-9P 149072-56-0P 149072-99-1P 149093-43-6P
 149093-44-7P 149093-46-9P 149093-47-0P 149368-83-2P
 149434-15-1P 149434-25-3P 149434-28-6P 149658-55-9P
 150103-52-9P 150103-59-6DP, reaction product with cyanatoethyl
 methacrylate 154042-89-4P 154042-90-7P 154042-92-9P
 154042-93-0P 154042-94-1P 154042-95-2P 154042-96-3P
 154042-97-4P 154042-98-5P 154042-99-6P 154043-00-2P
 154043-01-3P 154043-02-4P 154043-03-5P 154043-04-6P
 154043-05-7P 154043-06-8P 154043-07-9P 154043-08-0P
 154043-09-1P 154043-10-4P 154043-11-5P 154397-48-5P
 154452-24-1P 154452-25-2P 154452-26-3P 154452-28-5P
 154483-07-5P
 RL: TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)
 (preparation of, for electrophotog. materials for lithog. plate
 manufacture)

L55 ANSWER 9 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1994:469569 Document No. 121:69569 Electrophotographic photoreceptor
 sheet for lithographic platemaking. Kato, Eiichi (Fuji Photo Film
 Co Ltd, Japan). Jpn. Kokai Tokkyo Koho JP 05188664 A2 19930730
 Heisei, 74 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP
 1992-20696 19920110.

AB In the title photoreceptor sheet comprising, on an elec.
 conductive support, ≥ 1 photoconductive layers and a
 surface layer, the surface layer contains nonaq. solvent-dispersed
 resin particles (L) and the photoconductive layer contains the
 binder resin (A) claimed below. L is obtained by
 dispersion polymerizing in the presence of a soluble dispersion-
 stabilizing resin, ≥ 1 monofunctional monomers containing
 ≥ 1 functional groups yielding CO₂H on decomposition, and
 aminofunctional monomer containing substituents containing Si and/or F.
 Binder resin (A) (weight average mol. weight 1×10^3 - 2×10^4) is a
 resin comprising the structure repeating unit, CHa1Ca2(CO₂R) [a1,
 aa = H, halo, CN, hydrocarbyl; R = hydrocarbyl], 30% with 1 end of
 the polymer chain terminated by ≥ 1 polar groups selected
 from PO₃H₂, SO₃H, CO₂H, P(O)(OH)R [R = hydrocarbyl or

oxyhydrocarbyl], and cyclic anhydride. Durable lithog. plates giving superior printed copies even under severe operational conditions can be obtained.

IT 149434-22-0P

RL: PREP (Preparation)

(preparation of, as monofunctional polymer)

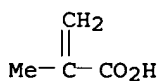
RN 149434-22-0 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, telomer with butyl 2-methyl-2-propenoate and 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

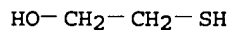
CRN 151543-37-2

CMF (C10 H14 O6 . C8 H14 O2)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



CM 4

CRN 150752-93-5

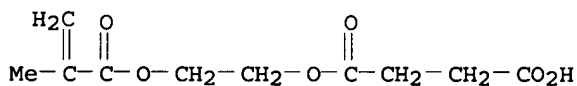
CMF (C10 H14 O6 . C8 H14 O2)x

CCI PMS

CM 5

CRN 20882-04-6

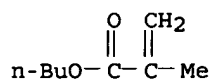
CMF C10 H14 O6



CM 6

CRN 97-88-1

CMF C8 H14 O2



- IC ICM G03G013-28
ICS G03G005-05; G03G005-06; G03G005-147
- CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35
- IT 9011-14-7DP, Methyl methacrylate homopolymer, carboxylated
31547-85-ODP, 1-Naphthyl methacrylate homopolymer,
carboxy-terminated 128338-04-5P 128338-05-6P, Benzyl
methacrylate telomer with thiosalicylic acid 138059-23-1P,
2-Naphthylmethyl methacrylate telomer with thiosalicylic acid
138059-26-4P, 2-Cyanophenyl methacrylate-ethyl methacrylate
telomer with thiosalicylic acid 138059-27-5P, 2-Phenoxyethyl
methacrylate telomer with thiosalicylic acid 138059-28-6P
138059-29-7P 138059-30-0P 138059-31-1P 138059-32-2P
138059-33-3P 138059-34-4P 138059-35-5P 138059-36-6P
139357-81-6P 139989-86-9P, Acrylic acid-benzyl methacrylate
telomer with thiosalicylic acid 139989-94-9P, Acrylic
acid-2-chlorophenyl methacrylate telomer with thiosalicylic acid
142199-53-9P, Methacrylic acid-phenyl methacrylate telomer with
thiosalicylic acid 146115-83-5P, Ethyl methacrylate-4-
vinylbenzoic acid telomer with thiosalicylic acid 146716-90-7P
146716-92-9P, 2-Benzoylphenyl methacrylate-2-phosphonoethyl
methacrylate telomer with thiosalicylic acid 146716-99-6P,
2-Carboxyethyl acrylate-ethyl methacrylate telomer with
thiosalicylic acid 146717-07-9P, 2,6-Dibromophenyl
methacrylate-3-sulfopropyl methacrylate telomer with thiosalicylic
acid 149234-62-8P, Benzyl methacrylate telomer with thioglycolic
acid 149265-85-0P, Acrylic acid-2-chloro-6-methylphenyl
methacrylate telomer with thiosalicylic acid
RL: TEM (Technical or engineered material use); PREP
(Preparation); USES (Uses)
(preparation of, as binder resin)
- IT 25719-51-1P 52229-66-0P 145807-49-4P 147130-23-2P
149072-21-9P 149234-63-9P 149235-47-2P 149368-81-0P
149368-84-3P 149433-97-6P 149433-98-7P 149433-99-8P
149434-01-5P 149434-02-6P 149434-04-8P 149434-06-0P
149434-09-3P 149434-10-6P 149434-11-7P 149434-17-3P
149434-22-0P 149434-38-8P
RL: PREP (Preparation)
(preparation of, as monofunctional polymer)
- L55 ANSWER 10 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
1994:446534 Document No. 121:46534 Electrophotographic plate for
electrophotographic lithographic plates. Kato, Eiichi; Kasai,
Seishi (Fuji Photo Film Co., Ltd., Japan). PCT Int. Appl. WO
9215048 A1 19920903, 213 pp. DESIGNATED STATES: W: US; RW: AT,
BE, CH, DE, DK, ES, FR, GB, GR, IT, LU, MC, NL, SE. (Japanese).
CODEN: PIXXD2. APPLICATION: WO 1992-JP188 19920221. PRIORITY: JP
1991-78711 19910222; JP 1991-78175 19910319; JP 1991-94886
19910402; JP 1991-156246 19910531.
- AB The title electrophotog. plate utilizing a photoconductor layer
containing photoconductive ZnO, a spectral sensitizer dye, and a
binder resin, the binder resin contains
≥1 resins (A) (weight average mol. weight 1 + 103-2 +
104) containing polymer component [CHa1a2(CO2R3)] [a1, a2 = H, halo,
CN, hydrocarbon moiety; R3 = hydrocarbon moiety] ≥ 30% and
a polymer component containing ≥1 polar groups selected from

PO₃H₂, SO₃H, CO₂H, P(O)(OH)R₁ (R₁ = hydrocarbon or oxyhydrocarbon moiety), and a cyclic acid anhydride moiety 0.5-15%. In addition, the photoconductor layer contains nonaq. medium dispersed resin fine particles (L) having particle size less than that of the maximum diameter of the photoconductive ZnO particles utilized above. L is obtained by copolymerizing a monofunctional monomer possessing ≥1 functional groups capable of decomposing to form CO₂H with another monofunctional monomer(s) in the precursor of a nonaq. solvent-soluble dispersion-stabilizing resin with structure repeating units containing F- and/or Si-containing substituents. The electrophotographic plate gives lithographic printing plates giving superior printed copies even under severe ambient conditions and having good durability.

IT 149368-85-4P 149434-22-0P 150497-82-8P

RL: PREP (Preparation); USES (Uses)

(preparation of, as dispersion stabilizing resin)

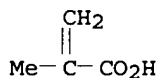
RN 149368-85-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl ester, telomer with 2-carboxyethyl 2-propenoate and 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

CRN 163148-87-6

CMF (C₁₀ H₉ F₉ O₂ . C₆ H₈ O₄)_x . C₂ H₆ O S

CM 3

CRN 60-24-2

CMF C₂ H₆ O S



CM 4

CRN 163148-86-5

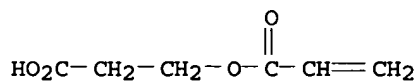
CMF (C₁₀ H₉ F₉ O₂ . C₆ H₈ O₄)_x

CCI PMS

CM 5

CRN 24615-84-7

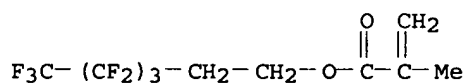
CMF C₆ H₈ O₄



CM 6

CRN 1799-84-4

CMF C10 H9 F9 O2



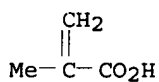
RN 149434-22-0 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, telomer with butyl 2-methyl-2-propenoate and
 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

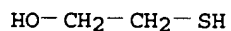
CRN 151543-37-2

CMF (C10 H14 O6 . C8 H14 O2)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



CM 4

CRN 150752-93-5

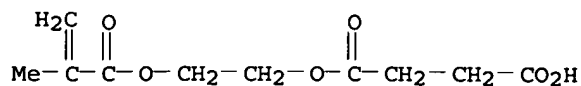
CMF (C10 H14 O6 . C8 H14 O2)x

CCI PMS

CM 5

CRN 20882-04-6

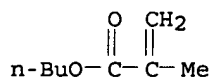
CMF C10 H14 O6



CM 6

CRN 97-88-1

CMF C8 H14 O2



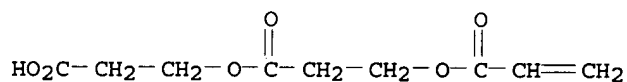
RN 150497-82-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, telomer with 2-mercaptoethanol and phenylbis(trifluoromethyl)silyl 2-methyl-2-propenoate, 3-[1-oxo-3-[(1-oxo-2-propenyl)oxy]propoxy]propanoate (9CI) (CA INDEX NAME)

CM 1

CRN 107825-26-3

CMF C9 H12 O6



CM 2

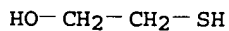
CRN 163255-66-1

CMF (C12 H10 F6 O2 Si . C4 H6 O2)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



CM 4

CRN 163255-65-0

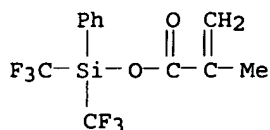
CMF (C12 H10 F6 O2 Si . C4 H6 O2)x

CCI PMS

CM 5

CRN 149072-54-8

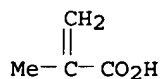
CMF C12 H10 F6 O2 Si



CM 6

CRN 79-41-4

CMF C4 H6 O2



IC ICM G03G005-05

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35

IT 80-62-6DP, Methylmethacrylate, carboxylation product
 19102-44-4DP, 1-Naphthylmethacrylate, carboxy-terminated
 30475-53-7P 65697-21-4P 65697-22-5P, Acrylic acid-benzyl methacrylate copolymer 126969-78-6P 127909-38-0P
 128338-04-5P 128338-05-6P 130094-33-6P 130952-79-3P
 131808-63-4P 135740-18-0P 135740-30-6P 135740-31-7P
 135740-32-8P 135740-33-9P 135740-35-1P 135740-37-3P
 135740-39-5P 135740-43-1P 135740-44-2P 135740-46-4P
 135740-47-5P 135770-63-7P 135820-62-1P 138059-19-5P
 138059-20-8P 138059-23-1P 138059-26-4P 138059-27-5P
 138059-28-6P 138059-30-0P 138059-31-1P 138059-33-3P
 138059-35-5P 138059-36-6P 139357-81-6P 139645-92-4P
 139989-86-9P 145169-24-0P 145807-38-1P 146115-83-5P
 146188-26-3DP, carboxy-terminated, ester with 2-hydroxyethylmethacrylate 146716-90-7P 146716-92-9P
 146716-99-6P 146717-07-9P 146817-57-4P 146817-58-5P
 146817-61-0P 146817-67-6P 147524-36-5P 149072-15-1P
 149072-16-2P 149072-17-3P 149072-18-4P 149072-19-5P
 149093-39-0P 149093-41-4P 149093-42-5P 149124-85-6P

RL: TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(preparation of, as binder resin)

IT 145168-75-8P 145168-89-4P 145168-94-1P 145169-02-4P
 145169-03-5P 145169-04-6P 145807-40-5P 145807-41-6P
 145807-53-0P 145807-54-1P 145807-55-2P 145807-56-3P
 145807-57-4P 145807-62-1P 145807-66-5P 145807-71-2P
 145807-72-3P 149072-22-0DP, reaction product with 2-isocyanatoethyl methacrylate 149072-24-2P 149072-26-4P
 149072-28-6P 149093-90-3P 149368-85-4P 149434-04-8P
 149434-06-0P 149434-15-1P 149434-21-9P 149434-22-0P
 149658-55-9P 150497-82-8P 150497-92-0P

RL: PREP (Preparation); USES (Uses)

(preparation of, as dispersion stabilizing resin)

L55 ANSWER 11 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1994:311614 Document No. 120:311614 Electrophotographic lithographic printing plate with high sensitivity to semiconductor laser scanning method. Kato, Eiichi; Kasai, Kyosuke (Fuji Photo Film Co Ltd, Japan). Jpn. Kokai Tokkyo Koho JP

05034947 A2 19930212 Heisei, 79 pp. (Japanese). CODEN: JKXXAF.

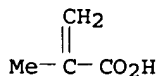
APPLICATION: JP 1991-207238 19910725.

- AB In an electrophotog. lithog. **printing plate** having ≥ 1 photoconductor layer containing a photoconductive ZnO, a spectral sensitizing dye and a **binder resin**, the photoconductor layer contains ≥ 1 **binder resin** (A) and ≥ 1 kind of nonaq. dispersion resin particles (B) whose average grain diameter is smaller than or equal to a maximum grain diameter of the photoconductive ZnO particles. The **binder resin** (A) contains the repeating unit $[a_1HCCa_2(COOR_3)]$ [$a_1, 2 = H, halo, cyano, hydrocarbon; R_3 = hydrocarbon$] having weight average mol. weight 1,000-20,000 as a polymer component $\geq 30\%$ and another polymer component 0.5-15% containing ≥ 1 polar moiety selected from $PO_3H_2, SO_3H, COOH, P(:O)(OH)R_1$ [$R_1 = hydrocarbon, OR_2; R_2 = hydrocarbon$], and a group containing cyclic anhydride. The nonaq. dispersion resin particles (B) are made of a copolymer obtained by dispersion polymerization of a monofunctional monomer (C) in the presence of a dispersion-stabilizing resin, which, soluble in the nonaq. solvent, contains a substituent containing Si and/or F, in which the monofunctional monomer (C) contains $W_1(CH_2)n_1HC:CH_2$ and/or $W_2(CH_2)n_2CH_2CH_2X$ [$W_1, 2 = SO_2, CO, OCO; n_1, n_2 = 0, 1; and X = halo$] and is soluble in the nonaq. solvent but becoming insol. upon polymerization
- IT **149368-85-4P 149434-28-6P**
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (preparation and use of, electrophotog. lithog. **printing plate** from)
- RN 149368-85-4 HCAPLUS
- CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl ester, telomer with 2-carboxyethyl 2-propenoate and 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

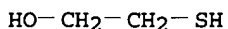
CRN 163148-87-6

CMF (C10 H9 F9 O2 . C6 H8 O4)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



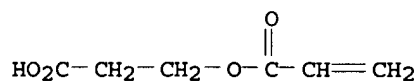
CM 4

CRN 163148-86-5

CMF (C10 H9 F9 O2 . C6 H8 O4)x
CCI PMS

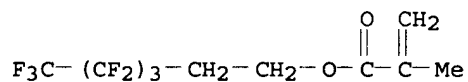
CM 5

CRN 24615-84-7
CMF C6 H8 O4



CM 6

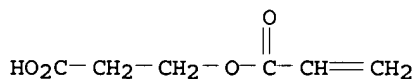
CRN 1799-84-4
CMF C10 H9 F9 O2



RN 149434-28-6 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, telomer with 2-mercaptoethanol and
phenylbis(trifluoromethyl)silyl 2-methyl-2-propenoate,
3-[(1-oxo-2-propenyl)oxy]propanoate (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7
CMF C6 H8 O4

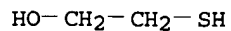


CM 2

CRN 163255-66-1
CMF (C12 H10 F6 O2 Si . C4 H6 O2)x . C2 H6 O S

CM 3

CRN 60-24-2
CMF C2 H6 O S



CM 4

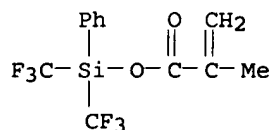
CRN 163255-65-0
CMF (C12 H10 F6 O2 Si . C4 H6 O2)x

CCI PMS

CM 5

CRN 149072-54-8

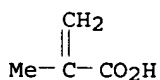
CMF C12 H10 F6 O2 Si



CM 6

CRN 79-41-4

CMF C4 H6 O2



IC ICM G03G005-05
 ICS G03G005-05; G03G005-06; G03G005-08; G03G013-28
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)
 ST electrophotog lithog **printing plate**;
binder resin electrophotog lithog printing; semiconductor
 laser scanning electrophotog lithog
 IT Lithographic plates
 (electrophotog., **binder** resins for)
 IT 145169-30-8P 149072-24-2DP, reaction product with
 2-isocyanatoethyl methacrylate 149368-83-2P **149368-85-4P**
 149434-15-1P 149434-25-3P **149434-28-6P** 149434-33-3P
 149658-55-9P 149839-15-6P 149839-16-7P 149839-17-8P
 149839-18-9P 149839-20-3P 149858-84-4P 149923-42-2P
 149923-43-3P 149923-44-4P 149923-45-5P 149923-47-7P
 149923-52-4P 149923-53-5P 149923-54-6P 149923-56-8P
 149923-57-9P 149923-58-0P 149923-59-1P 149923-60-4P
 149923-61-5P 149923-62-6P 149923-63-7P 149923-64-8P
 149923-65-9P 149923-67-1P 149961-77-3P 150103-52-9P
 152390-26-6P 152390-27-7P 152390-28-8P 152390-29-9P
 152390-30-2P 152406-06-9P 152406-07-0P 152406-09-2P
 152406-10-5P 152406-11-6P 152466-49-4P 152466-63-2P
 153014-31-4P
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (preparation and use of, electrophotog. lithog. **printing**
plate from)
 IT 65697-21-4P 65697-22-5P 126969-70-8P 126969-78-6P
 130094-33-6P 130952-79-3P 131808-63-4P 135740-18-0P
 135740-30-6P 135740-31-7P 135740-32-8P 135740-33-9P
 135740-35-1P 135740-36-2P 135740-37-3P 135740-38-4P
 135740-39-5P 135740-41-9P 135740-43-1P 135740-44-2P
 135740-46-4P 135770-63-7P 135820-62-1P 139663-63-1P
 142648-25-7P 145168-75-8P 145168-89-4P 145168-94-1P
 145169-02-4P 145169-03-5P 145169-04-6P 145169-24-0DP,
 carboxy-terminated, ester with 2-hydroxyethyl methacrylate

145807-38-1P 145807-40-5P 145807-51-8P 145807-53-0P
 145807-54-1P 145807-55-2P 145807-56-3P 145807-62-1P
 145807-63-2P 145807-64-3P 145807-65-4P 145807-66-5P
 145807-68-7P 145807-70-1P 145807-71-2P 145807-72-3P
 145807-78-9P 145807-80-3P 146188-26-3DP, carboxy-terminated,
 ester with 2-hydroxyethyl methacrylate 146817-57-4P
 146817-58-5P 146817-61-0P 147524-36-5P 150497-92-0P
 151688-53-8P 151688-55-0P

RL: PREP (Preparation)

(preparation of, electrophotog. lithog. printing
 plate from)

L55 ANSWER 12 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 1994:257467 Document No. 120:257467 Electrophotographic lithographic
 printing plate. Kato, Eiichi; Kasai, Kyosuke
 (Fuji Photo Film Co Ltd, Japan). Jpn. Kokai Tokkyo Koho JP
 05045919 A2 19930226 Heisei, 106 pp. (Japanese). CODEN: JKXXAF.
 APPLICATION: JP 1991-200506 19910809.

AB In an electrophotog. lithog. printing plate
 having ≥ 1 photoconductor layer on a conductive support and
 an uppermost surface layer thereon, the photoconductor layer
 contains a spectral sensitizing dye and ≥ 1 following
 binder resin and the surface layer contains ≥ 1
 nonaq. resin particle dispersion, in which the binder
 resin, having weight average mol. weight 1,000-20,000, contains a repeating
 unit [a1HCCa2(COOR3)] [a1,2 = H, halo, cyano, hydrocarbon; R3 =
 hydrocarbon] $\geq 30\%$ as a polymer component and one end of the
 polymer backbone chain is terminated with ≥ 1 polar moiety
 selected from PO3H2, SO3H, COOH, P(:O)(OH)R1 [R1 = hydrocarbon,
 OR2; R2 = hydrocarbon], and a cyclic anhydride and the nonaq.
 resin particle dispersion is obtained effecting dispersion polymerization
 of a monofunctional monomer, which is soluble in a nonaq. solvent but
 becoming insol. upon polymerization and forms thiol, phosphono, amino,
 and/or P(:O)(OH)R1 upon decomposition, in the presence of a dispersion
 stabilizing resin soluble in the nonaq. solvent.

IT 149434-08-2P 149434-16-2P

RL: PREP (Preparation)

(preparation of, electrophotog. lithog. printing
 plate from)

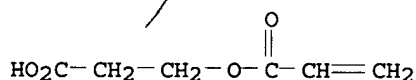
RN 149434-08-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, telomer with
 2-mercaptoethanol and 2-methyl-2-propenoic acid,
 3-[(1-oxo-2-propenyl)oxy]propanoate (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7

CMF C6 H8 O4



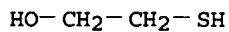
CM 2

CRN 162993-34-2

CMF (C8 H14 O2 . C4 H6 O2)x . C2 H6 O S

CM 3

CRN 60-24-2
CMF C2 H6 O S

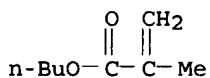


CM 4

CRN 26284-14-0
CMF (C8 H14 O2 . C4 H6 O2)x
CCI PMS

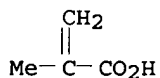
CM 5

CRN 97-88-1
CMF C8 H14 O2



CM 6

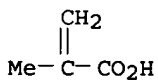
CRN 79-41-4
CMF C4 H6 O2



RN 149434-16-2 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, pentyl ester, telomer with
2-carboxyethyl 2-propenoate and 2-mercaptoethanol,
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4
CMF C4 H6 O2

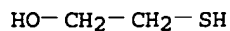


CM 2

CRN 163032-36-8
CMF (C9 H16 O2 . C6 H8 O4)x . C2 H6 O S

CM 3

CRN 60-24-2
CMF C2 H6 O S

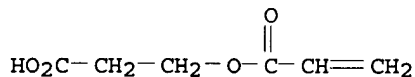


CM 4

CRN 163032-35-7
CMF (C9 H16 O2 . C6 H8 O4)x
CCI PMS

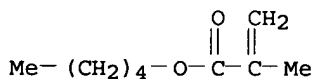
CM 5

CRN 24615-84-7
CMF C6 H8 O4



CM 6

CRN 2849-98-1
CMF C9 H16 O2



IC ICM G03G005-147
ICS G03G005-05; G03G005-06; G03G013-28
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
Other Reprographic Processes)
ST electrophotog lithog **printing plate;**
binder resin lithog printing plate;
spectral sensitizing dye printing plate
IT Lithographic plates
(electrophotog., binder resins and dispersion resin
particles for)
IT 9011-14-7DP, Methyl methacrylate homopolymer, carboxy-terminated,
1-diphenylhexyl-terminated 128338-05-6P 138059-26-4P
138059-27-5P 138059-28-6P 138059-29-7P 138059-30-0P
138059-31-1P 138059-32-2P 138059-33-3P 138059-34-4P
138059-35-5P 138123-83-8DP, carboxy-terminated 139357-80-5P
139357-81-6P 139989-86-9P 142199-53-9P 146716-90-7P
146716-92-9P 146717-07-9P 149234-62-8P 149235-48-3P
149235-49-4P 149235-51-8P 149235-54-1P 149235-55-2P
149235-56-3P 149235-57-4P 149235-60-9P 149235-61-0P
149235-62-1P 149235-69-8P 149235-70-1P 149235-73-4P
149235-84-7P 149265-82-7P 149265-84-9P 149265-85-0P
149265-87-2P 149265-89-4P 149275-09-2P 149275-10-5P
149275-12-7P 149476-82-4P 149478-77-3P 149512-92-5P
149512-93-6P 149512-94-7P 149512-95-8P 149512-96-9P
149512-97-0P 149512-98-1P 149512-99-2P 149544-80-9P

150321-29-2P 152546-30-0P 152546-32-2P 152546-33-3P
152546-35-5P 152546-36-6P 152546-37-7P 152546-39-9P
152579-45-8P 152641-11-7P 152641-12-8P 152759-74-5P
152759-75-6P

RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, electrophotog. lithog. printing
plate from)

IT 25719-51-1DP, 2-Ethylhexyl methacrylate homopolymer,
carboxy-terminated, ester with 2-hydroxyethyl methacrylate
52229-66-0P 145807-49-4P 147130-23-2P 149072-21-9DP,
reaction product with allylamine 149235-47-2P 149275-08-1DP,
reaction product with 2-isocyanatoethyl methacrylate
149368-81-0P 149433-97-6P 149433-98-7P 149433-99-8P
149434-02-6P 149434-05-9P 149434-08-2P 149434-09-3P
149434-10-6P 149434-11-7P 149434-16-2P 149434-17-3P
149434-20-8P 149434-23-1P 149434-27-5P 149434-31-1P
149434-32-2P 149434-38-8P

RL: PREP (Preparation)
(preparation of, electrophotog. lithog. printing
plate from)

L55 ANSWER 13 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
1994:231898 Document No. 120:231898 Electrophotographic lithographic
printing plate having excellent electrostatic
characteristics. Kato, Eiichi; Kasai, Kyosuke (Fuji Photo Film Co
Ltd, Japan). Jpn. Kokai Tokkyo Koho JP 05027454 A2 19930205
Heisei, 79 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP
1991-178100 19910718.

AB In an electrophotog. lithog. printing plate
having ≥ 1 photoconductor layer on a conductive support and
an uppermost surface layer, the photoconductor layer contains a
spectral sensitizing dye and ≥ 1 binder/resin (A),
and, furthermore, the uppermost surface layer contains ≥ 1
nonaq. dispersion resin particles (B). The binder
resin (A) having weight average mol. weight 1,000-20,000 contains a
repeating unit, $[a1CH-Ca2(COOR3)]$ [$a1,2 = H, halo, cyano,$
hydrocarbon; $R3 = hydrocarbon$], as a polymerizing component $\geq 30\%$
and one end of the backbone chain of the polymer is terminated
with ≥ 1 polar group selected from $PO3H2, SO3H, COOH,$
 $O:P(OH)R1,$ and cyclic anhydride. The nonaq. dispersion resin
particles (B) are obtained by polymerizing ≥ 1 monofunctional
monomer in the presence of a dispersion stabilizing resin soluble in
a nonaq. solvent; the monofunctional monomer being soluble in the
nonaq. solvent but insol. upon polymerization and containing a functional
group capable of forming ≥ 1 OH upon decomposition

IT 152728-54-6P 152728-55-7P 152728-56-8P
152728-57-9P 152728-58-0P 152728-59-1P
152728-60-4P 152728-61-5P 152750-88-4P
152750-89-5P 152751-01-4P

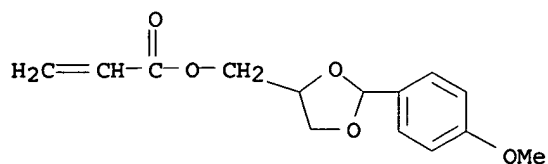
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, electrophotog. lithog. printing
plate from)

RN 152728-54-6 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
ester, polymer with butyl 2-methyl-2-propenoate, 1,2-ethanediyl
di-2-propenoate, [2-(4-methoxyphenyl)-1,3-dioxolan-4-yl]methyl
2-propenoate and 2-propenamide, graft (9CI) (CA INDEX NAME)

CM 1

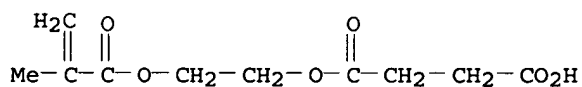
CRN 149858-20-8
CMF C14 H16 O5



CM 2

CRN 20882-04-6

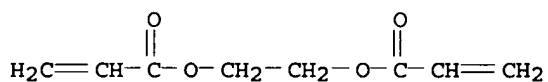
CMF C10 H14 O6



CM 3

CRN 2274-11-5

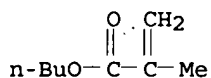
CMF C8 H10 O4



CM 4

CRN 97-88-1

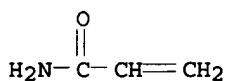
CMF C8 H14 O2



CM 5

CRN 79-06-1

CMF C3 H5 N O



RN 152728-55-7 HCAPLUS

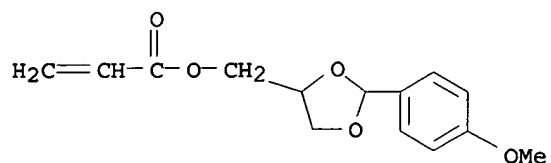
CM Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with butyl 2-methyl-2-propenoate, 1,2-ethanediyl
 bis(2-methyl-2-propenoate), [2-(4-methoxyphenyl)-1,3-dioxolan-4-

yl]methyl 2-propenoate and 2-propenamide, graft (9CI) (CA INDEX NAME)

CM 1

CRN 149858-20-8

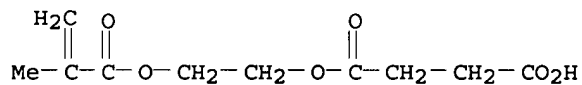
CMF C14 H16 O5



CM 2

CRN 20882-04-6

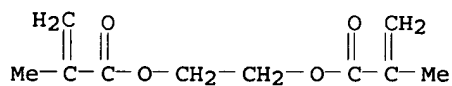
CMF C10 H14 O6



CM 3

CRN 97-90-5

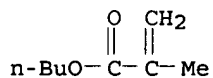
CMF C10 H14 O4



CM 4

CRN 97-88-1

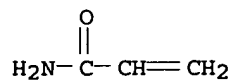
CMF C8 H14 O2



CM 5

CRN 79-06-1

CMF C3 H5 N O



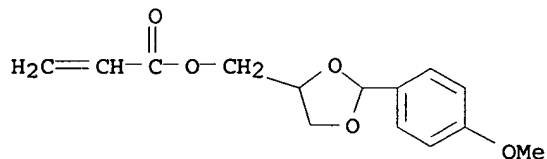
RN 152728-56-8 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with butyl 2-methyl-2-propenoate, diethenylbenzene,
 [2-(4-methoxyphenyl)-1,3-dioxolan-4-yl]methyl 2-propenoate and
 2-propenamide, graft (9CI) (CA INDEX NAME)

CM 1

CRN 149858-20-8

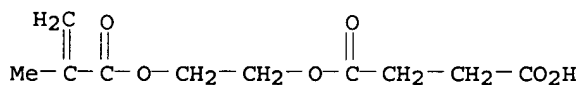
CMF C14 H16 O5



CM 2

CRN 20882-04-6

CMF C10 H14 O6

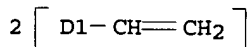


CM 3

CRN 1321-74-0

CMF C10 H10

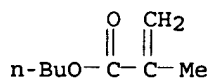
CCI IDS



CM 4

CRN 97-88-1

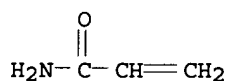
CMF C8 H14 O2



CM 5

CRN 79-06-1

CMF C3 H5 N O



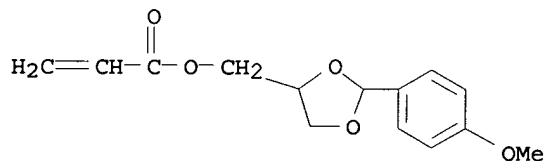
RN 152728-57-9 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with butyl 2-methyl-2-propenoate, [2-(4-methoxyphenyl)-1,3-dioxolan-4-yl]methyl 2-propenoate, oxydi-2,1-ethanediyl bis(2-methyl-2-propenoate) and 2-propenamide, graft (9CI) (CA INDEX NAME)

CM 1

CRN 149858-20-8

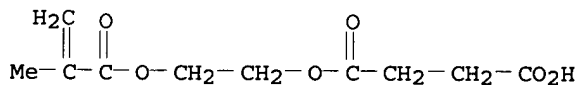
CMF C14 H16 O5



CM 2

CRN 20882-04-6

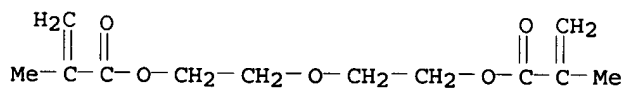
CMF C10 H14 O6



CM 3

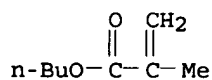
CRN 2358-84-1

CMF C12 H18 O5



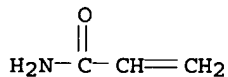
CM 4

CRN 97-88-1
CMF C8 H14 O2



CM 5

CRN 79-06-1
CMF C3 H5 N O

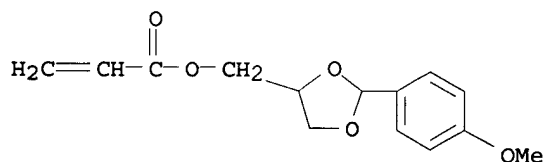


RN 152728-58-0 HCAPLUS

CM Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
ester, polymer with butyl 2-methyl-2-propenoate,
[2-(4-methoxyphenyl)-1,3-dioxolan-4-yl]methyl 2-propenoate,
2-propenamide and triethenylbenzene, graft (9CI) (CA INDEX NAME)

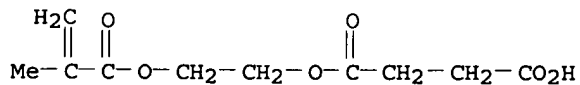
CM 1

CRN 149858-20-8
CMF C14 H16 O5



CM 2

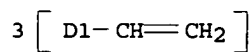
CRN 20882-04-6
CMF C10 H14 O6



CM 3

CRN 1322-23-2
CMF C12 H12

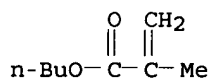
CCI IDS



CM 4

CRN 97-88-1

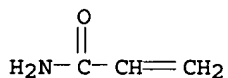
CMF C8 H14 O2



CM 5

CRN 79-06-1

CMF C3 H5 N O



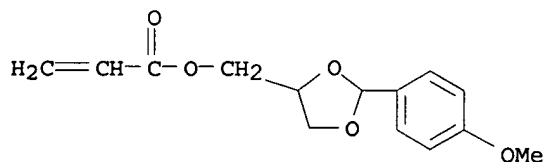
RN 152728-59-1 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with butyl 2-methyl-2-propenoate, [2-(4-methoxyphenyl)-1,3-dioxolan-4-yl]methyl 2-propenoate, 1-methyl-1,2-ethanediyl di-2-propenoate and 2-propenamide, graft (9CI) (CA INDEX NAME)

CM 1

CRN 149858-20-8

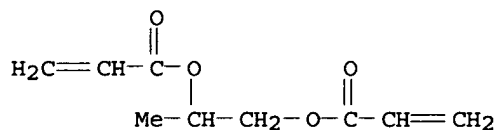
CMF C14 H16 O5



CM 2

CRN 25151-33-1

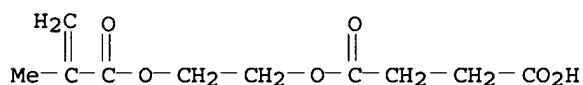
CMF C9 H12 O4



CM 3

CRN 20882-04-6

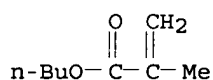
CMF C10 H14 O6



CM 4

CRN 97-88-1

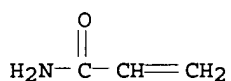
CMF C8 H14 O2



CM 5

CRN 79-06-1

CMF C3 H5 N O



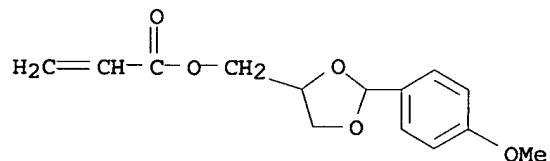
RN 152728-60-4 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with butyl 2-methyl-2-propenoate, ethenyl 2-methyl-2-propenoate, [2-(4-methoxyphenyl)-1,3-dioxolan-4-yl]methyl 2-propenoate and 2-propenamide, graft (9CI) (CA INDEX NAME)

CM 1

CRN 149858-20-8

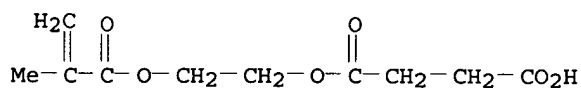
CMF C14 H16 O5



CM 2

CRN 20882-04-6

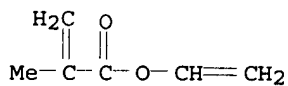
CMF C10 H14 O6



CM 3

CRN 4245-37-8

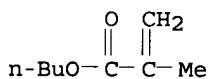
CMF C6 H8 O2



CM 4

CRN 97-88-1

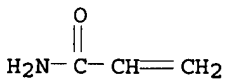
CMF C8 H14 O2



CM 5

CRN 79-06-1

CMF C3 H5 N O



RN 152728-61-5 HCAPLUS

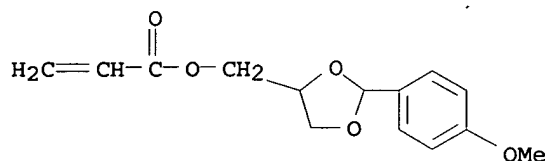
CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with butyl 2-methyl-2-propenoate,
 2-ethyl-2-[[[(2-methyl-1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl
 bis(2-methyl-2-propenoate), [2-(4-methoxyphenyl)-1,3-dioxolan-4-

yl)methyl 2-propenoate and 2-propenamide, graft (9CI) (CA INDEX NAME)

CM 1

CRN 149858-20-8

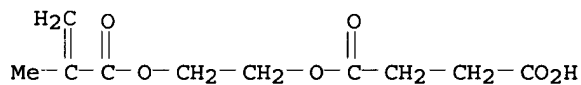
CMF C14 H16 O5



CM 2

CRN 20882-04-6

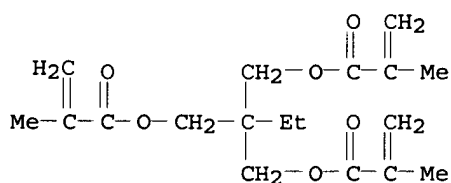
CMF C10 H14 O6



CM 3

CRN 3290-92-4

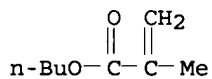
CMF C18 H26 O6



CM 4

CRN 97-88-1

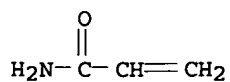
CMF C8 H14 O2



CM 5

CRN 79-06-1

CMF C3 H5 N O



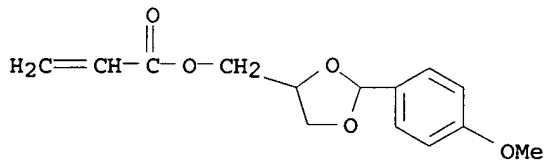
RN 152750-88-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-methyl-1,2-ethanediyl ester, polymer with butyl 2-methyl-2-propenoate, [2-(4-methoxyphenyl)-1,3-dioxolan-4-yl]methyl 2-propenoate, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] hydrogen butanedioate and 2-propenamide, graft (9CI) (CA INDEX NAME)

CM 1

CRN 149858-20-8

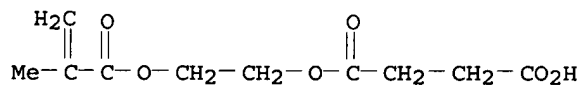
CMF C14 H16 O5



CM 2

CRN 20882-04-6

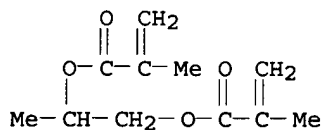
CMF C10 H14 O6



CM 3

CRN 7559-82-2

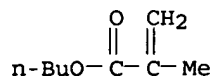
CMF C11 H16 O4



CM 4

CRN 97-88-1

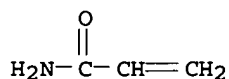
CMF C8 H14 O2



CM 5

CRN 79-06-1

CMF C3 H5 N O



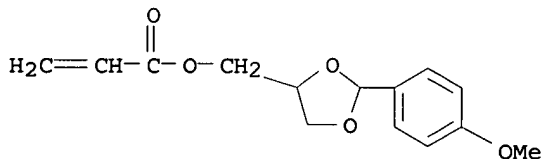
RN 152750-89-5 HCAPLUS

CM Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with butyl 2-methyl-2-propenoate,
 [2-(4-methoxyphenyl)-1,3-dioxolan-4-yl]methyl 2-propenoate,
 2-propenamide and 2-propenyl 2-methyl-2-propenoate, graft (9CI)
 (CA INDEX NAME)

CM 1

CRN 149858-20-8

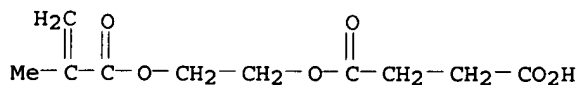
CMF C14 H16 O5



CM 2

CRN 20882-04-6

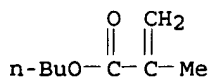
CMF C10 H14 O6



CM 3

CRN 97-88-1

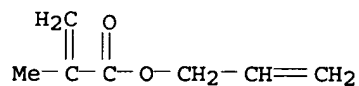
CMF C8 H14 O2



CM 4

CRN 96-05-9

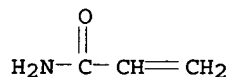
CMF C7 H10 O2



CM 5

CRN 79-06-1

CMF C3 H5 N O



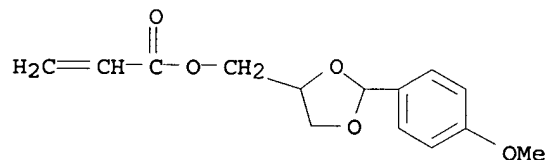
RN 152751-01-4 HCAPLUS

CN Butanedioic acid, methylene-, mono(1-methylethenyl) ester, polymer with butyl 2-methyl-2-propenoate, [2-(4-methoxyphenyl)-1,3-dioxolan-4-yl]methyl 2-propenoate, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] hydrogen butanedioate and 2-propenamide, graft (9CI) (CA INDEX NAME)

CM 1

CRN 149858-20-8

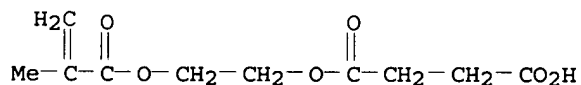
CMF C14 H16 O5



CM 2

CRN 20882-04-6

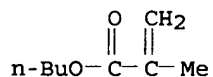
CMF C10 H14 O6



CM 3

CRN 97-88-1

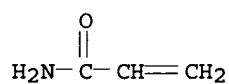
CMF C8 H14 O2



CM 4

CRN 79-06-1

CMF C3 H5 N O



CM 5

CRN 146222-07-3

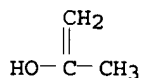
CMF C8 H10 O4

CCI IDS

CM 6

CRN 29456-04-0

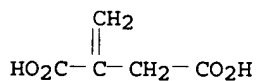
CMF C3 H6 O



CM 7

CRN 97-65-4

CMF C5 H6 O4



IT 149434-22-0P

RL: PREP (Preparation)

(preparation of, electrophotog. lithog. printing
plate from)

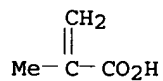
RN 149434-22-0 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
ester, telomer with butyl 2-methyl-2-propenoate and
2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

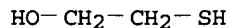
CRN 151543-37-2

CMF (C10 H14 O6 . C8 H14 O2)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



CM 4

CRN 150752-93-5

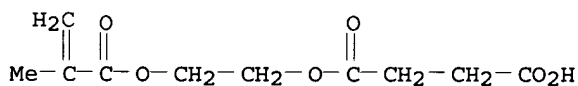
CMF (C10 H14 O6 . C8 H14 O2)x

CCI PMS

CM 5

CRN 20882-04-6

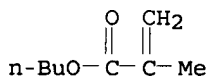
CMF C10 H14 O6



CM 6

CRN 97-88-1

CMF C8 H14 O2



IC ICM G03G005-05

ICS G03G005-06; G03G005-147; G03G013-28

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST electrophotog lithog **printing plate**; spectral sensitizing dye electrophotog lithog; **binder** resin electrophotog lithog printingIT Lithographic plates (electrophotog., **binder** resins for)

IT 150303-44-9P 150303-45-0P 150303-46-1P 150303-47-2P
 150303-48-3P 150303-49-4P 150321-69-0P 150321-70-3P
 150321-71-4P 150321-72-5P 150321-73-6P 150321-78-1P
 150321-79-2P 150344-25-5P 151205-82-2P 152728-52-4P
 152728-53-5P 152728-54-6P 152728-55-7P
 152728-56-8P 152728-57-9P 152728-58-0P
 152728-59-1P 152728-60-4P 152728-61-5P
 152728-68-2P 152728-69-3P 152728-79-5P 152750-88-4P
 152750-89-5P 152750-90-8P 152751-01-4P
 153014-11-0P

RL: SPN (Synthetic preparation); PREP (Preparation)
 (preparation and use of, electrophotog. lithog. printing
 plate from)

IT 9011-14-7DP, carboxylated, diphenylhexyl-terminated
 25719-51-1DP, carboxy-terminated, methacryloyloxyethyl derivative
 52229-66-0P 128338-04-5P 128338-05-6P, Benzyl
 methacrylate-thiosalicylic acid telomer 138059-26-4P
 138059-27-5P 138059-28-6P 138059-29-7P 138059-30-0P
 138059-32-2P 138059-33-3P 138059-34-4P 138059-35-5P
 138123-83-8DP, carboxy-terminated 139357-80-5P 139357-81-6P
 139989-86-9P 142199-53-9P 145807-49-4P 146716-90-7P
 146716-92-9P 146717-07-9P 147130-23-2P 149072-21-9P
 149234-62-8P 149234-63-9DP, reaction product with
 2-isocyanatoethyl methacrylate 149235-47-2P 149265-82-7P
 149265-84-9P 149265-85-0P 149265-87-2P 149265-89-4P
 149368-81-0P 149368-84-3P 149433-97-6P 149433-98-7P
 149433-99-8P 149434-01-5P 149434-02-6P 149434-04-8P
 149434-06-0P 149434-09-3P 149434-10-6P 149434-11-7P
 149434-17-3P 149434-22-0P 149434-38-8P 152728-71-7P

RL: PREP (Preparation)
 (preparation of, electrophotog. lithog. printing
 plate from)

IT 152752-46-0
 RL: USES (Uses)
 (spectral sensitizing dye, electrophotog. lithog.
 printing plate from)

L55 ANSWER 14 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 1994:148984 Document No. 120:148984 Manufacture of lithographic
 printing plate having excellent water-retaining
 properties. Kato, Eiichi (Fuji Photo Film Co Ltd, Japan). Jpn.
 Kokai Tokkyo Koho JP 05100504 A2 19930423 Heisei, 81 pp.
 (Japanese). CODEN: JKXAF. APPLICATION: JP 1991-289414 19911009.

AB The manufacture of a lithog. printing plate, which
 has ≥ 1 photoconductor layer on a conductive support and an
 uppermost surface layer, comprises effecting imagewise exposure of
 the lithog. printing plate containing nonaq.
 dispersion resin particles in the surface layer and and a
 binder resin in the photosensitive layer to form a toner
 image and desensitizing nonimage regions of the photoconductor
 layer with a solution containing a hydrophilic compound having a Pearson's
 nucleophilic constant ≥ 5.5 . The nonaq. dispersion resin
 particles are copolymer particles which are obtained by polymerizing in
 a nonaq. solvent a monofunctional monomer, which (soluble in the
 solvent but becoming insol. upon polymerization) contains formyl and/or
 CH(OA1)(OA2) [A1,2 = hydrocarbyl, organic residues coming together
 to form a ring], in the presence of a dispersion stabilizing resin
 made up of a repeating unit containing Si- and/or F-bearing
 substituent and the binder resin with a weight-average mol. weight
 1000-20,000 contains a repeating unit [CalHCA2(COOR1)] [a1,2 = H,
 halo, cyano, hydrocarbyl; R1 = hydrocarbyl] $\geq 30\%$ and a
 polymer component 0.5-15% containing ≥ 1 kind of a polar moiety

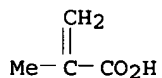
selected from PO₃H₂, SO₃H, COOH, P(:O)(OH)R₂ [R₂ = hydrocarbyl, OR₃; R₃ = hydrocarbyl] and a group containing cyclic anhydride. .

IT 149368-85-4P 149434-28-6P
 RL: TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)
 (preparation of, for lithog. printing plate
 preparation)

RN 149368-85-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl
 ester, telomer with 2-carboxyethyl 2-propenoate and
 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4
 CMF C4 H6 O2

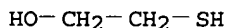


CM 2

CRN 163148-87-6
 CMF (C10 H9 F9 O2 . C6 H8 O4)x . C2 H6 O S

CM 3

CRN 60-24-2
 CMF C2 H6 O S

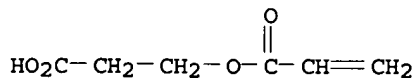


CM 4

CRN 163148-86-5
 CMF (C10 H9 F9 O2 . C6 H8 O4)x
 CCI PMS

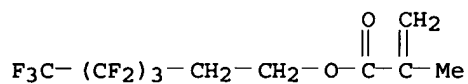
CM 5

CRN 24615-84-7
 CMF C6 H8 O4



CM 6

CRN 1799-84-4
 CMF C10 H9 F9 O2

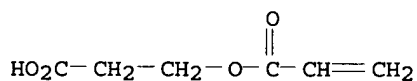


RN 149434-28-6 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, telomer with 2-mercaptoethanol and
 phenylbis(trifluoromethyl)silyl 2-methyl-2-propenoate,
 3-[(1-oxo-2-propenyl)oxy]propanoate (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7

CMF C6 H8 O4



CM 2

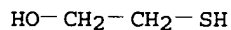
CRN 163255-66-1

CMF (C12 H10 F6 O2 Si . C4 H6 O2)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



CM 4

CRN 163255-65-0

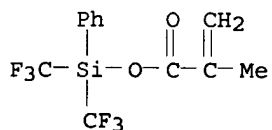
CMF (C12 H10 F6 O2 Si . C4 H6 O2)x

CCI PMS

CM 5

CRN 149072-54-8

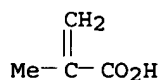
CMF C12 H10 F6 O2 Si



CM 6

CRN 79-41-4

CMF C4 H6 O2



IC ICM G03G013-28
ICS G03G005-05; G03G005-06; G03G005-147
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
Other Reprographic Processes)
ST lithog **printing plate** manuf; **binder**
resin lithog **printing plate**; dispersion resin
particle lithog printing
IT 65697-21-4P 65697-22-5P 126969-78-6P 130094-33-6P
130952-79-3P 131808-63-4P 135740-18-0P 135740-30-6P
135740-31-7P 135740-32-8P 135740-33-9P 135740-35-1P
135740-36-2P 135740-37-3P 135740-38-4P 135740-39-5P
135740-41-9P 135740-43-1P 135740-44-2P 135740-46-4P
135770-63-7P 135820-62-1P 139663-63-1P 142648-25-7P
145168-75-8P 145168-89-4P 145168-94-1P 145169-02-4P
145169-03-5P 145169-04-6P 145169-24-0P 145169-26-2P
145169-30-8P 145807-38-1P 145807-40-5P 145807-41-6P
145807-51-8P 145807-53-0P 145807-54-1P 145807-55-2P
145807-56-3P 145807-57-4P 145807-63-2P 145807-64-3P
145807-65-4P 145807-66-5P 145807-68-7P 145807-70-1P
145807-71-2P 145807-72-3P 145807-78-9P 145807-80-3P
146188-26-3DP, carboxy-terminated, ester with 2-hydroxyethyl
methacrylate 146817-57-4P 146817-58-5P 146817-61-0P
146966-35-0P 147524-36-5P 147545-76-4P 149072-24-2DP,
reaction product with 2-isocyanatoethyl methacrylate
149368-83-2P **149368-85-4P** 149434-15-1P 149434-21-9P
149434-25-3P **149434-28-6P** 149434-33-3P 149658-55-9P
149698-33-9P 149698-34-0P 149698-35-1P 149698-37-3P
149698-38-4P 149698-39-5P 149698-40-8P 149698-42-0P
149698-43-1P 149698-46-4P 149698-47-5P 149698-48-6P
149698-49-7P 149698-50-0P 149698-52-2P 149698-53-3P
149698-54-4P 149698-55-5P 149698-56-6P 149698-57-7P
149698-58-8P 149698-59-9P 149698-60-2P 149698-63-5P
149729-05-5P 149729-07-7P 149729-28-2P 149729-30-6P
149729-31-7P 149729-32-8P 149729-33-9P 149765-50-4P
149934-66-7P 149962-75-4P 151864-21-0P 152586-80-6P
152586-81-7DP, reaction product with acrylamide 153147-24-1P
RL: TEM (Technical or engineered material use); PREP
(Preparation); USES (Uses)
(preparation of, for lithog. **printing plate**
preparation)

L55 ANSWER 15 OF 29 HCAPLUS COPYRIGHT/2006 ACS on STN
1994:148983 Document No. 120:148983 Manufacture of
electrophotographic lithographic **printing plate**
having excellent water retention. Kato, Eiichi (Fuji Photo Film
Co Ltd, Japan). Jpn. Kokai Tokkyo Koho JP 05100503 A2 19930423
Heisei, 84 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP
1991-289413 19911009.
AB The manufacture of a lithog. **printing plate**, which
has ≥1 photoconductor layer on a conductive support and an
uppermost surface layer, comprises effecting imagewise exposure of
the lithog. **printing plate** containing nonaq.
dispersion resin particles in the surface layer and a
binder resin in the photosensitive layer to form a toner
image and desensitizing nonimage regions of the photoconductor

layer with a solution containing a hydrophilic compound having a Pearson's nucleophilic constant ≥ 5.5 . The nonaq. dispersion resin particles are copolymer particles which are obtained by polymerizing in a nonaq. solvent a monofunctional monomer, which (soluble in the solvent but becoming insol. upon polymerization) contains formyl and/or CH(OA1)(OA2) [A1,2 = hydrocarbyl, organic residues combining together to form a ring], in the presence of a dispersion stabilizing resin made up of a repeating unit containing Si- and/or F-bearing substituent. The binder resin with a weight-average mol. weight 1000-20,000 contains a repeating unit [Ca1HCa2(COOR1)] [a1,2 = H, halo, cyano, hydrocarbyl; R1 = hydrocarbyl] $\geq 30\%$ and terminated, on one end of the backbone chain, with a polar moiety selected from PO3H2, SO3H, COOH, P(:O)(OH)R2 [R2 = hydrocarbyl, OR3; R3 = hydrocarbyl] and a group containing cyclic anhydride.

IT 149368-85-4P 149434-28-6P

RL: TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(preparation of, for lithog. printing plate preparation)

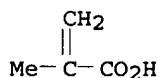
RN 149368-85-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl ester, telomer with 2-carboxyethyl 2-propenoate and 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

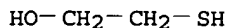
CRN 163148-87-6

CMF (C10 H9 F9 O2 . C6 H8 O4)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



CM 4

CRN 163148-86-5

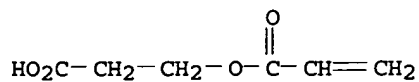
CMF (C10 H9 F9 O2 . C6 H8 O4)x

CCI PMS

CM 5

CRN 24615-84-7

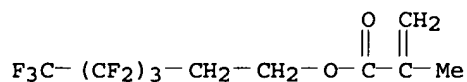
CMF C6 H8 O4



CM 6

CRN 1799-84-4

CMF C10 H9 F9 O2



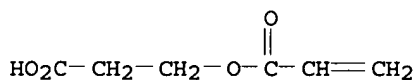
RN 149434-28-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, telomer with 2-mercaptoethanol and
 phenylbis(trifluoromethyl)silyl 2-methyl-2-propenoate,
 3-[(1-oxo-2-propenyl)oxy]propanoate (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7

CMF C6 H8 O4



CM 2

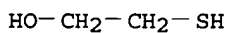
CRN 163255-66-1

CMF (C12 H10 F6 O2 Si . C4 H6 O2)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



CM 4

CRN 163255-65-0

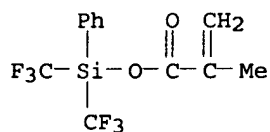
CMF (C12 H10 F6 O2 Si . C4 H6 O2)x

CCI PMS

CM 5

CRN 149072-54-8

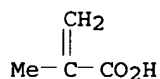
CMF C12 H10 F6 O2 Si



CM 6

CRN 79-41-4

CMF C4 H6 O2



IC ICM G03G013-28
ICS B41N003-08; G03G005-147

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST lithog **printing plate** manuf; **binder**
resin lithog **printing plate**; dispersion resin
particle lithog printing

IT 128338-04-5P 128338-05-6P 138059-23-1P 138059-26-4P
138059-27-5P 138059-28-6P 138059-29-7P 138059-30-0P
138059-31-1P 138059-32-2P 138059-33-3P 138059-34-4P
138059-35-5P 138059-36-6P 139357-81-6P 139989-86-9P
139989-94-9P 142199-53-9P 145168-75-8P 145168-89-4P
145168-94-1P 145169-02-4P 145169-03-5P 145169-04-6P
145169-24-0P 145169-26-2P 145169-30-8P 145807-38-1P
145807-40-5P 145807-41-6P 145807-51-8P 145807-53-0P
145807-54-1P 145807-55-2P 145807-56-3P 145807-57-4P
145807-63-2P 145807-64-3P 145807-65-4P 145807-66-5P
145807-68-7P 145807-70-1P 145807-71-2P 145807-72-3P
145807-78-9P 145807-80-3P 146115-83-5P 146188-26-3DP,
carboxy-terminated, ester with 2-hydroxyethyl methacrylate
146716-90-7P 146716-92-9P 146716-99-6P 146717-07-9P
146966-35-0P 147545-76-4P 149072-24-2DP, reaction product with
isocyanatoethyl methacrylate 149295-28-3P 149368-83-2P
149368-85-4P 149434-15-1P 149434-21-9P 149434-25-3P
149434-28-6P 149434-33-3P 149658-55-9P 149698-33-9P
149698-34-0P 149698-35-1P 149698-37-3P 149698-38-4P
149698-39-5P 149698-40-8P 149698-42-0P 149698-43-1P
149698-46-4P 149698-47-5P 149698-48-6P 149698-49-7P
149698-50-0P 149698-52-2P 149698-53-3P 149698-54-4P
149698-55-5P 149698-56-6P 149698-57-7P 149698-58-8P
149698-59-9P 149698-60-2P 149698-63-5P 149729-05-5P
149729-07-7P 149729-28-2P 149729-30-6P 149729-31-7P
149729-32-8P 149729-33-9P 149765-50-4P 149934-66-7P
149962-75-4P 151864-21-0P 152586-80-6P 152586-81-7DP,
reaction product with acrylamide 153147-24-1P
RL: TEM (Technical or engineered material use); PREP
(Preparation); USES (Uses)
(preparation of, for lithog. **printing plate**
preparation)

L55 ANSWER 16 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
1994:148980 Document No. 120:148980 Manufacture of lithographic
plate from electrophotographic photoreceptor. Kato, Eiichi;

Kasai, Kyosuke (Fuji Photo Film Co Ltd, Japan). Jpn. Kokai Tokkyo Koho JP 05061214 A2 19930312 Heisei, 87 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1991-250310 19910904.

AB The manufacture of a lithog. plate from an electrophotog. photoreceptor, which has ≥ 1 photosensitive layer containing at least photoconductive ZnO grains, a spectral sensitizing dye, and a binder resin on a conductive support, comprises effecting imagewise exposure of the electrophotog. photoreceptor containing the binder resin in the photosensitive layer and ≥ 1 kind of nonaq. dispersion resin grains having the average grain diameter equal to or smaller than that of the maximum grain diameter of the ZnO grains to form a toner image and effecting desensitization process of nonimage regions by using a solution containing a hydrophilic compound with Pearson's nucleophilic constant ≥ 5.5 ; The binder resin, with weight average mol. weight 1000-20,000, has a repeating unit $[\text{CHa1Ca2COOR1}]$ [$\text{a1,2} = \text{H, halo, cyano, hydrocarbyl}$; $\text{R1} = \text{hydrocarbyl}$] as a polymer component $\geq 30\%$ and another polymer component 0.5-15% containing ≥ 1 polar moiety selected from PO3H2 , SO3H , COOH , and $\text{P}(\text{:O})(\text{OH})\text{R2}$ [$\text{R2} = \text{hydrocarbyl}$ or OR3 ; $\text{R3} = \text{hydrocarbyl}$] and a moiety containing a cyclic anhydride group. The nonaq. dispersion resin grains are made of a copolymer obtained through dispersion polymerization of a monofunctional monomer, which contains formyl and/or $\text{CH}(\text{OA1})(\text{OA2})$ [$\text{A1,2} = \text{hydrocarbyl}$] and is soluble in the nonaq. solvent but becoming insol. upon polymerization, with a monofunctional monomer containing Si and/or F.

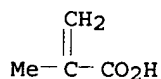
IT 149434-22-0P
RL: PREP (Preparation)
(preparation of, for electrophotog. photoreceptor for lithog. plate preparation)

RN 149434-22-0 HCAPLUS
CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, telomer with butyl 2-methyl-2-propenoate and 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

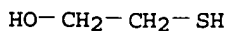
CRN 151543-37-2

CMF $(\text{C}_{10} \text{H}_{14} \text{O}_6 \cdot \text{C}_8 \text{H}_{14} \text{O}_2) \times \cdot \text{C}_2 \text{H}_6 \text{O}_2 \text{S}$

CM 3

CRN 60-24-2

CMF $\text{C}_2 \text{H}_6 \text{O}_2 \text{S}$



CM 4

CRN 150752-93-5

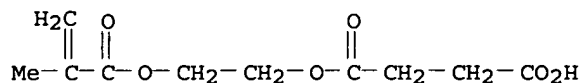
CMF (C10 H14 O6 . C8 H14 O2)x

CCI PMS

CM 5

CRN 20882-04-6

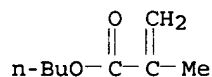
CMF C10 H14 O6



CM 6

CRN 97-88-1

CMF C8 H14 O2



IC ICM G03G005-05

ICS G03G005-05; G03G005-06; G03G005-08; G03G013-28

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST electrophotog lithog **printing plate** manuf

IT 25719-51-1DP, 2-Ethylhexyl methacrylate homopolymer, carboxy-terminated, ester with 2-hydroxyethyl methacrylate

52229-66-0P 65697-21-4P 65697-22-5P 126969-78-6P
 130094-33-6P 130952-79-3P 131808-63-4P 135740-18-0P
 135740-30-6P 135740-31-7P 135740-32-8P 135740-33-9P
 135740-35-1P 135740-36-2P 135740-37-3P 135740-38-4P
 135740-39-5P 135740-41-9P 135740-43-1P 135740-44-2P
 135740-46-4P 135770-63-7P 135820-62-1P 139645-92-4P
 139663-63-1P 142648-25-7P 145807-49-4P 146817-57-4P
 146817-58-5P 146817-61-0P 147130-23-2P 147524-36-5P
 149072-21-9DP, reaction product with allylamine 149093-90-3DP,
 reaction product with isocynoethyl methacrylate 149234-56-0P
 149234-57-1P 149234-58-2P 149234-59-3P 149234-60-6P
 149234-61-7P 149234-63-9DP, reaction product with
 2-isocyanatoethyl methacrylate 149235-47-2P 149235-75-6P
 149265-77-0P 149295-65-8P 149295-66-9P 149295-67-0P
 149368-81-0P 149368-84-3P 149433-97-6P 149433-98-7P
 149433-99-8P 149434-02-6P 149434-04-8P 149434-06-0P
 149434-09-3P 149434-10-6P 149434-11-7P 149434-17-3P
149434-22-0P 149434-38-8P 152640-58-9P 152640-60-3P
 152640-61-4P 152640-62-5P 152640-64-7P 152681-23-7P
 152681-24-8P 152681-25-9P 152681-27-1P 152681-47-5P
 152681-48-6P 152725-66-1P 152725-67-2P 152725-68-3P
 152725-69-4P 152725-70-7P 152725-71-8P 152725-72-9P
 152725-73-0P 152725-74-1P 152725-75-2P 152725-76-3P
 152725-77-4P 152725-78-5P 153014-29-0P

RL: PREP (Preparation)

(preparation of, for electrophotog. photoreceptor for lithog. plate

preparation)

L55 ANSWER 17 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1994:148866 Document No. 120:148866 Electrophotographic plate for lithographic platemaking. Kato, Eiichi; Kasaik, Kiyosuke (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 04294359 A2 19921019 Heisei, 65 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1991-81167 19910322.

AB In the title electrophotog. plate obtained by coating an elec. conductive support with ≥ 1 photoconductive layer(s) containing photoconductive ZnO, spectral sensitizing dyes and a binder resin, the above photoconductive layer(s) contains ≥ 1 resin(s) (A) as the above binder resin and ≥ 1 types of nonaq. solvent-dispersed resin particles of particle size equal to or smaller than that of the largest ZnO particles. The above resin (A) (mol. weight $1 + 103 \cdot 2 + 104$) contains polymer component CHa1Ca3CO2R ($\text{a1, a2} = \text{H, halo, CN, hydrocarbon group}$; $\text{R} = \text{hydrocarbon group}$) $\geq 30\%$, and ≥ 1 polar group(s) bonded to 1 end of the polymer main chain; the above polar group being selected from $\text{PO3H2, SO3H, CO2H, P(O)(OH)R01}$ ($\text{R01} = \text{hydrocarbon, OR02}$ ($\text{R02} = \text{hydrocarbon}$)) and cyclic acid anhydride. The above nonaq. solvent-dispersed resin particles are obtained by dispersion polymerizing a functional monomer (C) containing a functional group which produces ≥ 1 OH group on decomposition in the presence of a soluble dispersion-stabilizing resin containing structure-repeating units containing Si and F-containing substituents. The dispersion-stabilizing resin used contains polymerizable double bonds. The lithog. plates obtained with the title electrophotog. plate give superior printed copies and show good printing performance even under severe conditions; and, furthermore, the electrophotog. plate is very useful for laser scanning-exposure.

IT 149434-00-4P 149434-28-6P

RL: PREP (Preparation)
(preparation of, as macromonomer)

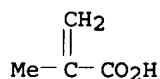
RN 149434-00-4 HCAPLUS

CN 2-Propenoic acid, 2-carboxyethyl ester, telomer with 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

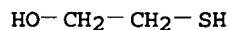
CRN 162873-02-1

CMF (C6 H8 O4)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S

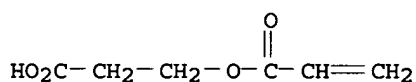


CM 4

CRN 102570-77-4
 CMF (C6 H8 O4)x
 CCI PMS

CM 5

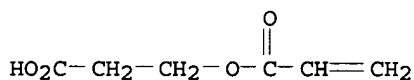
CRN 24615-84-7
 CMF C6 H8 O4



RN 149434-28-6 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, telomer with 2-mercaptoethanol and
 phenylbis(trifluoromethyl)silyl 2-methyl-2-propenoate,
 3-[(1-oxo-2-propenyl)oxy]propanoate (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7
 CMF C6 H8 O4

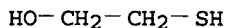


CM 2

CRN 163255-66-1
 CMF (C12 H10 F6 O2 Si . C4 H6 O2)x . C2 H6 O S

CM 3

CRN 60-24-2
 CMF C2 H6 O S



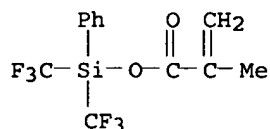
CM 4

CRN 163255-65-0
 CMF (C12 H10 F6 O2 Si . C4 H6 O2)x
 CCI PMS

CM 5

CRN 149072-54-8

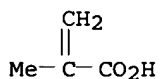
CMF C12 H10 F6 O2 Si



CM 6

CRN 79-41-4

CMF C4 H6 O2



- IC ICM G03G005-05
ICS G03G005-05; G03G005-08; G03G013-28
- CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
- IT 9011-14-7DP, Methylmethacrylate homopolymer, carboxylation product
128338-04-5P 128338-05-6P 138059-26-4P 138059-27-5P
138059-28-6P 138059-30-0P 138059-31-1P 138059-32-2P
138059-33-3P 138059-34-4P 138059-35-5P 138059-36-6P
138123-83-8P 139357-81-6P 139989-86-9P 142199-53-9P
146716-90-7P 146716-92-9P 149072-19-5P 149234-62-8P
149265-82-7P 149265-84-9P 149265-85-0P
RL: TEM (Technical or engineered material use); PREP
(Preparation); USES (Uses)
(preparation of, as binder resin)
- IT 145168-75-8P 145168-89-4P 145168-94-1P 145169-02-4P
145169-03-5P 145169-04-6P 145169-24-0P 145169-26-2P
145169-30-8P 145807-38-1P 145807-40-5P 145807-41-6P
145807-51-8P 145807-53-0P 145807-54-1P 145807-55-2P
145807-56-3P 145807-57-4P 145807-63-2P 145807-64-3P
145807-65-4P 145807-66-5P 145807-68-7P 145807-70-1P
145807-71-2P 145807-72-3P 145807-80-3P 146188-26-3DP,
carboxy-terminated, 2-hydroxyethylmethacrylate ester
147545-76-4P 149072-23-1DP, reaction product with
2-isocyanatoethylmethacrylate 149368-83-2P 149434-00-4P
149434-15-1P 149434-21-9P 149434-25-3P 149434-28-6P
149434-33-3P 150958-51-3P 150997-21-0P 151064-79-8P
RL: PREP (Preparation)
(preparation of, as macromonomer)
- L55 ANSWER 18 OF 29 HCAPLUS COPYRIGHT/2006 ACS on STN
1994:120795 Document No. 120:120795 Electrophotographic lithographic
printing plate giving high sensitivity to
semiconductor laser scanning method. Kato, Eiichi; Kasai, Kyosuke
(Fuji Photo Film Co Ltd, Japan). Jpn. Kokai Tokkyo Koho JP
05034948 A2 19930212 Heisei, 74 pp. (Japanese). CODEN: JKXXAF.
APPLICATION: JP 1991-213047 19910731.
- AB In an electrophotog. lithog. printing plate
having ≥ 1 photoconductor layer containing a photoconductive
ZnO, a spectral sensitizing dye and a binder resin, the
photoconductor layer contains ≥ 1 following binder

resin (A) and ≥ 1 kind of nonaq. dispersion resin particles (B) whose average grain diameter is smaller than or equal to the maximum grain diameter of the photoconductive ZnO particles:. The binder resin (A) contains a repeating unit $[a_1HCCa_2(COOR_3)]$ [$a_1, 2 = H, halo, cyano, hydrocarbon$; $R_3 = hydrocarbon$] having weight average mol. weight 1,000-20,000 as a polymer component $\geq 30\%$ and further contains another polymer component 0.5-1% containing ≥ 1 polar moiety selected from $PO_3H_2, SO_3H, COOH, P(:O)(OH)R_1$ [$R_1 = hydrocarbon, OR_2$; $R_2 = hydrocarbon$], and a group containing a cyclic anhydride. The nonaq. dispersion resin particles (B) are made of a copolymer obtained by dispersion polymerization of a monofunctional monomer (C) with a monofunctional monomer (D) in the presence of a dispersion-stabilizing resin soluble in the nonaq. solvent, in which the monofunctional monomer (C) contains $W_1(CH_2)n_1HC:CH_2$ and/or $W_2(CH_2)n_2CH_2CH_2X$ [$W_1, 2 = SO_2, CO, OCO$; $n_1, n_2 = 0, 1$; and $X = halo$] and is soluble in the nonaq. solvent but becoming insol. upon polymerization and the monofunctional monomer (D) contains a substituent containing Si and/or F.

IT 149434-22-0P

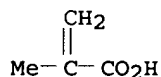
RL: PREP (Preparation)
(preparation of, electrophotog. lithog. printing plate from)

RN 149434-22-0 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, telomer with butyl 2-methyl-2-propenoate and 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4
CMF C4 H6 O2

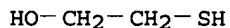


CM 2

CRN 151543-37-2
CMF (C10 H14 O6 . C8 H14 O2)x . C2 H6 O S

CM 3

CRN 60-24-2
CMF C2 H6 O S

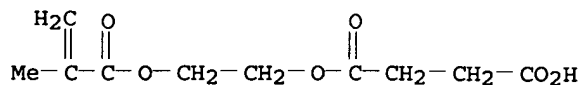


CM 4

CRN 150752-93-5
CMF (C10 H14 O6 . C8 H14 O2)x
CCI PMS

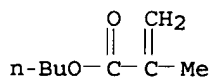
CM 5

CRN 20882-04-6
CMF C10 H14 O6



CM 6

CRN 97-88-1
CMF C8 H14 O2



- IC ICM G03G005-05
ICS G03G005-05; G03G005-06; G03G005-08; G03G013-28
- CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
- ST electrophotog lithog **printing plate**;
binder resin electrophotog lithog printing; photoconductor layer electrophotog lithog printing
- IT Lithographic plates
(electrophotog., **binder** resins for)
- IT 79-41-4DP, fluoroalkyl derivative, polymers with allyl Et sulfone and methacrylates 97-90-5DP, polymers with allyl Et sulfone and methacrylates 106-91-2DP, polymers with allyl Et sulfone and methacrylates 142-09-6DP, polymers with allyl Et sulfone and methacrylates 149839-06-5DP, polymers with methacrylates
151733-27-6P 151733-28-7P 151733-29-8P 151733-30-1P
151733-31-2P 151733-32-3P 151733-33-4P 151733-34-5P
151733-35-6P 151735-81-8P 151752-65-7P 151752-80-6P
151752-81-7P 151752-82-8P 151752-83-9P 151752-84-0P
151752-85-1P 151758-71-3P 151758-72-4P 151758-73-5P
151758-74-6P 151758-75-7P 151758-77-9P 151758-79-1P
151758-81-5P 151758-82-6P 151758-83-7P 151758-84-8P
151767-53-2P 151767-55-4P 151813-68-2P 151835-58-4P
152751-59-2P 152776-26-6P
- RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, electrophotog. lithog. **printing plate** from)
- IT 25719-51-1DP, 2-Ethylhexyl methacrylate homopolymer, carboxy-terminated, ester with glycidyl methacrylate 52229-66-0P
65697-21-4P 65697-22-5P 126969-70-8P 126969-78-6P
130094-33-6P 130952-79-3P 131808-63-4P 135740-18-0P
135740-30-6P 135740-31-7P 135740-32-8P 135740-33-9P
135740-35-1P 135740-36-2P 135740-37-3P 135740-38-4P
135740-39-5P 135740-41-9P 135740-43-1P 135740-44-2P
135740-46-4P 135770-63-7P 135820-62-1P 139663-63-1P
142648-25-7P 145807-49-4P 146817-57-4P 146817-58-5P
146817-61-0P 147130-23-2P 147524-36-5P 149072-21-9DP,
reaction product with allylamine 149234-63-9DP, reaction product with 2-isocyanatoethyl methacrylate 149235-47-2P 149368-81-0P
149368-84-3P 149433-97-6P 149433-98-7P 149433-99-8P
149434-01-5P 149434-02-6P 149434-04-8P 149434-06-0P

149434-09-3P 149434-10-6P 149434-11-7P 149434-17-3P
149434-22-0P 149434-38-8P

RL: PREP (Preparation)

(preparation of, electrophotog. lithog. printing
plate from)

L55 ANSWER 19 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1994:41999 Document No. 120:41999 Electrophotographic lithographic
printing plate giving high sensitivity to

semiconductor laser scanning method. Kato, Eiichi; Kasai, Kyosuke
(Fuji Photo Film Co Ltd, Japan). Jpn. Kokai Tokkyo Koho JP
05034949 A2 19930212 Heisei, 84 pp. (Japanese). CODEN: JKXXAF.
APPLICATION: JP 1991-213049 19910731.

AB In an electrophotog. lithog. plate having ≥ 1 photoconductor
layer containing photoconductive ZnO grains, a spectral sensitizing
dye and a binder resin with the photoconductor layer
containing ≥ 1 following binder resin (A) and
 ≥ 1 kind of nonaq. dispersion resin particles (L) whose average
grain diameter is smaller than or equal to the maximum grain diameter of
the photoconductive ZnO particles, a toner image is formed on the
photoreceptor by imagewise exposure following elec. charging, and
nonimage regions of the photoconductor layer are desensitized with
a hydrophilic compound-containing solution having Pearson's nucleophilic
constant ≥ 5.5 . The binder resin (A) (weight average mol.
weight 1,000-20,000) contains a repeating unit [a1HC-Ca2(COOR3)]
[a1,2 = H, halo, cyano, hydrocarbon; R3 = hydrocarbon] as a
polymer component $\geq 30\%$ and further contains a polymer
component 0.5-15% having ≥ 1 polar moiety selected from
PO3H2, SO3H, COOH, P(:O)(OH)R1 [R1 = hydrocarbon, OR2; R2 =
hydrocarbon], and group containing cyclic anhydride. The nonaq.
dispersion resin particles (L) are made of a copolymer obtained by
dispersion polymerization of a monofunctional monomer (C) in the presence
of a dispersion stabilizing resin, which, soluble in a nonaq.
solvent, contains a repeating unit containing a moiety having Si
and/or F, in which the monofunctional monomer (C), which, soluble in
the nonaq. solvent but insol. upon polymerization, contains ≥ 1
functional group from formyl and/or HC(OA1)(OA2) [A1,2 =
hydrocarbon; or may form a cyclic residue by combining together].

IT 149368-85-4P 149434-28-6P

RL: PREP (Preparation)

(preparation of, electrophotog. lithog. printing
plate from)

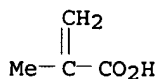
RN 149368-85-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl
ester, telomer with 2-carboxyethyl 2-propenoate and
2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

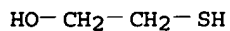
CRN 163148-87-6

CMF (C10 H9 F9 O2 . C6 H8 O4)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S



CM 4

CRN 163148-86-5

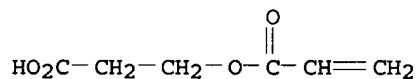
CMF (C10 H9 F9 O2 . C6 H8 O4)x

CCI PMS

CM 5

CRN 24615-84-7

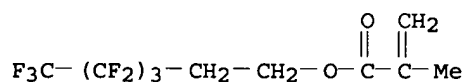
CMF C6 H8 O4



CM 6

CRN 1799-84-4

CMF C10 H9 F9 O2



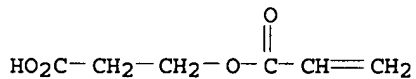
RN 149434-28-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, telomer with 2-mercaptoethanol and phenylbis(trifluoromethyl)silyl 2-methyl-2-propenoate, 3-[(1-oxo-2-propenyl)oxy]propanoate (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7

CMF C6 H8 O4

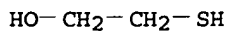


CM 2

CRN 163255-66-1

CMF (C12 H10 F6 O2 Si . C4 H6 O2)x . C2 H6 O S

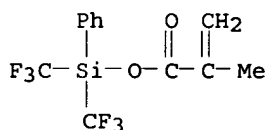
CM 3

CRN 60-24-2
CMF C2 H6 O S

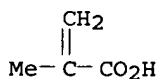
CM 4

CRN 163255-65-0
CMF (C12 H10 F6 O2 Si . C4 H6 O2)x
CCI PMS

CM 5

CRN 149072-54-8
CMF C12 H10 F6 O2 Si

CM 6

CRN 79-41-4
CMF C4 H6 O2

IC ICM G03G005-05
ICS G03G005-05; G03G005-06; G03G005-08; G03G013-28
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
Other Reprographic Processes)
ST electrophotog lithog **printing plate**;
binder resin electrophotog lithog printing; photoconductor
layer electrophotog lithog printing
IT Lithographic plates
(electrophotog., **binder** resins for)
IT 65697-21-4P 65697-22-5P 126969-70-8P 126969-78-6P
130094-33-6P 130952-79-3P 131808-63-4P 135740-18-0P
135740-30-6P 135740-31-7P 135740-32-8P 135740-33-9P
135740-35-1P 135740-36-2P 135740-37-3P 135740-38-4P
135740-39-5P 135740-41-9P 135740-43-1P 135740-44-2P
135740-46-4P 135770-63-7P 135820-62-1P 139663-63-1P
142648-25-7P 145168-75-8P 145168-89-4P 145168-94-1P
145169-02-4P 145169-03-5P 145169-04-6P 145169-24-0P
145169-30-8P 145807-38-1P 145807-40-5P 145807-51-8P
145807-53-0P 145807-54-1P 145807-55-2P 145807-56-3P
145807-62-1P 145807-63-2P 145807-64-3P 145807-65-4P

145807-66-5P 145807-68-7P 145807-70-1P 145807-71-2P
 145807-72-3P 145807-78-9P 145807-80-3P 146188-26-3DP,
 carboxy-terminated, ester with 2-hydroxyethyl methacrylate
 146817-57-4P 146817-58-5P 147524-36-5P 149072-24-2DP,
 reaction product with 2-isocyanatoethyl methacrylate
 149368-83-2P **149368-85-4P** 149434-15-1P 149434-25-3P
149434-28-6P 149434-33-3P 149658-55-9P 149698-39-5P
 149698-40-8P 149698-42-0P 149698-43-1P 149698-46-4P
 149698-47-5P 149698-48-6P 149698-49-7P 149698-50-0P
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 149698-56-6P 149698-57-7P 149698-58-8P 149698-59-9P
 149698-60-2P 149729-05-5P 149729-06-6P 149729-30-6P
 149729-31-7P 149729-32-8P 149729-33-9P 149765-50-4P
 149934-66-7P 150103-52-9P 150497-92-0P 151688-53-8P
 151688-55-0P 151709-96-5P 151709-97-6P 151754-98-2P
 151754-99-3P 151755-00-9P 151755-01-0P 151755-02-1P
 151755-03-2P 151755-05-4P 151755-06-5P 151755-07-6P
 151864-21-0P 152103-17-8P

RL: PREP (Preparation)

(preparation of, electrophotog. lithog. printing
 plate from)

L55 ANSWER 20 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 1994:19283 Document No. 120:19283 Electrophotographic lithographic
 printing plate giving high sensitivity to
 semiconductor laser scanning method. Kato, Eiichi; Kasai, Kyosuke
 (Fuji Photo Film Co Ltd, Japan). Jpn. Kokai Tokkyo Koho JP
 05034950 A2 19930212 Heisei, 75 pp. (Japanese). CODEN: JKXXAF.
 APPLICATION: JP 1991-213050 19910731.

AB In an electrophotog. lithog. printing plate
 having ≥ 1 photoconductor layer containing photoconductive ZnO,
 spectral sensitizing dye and binder resin, the
 photoconductor layer contains ≥ 1 kinds of binder
 resin (A) and ≥ 1 kinds of nonaq. dispersion resin particles
 (B) whose average grain diameter is smaller than or equal to the maximum
 grain diameter of the photoconductive ZnO particles. The
 binder resin (A) contains a repeating unit
 $[a_1HC-Ca_2(COOR_3)]$ [$a_1, 2 = H, halo, cyano, hydrocarbon$; $R_3 =$
 $hydrocarbon$] having weight average mol. weight 1,000-20,000 as a polymer
 component $\geq 30\%$ and further contains ≥ 1 polar moiety
 selected from $PO_3H_2, SO_3H, COOH, P(=O)(OH)R_1$ [$R_1 = hydrocarbon,$
 OR_2 ; $R_2 = hydrocarbon$], and a group containing a cyclic anhydride
 which terminates at least one end of the polymer backbone chain.
 The nonaq. dispersion resin particles (B) are made of a copolymer
 obtained by dispersion polymerization of a monofunctional monomer (C)
 with a monofunctional monomer (D) in the presence of a
 dispersion-stabilizing resin soluble in the nonaq. solvent, in which
 the monofunctional monomer (C) contains $W_1(CH_2)n_1HC:CH_2$ and/or
 $W_2(CH_2)n_2CH_2CH_2X$ [$W_{1,2} = SO_2, CO, OCO$; $n_1, n_2 = 0, 1$; and $X =$
 $halo$] and is soluble in the nonaq. solvent but becoming insol. upon
 polymerization and the monofunctional monomer (D) contains a substituent
 containing Si and/or F.

IT **149434-22-0P**

RL: PREP (Preparation)

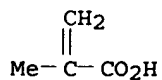
(preparation of, electrophotog. lithog. printing
 plate from)

RN 149434-22-0 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, telomer with butyl 2-methyl-2-propenoate and
 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4
CMF C4 H6 O2

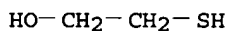


CM 2

CRN 151543-37-2
CMF (C10 H14 O6 . C8 H14 O2)x . C2 H6 O S

CM 3

CRN 60-24-2
CMF C2 H6 O S

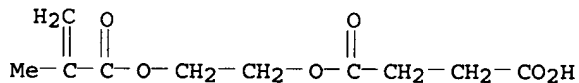


CM 4

CRN 150752-93-5
CMF (C10 H14 O6 . C8 H14 O2)x
CCI PMS

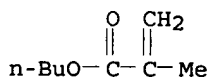
CM 5

CRN 20882-04-6
CMF C10 H14 O6



CM 6

CRN 97-88-1
CMF C8 H14 O2

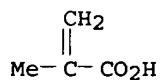


IC ICM G03G005-05
ICS G03G005-05; G03G005-06; G03G005-08; G03G013-28
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST electrophotog lithog printing plate;
binder resin electrophotog lithog printing; photoconductor layer electrophotog lithog printing

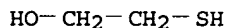
- IT Lithographic plates
(electrophotog., binder resins for)
- IT 151752-85-1P
RL: PREP (Preparation)
(preparation and use of , electrophotog. lithog. printing plate from)
- IT 149839-06-5DP, polymers with methacrylates 151733-27-6P
151733-28-7P 151733-29-8P 151733-30-1P 151733-31-2P
151733-32-3P 151733-33-4P 151733-34-5P 151733-35-6P
151735-81-8P 151752-65-7P 151752-80-6P 151752-81-7P
151752-82-8P 151752-83-9P 151752-84-0P 151758-71-3P
151758-72-4P 151758-73-5P 151758-74-6P 151758-75-7P
151758-76-8P 151758-77-9P 151758-79-1P 151758-81-5P
151758-82-6P 151758-83-7P 151758-84-8P 151767-53-2P
151767-55-4P 151813-66-0P 151813-68-2P 151835-58-4P
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of of, electrophotog. lithog. printing plate from)
- IT 79-41-4DP, fluoroalkyl derivs., polymers with methacrylates and allyl Et sulfone 97-90-5DP, polymers with methacrylates and allyl Et sulfone 106-91-2DP, polymers with methacrylates and allyl Et sulfone 142-09-6DP, polymers with methacrylates and allyl Et sulfone
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, electrophotog. lithog. printing plate from)
- IT 9011-14-7DP, Methyl methacrylate homopolymer, carboxylated, terminated with diphenylhexylhexane 25719-51-1DP, 2-Ethylhexyl methacrylate homopolymer, carboxy-terminated, ester with 2-hydroxyethyl methacrylate 52229-66-0P 128338-04-5P
128338-05-6P, Benzyl methacrylate-thiosalicylic acid telomer
138059-23-1P 138059-26-4P 138059-27-5P 138059-28-6P
138059-29-7P 138059-30-0P 138059-31-1P 138059-32-2P
138059-33-3P 138059-34-4P 138059-35-5P 138123-83-8DP,
carboxy-terminated 139357-81-6P 139989-86-9P 139989-94-9P
142199-53-9P 145807-49-4P 146115-83-5P 146716-90-7P
146716-92-9P 146716-99-6P 146717-07-9P 147130-23-2P
149072-21-9DP, reaction product with allylamine 149234-63-9DP,
reaction product with 2-isocyanatoethyl methacrylate
149235-47-2P 149295-28-3P 149368-81-0P 149368-84-3P
149433-97-6P 149433-98-7P 149433-99-8P 149434-01-5P
149434-02-6P 149434-04-8P 149434-06-0P 149434-09-3P
149434-10-6P 149434-11-7P 149434-17-3P 149434-22-0P
149434-38-8P 151733-39-0P
RL: PREP (Preparation)
(preparation of, electrophotog. lithog. printing plate from)
- L55 ANSWER 21 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
1993:637907 Document No. 119:237907 Electrophotographic plate for lithographic platemaking. Kato, Eiichi (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 04298757 A2 19921022 Heisei, 42 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1991-64403 19910328.
- AB The title electrophotog. plate comprises on an elec. conductive support ≥ 1 photoconductive layer(s) containing photoconductive ZnO, a binder resin, and ≥ 1 nonaq. solvent-dispersed resin particles. The above resin particles are obtained by dispersion polymerizing a functional monomer which contains a functional group capable of producing ≥ 1 carboxyl(s) on decomposition (in a nonaq. solvent), with a functional monomer containing Si- and(or) F-containing substituents in the presence of a nonaq.

solvent-soluble dispersion-stabilizing resin. The dispersion-stabilizing resin used contains polymerizable double bonds. The title **printing plate** shows superior electrostatic characteristics, and allows superior desensitization for offset masters to give sharp and good printed copies under (low-temperature)-(low-humidity) or (high-temperature)-(high-humidity) conditions.

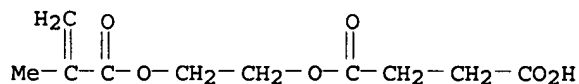
IT 149434-22-0P
 RL: TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)
 (preparation of, as dispersion-stabilizing resin)
 RN 149434-22-0 HCAPLUS
 CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, telomer with butyl 2-methyl-2-propenoate and
 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)
 CM 1
 CRN 79-41-4
 CMF C4 H6 O2



CM 2
 CRN 151543-37-2
 CMF (C10 H14 O6 . C8 H14 O2)x . C2 H6 O S
 CM 3
 CRN 60-24-2
 CMF C2 H6 O S

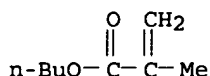


CM 4
 CRN 150752-93-5
 CMF (C10 H14 O6 . C8 H14 O2)x
 CCI PMS
 CM 5
 CRN 20882-04-6
 CMF C10 H14 O6



CM 6

CRN 97-88-1
CMF C8 H14 O2



IC ICM G03G005-06
ICS G03G005-05; G03G013-28

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 149072-21-9DP, allylamide 149093-90-3DP, reaction product with carboxymethacryloylamine 149234-63-9DP, reaction product with 2-isocyanatoethylmethacrylate 149235-47-2P 149368-84-3P 149434-04-8P 149434-06-0P 149434-10-6P 149434-11-7P 149434-22-0P
RL: TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(preparation of, as dispersion-stabilizing resin)

L55 ANSWER 22 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
1993:570521 Document No. 119:170521 Electrophotographic lithographic printing plate. Kato, Eiichi; Kasai, Kyosuke; Yamazaki, Hirohisa (Fuji Photo Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 04268563 A2 19920924 Heisei, 47 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1991-78710/19910222.

AB An electrophotog. lithog. printing plate having a photoconductor layer from photoconductive ZnO and a binder resin on a conductive support is characterized in that the photoconductive layer contains ≥ 1 binder resin and also contains ≥ 1 types of non-aqueous dispersion resin particles whose diameter are equal to or small than the maximum diameter of the ZnO particles. The binder resin with weight average mol. weight 1,000-20,000 contains a repeating unit [a1HC-Ca2(COOR3)] [a1, a2 = H, halo, cyano, hydrocarbon; R3 = hydrocarbon] $\geq 30\%$ and a polymer component containing polar moieties 0.5-15%. The non-aqueous dispersion resin particles are obtained by polymerizing a monofunctional monomer with ≥ 1 polar moiety in the presence of a dispersion stabilizing resin.

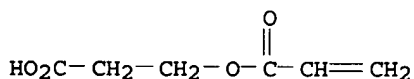
IT 148208-15-5P
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, electrophotog. lithog. printing plate from)

RN 148208-15-5 HCAPLUS

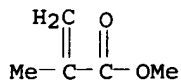
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 2-carboxyethyl 2-propenoate and 2-propenoic acid, graft (9CI) (CA INDEX NAME)

CM 1

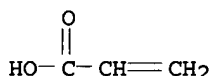
CRN 24615-84-7
CMF C6 H8 O4



CM 2

CRN 80-62-6
CMF C5 H8 O2

CM 3

CRN 79-10-7
CMF C3 H4 O2

- IC ICM G03G005-05
ICS G03G005-05; G03G005-08; G03G013-28
- CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
- ST electrophotog lithog **printing plate**;
binder resin electrophotog lithog printing; acrylic resin
electrophotog lithog plate
- IT Lithographic plates
(electrophotog., binder resins and resin particles
in)
- IT 9010-88-2D, Methyl methacrylateethyl acrylate copolymer,
carboxy-terminated 25135-39-1, Methyl methacrylateethyl
acrylate-acrylic acid copolymer 36582-66-8 128440-91-5D,
carboxy-terminated 146056-80-6D, carboxy-terminated
RL: USES (Uses)
(electrophotog. lithog. **printing plate**
from)
- IT 25719-51-1DP, carboxy-terminated, reaction product with
2-hydroxyethyl methacrylate 145807-49-4P 148878-95-9P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP
(Preparation); RACT (Reactant or reagent)
(preparation and reaction of, electrophotog. lithog.
printing plate from)
- IT 61156-93-2P, Methyl methacrylate-acrylic acid-crotonic acid
copolymer 111966-24-6P 126034-11-5P 144016-72-8P
148208-03-1P 148208-04-2P 148208-05-3P 148208-06-4P
148208-07-5P 148208-08-6P 148208-09-7P 148208-10-0P
148208-11-1P 148208-12-2P 148208-13-3P 148208-14-4P
148208-15-5P 148208-16-6P 148208-17-7P 148208-18-8P
148208-19-9P 148208-20-2P 148208-21-3P 148208-22-4P
148226-54-4P 148226-55-5P 148226-56-6P 148261-40-9P
148261-41-0P 149038-54-0P 149378-63-2P
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, electrophotog. lithog. **printing**
plate from)
- IT 9011-14-7DP, Methyl methacrylate homopolymer, carboxy-terminated
31547-85-ODP, carboxy-terminated 128338-04-5P 128338-05-6P,
Benzyl methacrylate-thiosalicylic acid telomer 138059-19-5P

138059-20-8P 138059-23-1P 138059-26-4P 138059-27-5P
 138059-28-6P 138059-29-7P 138059-30-0P 138059-31-1P
 138059-32-2P 138059-33-3P 138059-34-4P 138059-35-5P
 138059-36-6P 139357-81-6P 139989-86-9P 142199-53-9P
 146115-83-5P 146716-90-7P 146716-92-9P 146716-99-6P
 146717-07-9P

RL: PREP (Preparation)

(preparation of, electrophotog. lithog. printing
 plate from)

L55 ANSWER 23 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 1993:570434 Document No. 119:170434 Electrophotographic plates for
 lithographic master. Kato, Eiichi; Kasai, Kyosuke (Fuji Photo
 Film Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 04296866 A2
 19921021 Heisei, 62 pp. (Japanese). CODEN: JKXXAF. APPLICATION:
 JP 1991-85796 19910327.

AB In the title electrophotog. plate obtained by coating an elec.
 conductive support with ≥ 1 photoconductive layer(s) containing
 photoconductive ZnO, spectral sensitizing dyes and a
 binder resin, the above photoconductive layer(s) contains
 ≥ 1 resin(s) (A) as the above binder resin and
 ≥ 1 types of nonaq. solvent-dispersed resin particles of
 particle size equal to or smaller than that of the largest ZnO
 particles. The above resin (A) (mol. weight $1 + 103-2 +$
 104) contains polymer component CHAlCa2CO2R ($a_1, a_2 = \text{H, halo, CN,}$
 hydrocarbon group; $R = \text{hydrocarbon group}$) $\geq 30\%$, and
 ≥ 1 polar group(s) bonded to 1 end of the polymer main
 chain; the above polar group being selected from PO3H2, SO3H,
 CO2H, P(O)(OH)R01 ($R01 = \text{hydrocarbon, OR02}$ ($R02 = \text{hydrocarbon}$))
 and cyclic acid anhydride. The above nonaq. solvent-dispersed
 resin particles are obtained by dispersion polymerizing a functional
 monomer containing a functional group which produces $\geq \text{OH}$
 group(s) on decomposition with a functional monomer containing a Si-
 and(or) F-containing group in the presence of a nonaq. solvent-soluble
 dispersion-stabilizing resin. The dispersion-stabilizing resin
 used contains ≥ 1 polymerizable double bonds in its polymer
 chain. An electrophotog. receptor with superior electrostatic and
 mech. properties can be obtained even under severe conditions, the
 lithog. plates show good printing performance,
 and, furthermore, the electrophotog. plate is very useful for
 laser scanning-exposure.

IT 149434-22-0P

RL: TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)
 (preparation of, as dispersion-stabilizing resin)

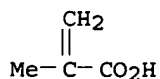
RN 149434-22-0 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, telomer with butyl 2-methyl-2-propenoate and
 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4

CMF C4 H6 O2



CM 2

CRN 151543-37-2

CMF (C10 H14 O6 . C8 H14 O2)x . C2 H6 O S

CM 3

CRN 60-24-2

CMF C2 H6 O S

HO-CH₂-CH₂-SH

CM 4

CRN 150752-93-5

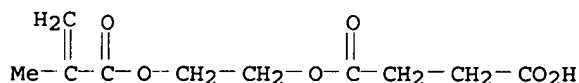
CMF (C10 H14 O6 . C8 H14 O2)x

CCI PMS

CM 5

CRN 20882-04-6

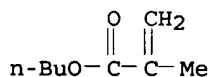
CMF C10 H14 O6



CM 6

CRN 97-88-1

CMF C8 H14 O2



IC ICM G03G005-05

ICS G03G005-05; G03G005-08; G03G013-28

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 35

IT 25719-51-1DP, 2-Ethylhexyl methacrylate homopolymer,
 carboxy-terminated ester with 2-hydroxyethyl methacrylate
 52229-66-0P 145807-49-4P 147130-23-2P 149072-21-9DP,
 reaction product with allylamine 149234-63-9DP, reaction product
 with 2-isocyanatoethyl methacrylate 149235-47-2P 149368-84-3P
 149433-97-6P 149433-98-7P 149433-99-8P 149434-01-5P
 149434-02-6P 149434-04-8P 149434-06-0P 149434-09-3P
 149434-10-6P 149434-11-7P 149434-17-3P **149434-22-0P**
 149434-38-8P 150103-50-7P

RL: TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)

(preparation of, as dispersion-stabilizing resin)

L55 ANSWER 24 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
 1992:458836 Document No. 117:58836 Electrophotographic
 light-sensitive material. Kato, Eiichi (Fuji Photo Film Co.,
 Ltd., Japan). Eur. Pat. Appl. EP 432727 A2 19910619, 96 pp.
 DESIGNATED STATES: R: DE, GB. (English). CODEN: EPXXDW.
 APPLICATION: EP 1990-123810 19901211. PRIORITY: JP 1989-320639
 19891212; JP 1990-126782 19900518.

AB An electrophotog. light-sensitive material is described having a
 photoconductive layer containing ≥ 1 inorg. photoconductive
 substance and a binder resin, where the binder
 resin contains an AB block copolymer having a weight average mol. weight of
 from $1 + 10^3$ to $2 + 10^4$ and composed of a 1st block
 comprising ≥ 1 polymer component containing ≥ 1 acidic
 group selected from $-PO_2H_2$, $-COOH$, $-SO_3H$, a phenolic hydroxy
 group, $-P(R)(O)OH$. [R represents a hydrocarbon group or $-OR'$
 (wherein R' represents a hydrocarbon group)) and a cyclic acid
 anhydride-containing group], and a 2nd block containing > 1 polymer
 component represented by $-CH_2-CMC(CO_2R')$ - [R1 represents a
 hydrocarbon group]. The material has improved mech. properties.

IT 141738-70-7

RL: USES (Uses)

(as binder in electrophotog. plate)

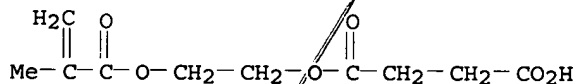
RN 141738-70-7 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with 2-chlorophenyl 2-methyl-2-propenoate,
 phenylmethyl 2-methyl-2-propenoate, 2-propenoic acid and
 3a,4,7,7a-tetrahydro-1,3-isobenzofurandione, block (9CI) (CA
 INDEX NAME)

CM 1

CRN 20882-04-6

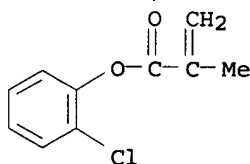
CMF C10 H14 O6



CM 2

CRN 18967-23-2

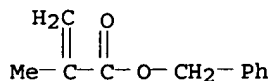
CMF C10 H9 Cl O2



CM 3

CRN 2495-37-6

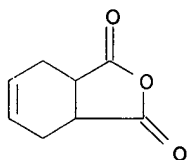
CMF C11 H12 O2



CM 4

CRN 85-43-8

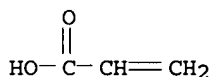
CMF C8 H8 O3



CM 5

CRN 79-10-7

CMF C3 H4 O2



IC ICM G03G005-05
 CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)
 ST electrophotog plate binder resin
 IT Electrophotographic photoconductors and photoreceptors
 Printing plates
 (binder resin for)

IT 9003-42-3 9003-63-8 26335-61-5 28062-47-7 28572-98-7
 29531-62-2 60472-59-5 72923-41-2 72923-42-3 79042-18-5
 81772-37-4 101842-61-9 109116-83-8, Dianal LR 186
 118786-81-5 118786-83-7 120823-88-3 120823-89-4
 128294-84-8 131004-74-5 131808-83-8 131808-84-9
 131808-86-1 131808-87-2 131808-88-3 131808-91-8
 131837-97-3 131914-87-9 137292-82-1 141656-65-7
 141656-66-8 141680-32-2 141680-33-3 141680-34-4
 141680-35-5 141680-36-6 141681-02-9 141681-04-1
 141698-79-5 141714-29-6 141714-30-9 141714-31-0
 141714-32-1 141714-33-2 141714-34-3 141714-35-4
 141714-36-5 141714-37-6 141714-38-7 141714-39-8
 141714-40-1 141714-41-2 141714-42-3 141714-43-4
 141714-44-5 141714-45-6 141738-68-3 141738-69-4
 141738-70-7 142453-80-3
 RL: USES (Uses)
 (as binder in electrophotog. plate)

IT 138115-34-1DP, hydrolyzed 138136-28-4DP, hydrolyzed
 138232-67-4DP, hydrolyzed 138232-68-5P 141681-05-2P
 141681-06-3P 141681-07-4P 141681-08-5P 141681-09-6P
 141681-10-9P 141681-11-0P 141681-12-1P 141681-13-2P
 141681-14-3P 141681-15-4P 141681-16-5P 141681-17-6P
 141681-18-7P 141681-19-8P 141681-20-1P 141681-21-2P

141698-82-0P 141725-80-6P

RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, as **binder** in electrophotog.
plate)

L55 ANSWER 25 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
1992:417227 Document No. 117:17227 An electrophotographic
lithographic **printing plate** precursor. Kato,
Eiichi; Oda, Akio; Kasai, Seishi (Fuji Photo Film Co., Ltd.,
Japan). Eur. Pat. Appl. EP 422888 A2 1991/0417, 65 pp. DESIGNATED
STATES: R: DE, GB. (English). CODEN: EPXXDW. APPLICATION: EP
1990-311039 19901009. PRIORITY: JP 1989-263108 19891011; JP
1989-285021 19891102.

AB An electrophotog. plate is described comprising a photoconductive
layer containing ZnO and a **binder**, where the **binder**
contains formyl groups and the functional groups -CH(OR1)(OR2)
[R1,R2 = hydrocarbon, organic radicals which may combined to form
ring]. The plate has improved stability during storage.

IT 139288-25-8P

RL: RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(preparation and polymerization of, **binder** resin for
electrophotog. plate from)

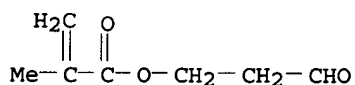
RN 139288-25-8 HCAPLUS

CN Pentanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
ester, polymer with 3-oxopropyl 2-methyl-2-propenoate and
2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

CRN 95984-03-5

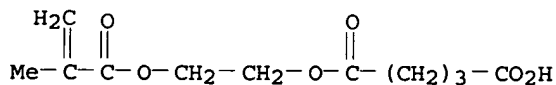
CMF C7 H10 O3



CM 2

CRN 64680-77-9

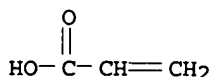
CMF C11 H16 O6



CM 3

CRN 79-10-7

CMF C3 H4 O2



IT 141680-49-1P 141680-56-0P 141680-80-0P

RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, as binder in electrophotog.-
plate)

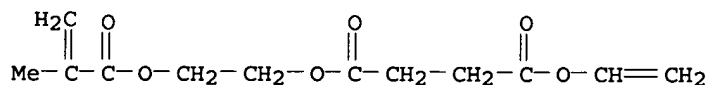
RN 141680-49-1 HCAPLUS

CN Butanedioic acid, ethenyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl
ester, polymer with methyl 2-methyl-2-propenoate,
[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] hydrogen butanedioate,
3-oxopropyl 2-methyl-2-propenoate, 2-propenoic acid and 2-propenyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 100904-40-3

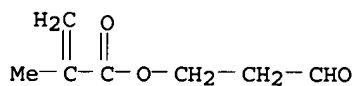
CMF C12 H16 O6



CM 2

CRN 95984-03-5

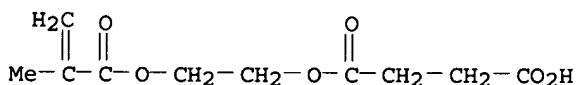
CMF C7 H10 O3



CM 3

CRN 20882-04-6

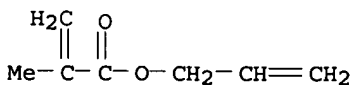
CMF C10 H14 O6



CM 4

CRN 96-05-9

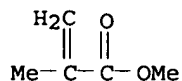
CMF C7 H10 O2



CM 5

CRN 80-62-6

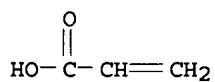
CMF C5 H8 O2



CM 6

CRN 79-10-7

CMF C3 H4 O2



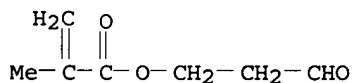
RN 141680-56-0 HCAPLUS

CMN Pentanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2,2'-[1,2-ethanediylbis(oxymethylene)]bis[oxirane], [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] hydrogen butanedioate, 3-oxopropyl 2-methyl-2-propenoate, 2-propenoic acid and propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 95984-03-5

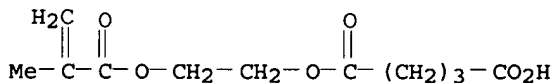
CMF C7 H10 O3



CM 2

CRN 64680-77-9

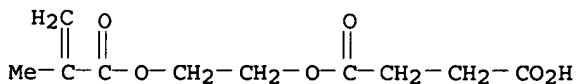
CMF C11 H16 O6



CM 3

CRN 20882-04-6

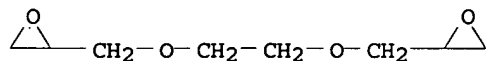
CMF C10 H14 O6



CM 4

CRN 2224-15-9

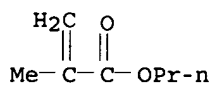
CMF C8 H14 O4



CM 5

CRN 2210-28-8

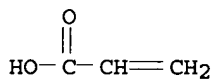
CMF C7 H12 O2



CM 6

CRN 79-10-7

CMF C3 H4 O2



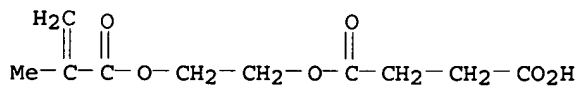
RN 141680-80-0 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2,2'-[1,2-ethanediylbis(oxymethylene)]bis[oxirane], phenylmethyl 2-methyl-2-propenoate and 2-propenoic acid, graft (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

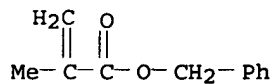
CMF C10 H14 O6



CM 2

CRN 2495-37-6

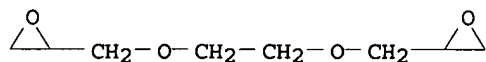
CMF C11 H12 O2



CM 3

CRN 2224-15-9

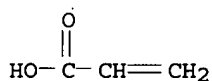
CMF C8 H14 O4



CM 4

CRN 79-10-7

CMF C3 H4 O2



IC ICM G03G005-05

ICS G03G013-28

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and
Other Reprographic Processes)
Section cross-reference(s): 35

ST electrophotog plate binder resin

IT Electrophotographic photoconductors and photoreceptors
(binder resin for)

IT 139252-83-8 139289-41-1

RL: USES (Uses)

(binder resin blend containing, for electrophotog.
-plate)

IT 139252-57-6P 139288-08-7P 139288-19-0P 139288-21-4P
139288-22-5P 139288-23-6P 139288-24-7P **139288-25-8P**
139288-26-9P 139288-28-1P 139320-89-1P 141680-89-9P
141680-90-2P

RL: RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(preparation and polymerization of, binder resin for
electrophotog. plate from)

IT 130952-79-3P 139288-27-0P **141680-49-1P** 141680-50-4P
141680-51-5P 141680-52-6P 141680-54-8P 141680-55-9P
141680-56-0P 141680-57-1P 141680-58-2P 141680-59-3P
141680-61-7P 141680-67-3P 141680-68-4P 141680-69-5P
141680-70-8P 141680-71-9P 141680-72-0P 141680-73-1P
141680-74-2P 141680-75-3P 141680-76-4P 141680-77-5P
141680-78-6P 141680-79-7P **141680-80-0P** 141680-81-1P
141680-82-2P 141680-83-3P 141680-84-4P 141680-86-6P
141680-87-7P 141680-88-8P 141680-91-3P 141680-93-5P
141680-94-6P 141680-95-7P 141680-96-8P 141680-98-0P
141681-00-7P 141690-33-7P 141690-35-9P 141690-36-0P
141690-37-1P 141690-38-2P 141690-39-3P 141698-80-8P
141698-81-9P 141713-23-7P 141740-78-5P 141740-79-6P

141740-80-9P 141740-81-OP 141740-82-1P 141740-83-2P
 141740-84-3P 141752-73-OP 141752-80-9P 141780-86-1P
 141898-60-4P

RL: SPN (Synthetic preparation); PREP (Preparation)
 (preparation and use of, as binder in electrophotog.-
 plate)

L55 ANSWER 26 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1992:31493 Document No. 116:31493 Photomerizable **printing**
plate for flexography. Abele, Werner (Du Pont de Nemours
 (Deutschland) G.m.b.H., Germany). Ger. DE 4022980 C1 19910808, 8
 pp. (German). CODEN: GWXXAW. APPLICATION: DE 1990-4022980
 19900719.

AB The title material containing a support; a photopolymerizable layer
 containing ≥ 1 elastomeric **binder**, an addition
 polymerizable compound, ethylenically unsatd. monomer, and a
 photoinitiator; an elastomer layer containing ≥ 1 thermoplastic
 elastomeric block copolymer; and a surface layer, the
 thermoplastic elastomer layer contains ≥ 1 polymer from -
 $\text{CH}_2\text{CR}_1(\text{CO}_2(\text{CH}_2)_m(\text{CR}_2\text{R}_3)\text{nO}_2\text{C} \geq \text{CR}_4\text{CR}_5\text{CO}_2\text{H}$ [$\text{R}_1 = \text{H}, \text{Me}$; R_2 ,
 $\text{R}_3 = \text{H}$, alkyl, aryl; $\text{R}_4\text{R}_5 = \text{H}$, alkyl; $m, n = 0-10$; $m + n = 2-20$].
 A method of producing the plate by using the above elastomer is
 also claimed.

IT 75226-38-9 114239-65-5

RL: USES (Uses)

(thermoplastic elastomer layer containing, for flexog. plate)

RN 75226-38-9 HCAPLUS

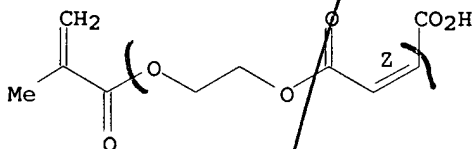
CN 2-Butenedioic acid (2Z)-, mono[2-[(2-methyl-1-oxo-2-
 propenyl)oxy]ethyl] ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 51978-15-5

CMF C10 H12 O6

Double bond geometry as shown.



RN 114239-65-5 HCAPLUS

CN 2-Butenedioic acid (2Z)-, mono[2-[(1-oxo-2-propenyl)oxy]ethyl]
 ester, homopolymer (9CI) (CA INDEX NAME)

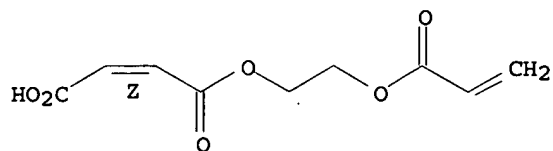
CM 1

CRN 19201-36-6

CMF C9 H10 O6

Double bond geometry as shown.

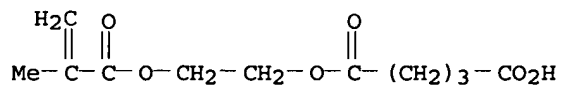
= 5213948



- IC ICM G03F007-11
ICS G03F007-027; G03F007-16; C08F002-50; C08L053-00; C08L033-14
- CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
- ST hexog printing plate thermoplastic elastomer
- IT **Printing plates**
(flexog., thermoplastic elastomer layer for)
- IT 108-31-6D, 2,5-Furandione, reaction product with methacrylic acid hydroxypropyl ester copolymer 27813-02-1D, reaction product with maleic acid anhydride 75226-38-9 105729-79-1, Isoprene-styrene block copolymer 106107-54-4, Butadiene-styrene block copolymer 114239-65-5
- RL: USES (Uses)
(thermoplastic elastomer layer containing, for flexog. plate)
- L55 ANSWER 27 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
1991:174901 Document No. 114:174901 Electrophotographic material.
Kato, Eiichi; Ishii, Kazuo (Fuji Photo Film Co., Ltd., Japan).
Eur. Pat. Appl. EP 389928 A2 19901003, 100 pp. DESIGNATED STATES:
R: DE, GB. (English). CODEN: EPXXDW. APPLICATION: EP
1990-105237 19900320. PRIORITY: JP 1989-69011 19890320; JP
1989-93144 19890414.
- AB An electrophotog. material which has excellent electrostatic characteristics, moisture resistance, and durability comprises a support having provided thereon a photoconductive layer containing inorg. photoconductive particles and a binder resin which comprises a copolymer comprising a monomer having the formula CHR1:CR2Z1R3 (R1, R2 = H, halogen, CN, hydrocarbyl, or CO2R4 where R4 = H or hydrocarbonyl; R3 = a C1-18 aliphatic group or a C6-12 aromatic group; Z1 = CO2, COC, CH2OCO, CH2CO2, O, SO2, CO, C6H4, CONR5 or SO2NR5 where R5 = H or hydrocarbyl) and ≥1 monofunctional macromonomer having a weight-average mol. weight ≤2 + 104 and comprising ≥1 polymer component having the formula -(CHR1CR2R6)- or -[CHR1CR2(Z1R3)]- (R1, R2, R3, Z1 are defined above; R6 = CN, CONH2, or C6H4R7 where R7 = H, halogen, alkoxy, or CO2R8 where R8 = alkyl, aralkyl, or aryl), ≥1 polymer component containing ≥1 polar group preferably selected from PO3H2, SO3H, and CO2H, and a polymerizable double bond group having the formula CHR1:CHR2Z1- (R1, R2, Z1 are defined above). The electrophotog. material is especially suitable for preparing an offset printing plate.
- IT 131808-69-0 131808-71-4 131837-95-1
RL: USES (Uses)
(resin binders containing, for inorg. photoconductive particles for electrophotog. photoreceptors)
- RN 131808-69-0 HCAPLUS
- CN Pentanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with methyl 2-propenoate, phenylmethyl 2-methyl-2-propenoate, 2-propenoic acid and propyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

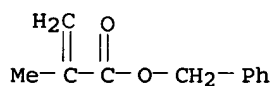
CM 1

CRN 64680-77-9
CMF C11 H16 O6



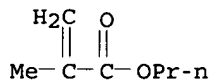
CM 2

CRN 2495-37-6
CMF C11 H12 O2



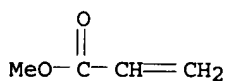
CM 3

CRN 2210-28-8
CMF C7 H12 O2



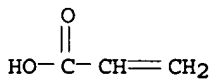
CM 4

CRN 96-33-3
CMF C4 H6 O2



CM 5

CRN 79-10-7
CMF C3 H4 O2

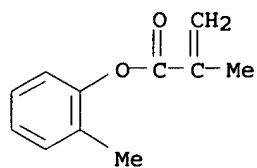


RN 131808-71-4 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with
2-carboxyethyl 2-propenoate, 2-methylphenyl 2-methyl-2-propenoate,
methyl 2-propenoate and 2-propenoic acid, graft (9CI) (CA INDEX
NAME)

CM 1

CRN 74937-80-7

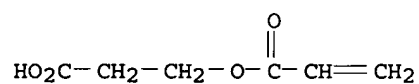
CMF C11 H12 O2



CM 2

CRN 24615-84-7

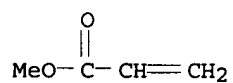
CMF C6 H8 O4



CM 3

CRN 96-33-3

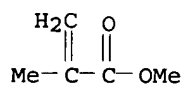
CMF C4 H6 O2



CM 4

CRN 80-62-6

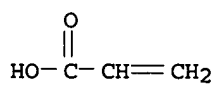
CMF C5 H8 O2



CM 5

CRN 79-10-7

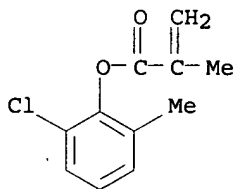
CMF C3 H4 O2



RN 131837-95-1 HCAPLUS
 CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with 2-chloro-6-methylphenyl 2-methyl-2-propenoate,
 methyl 2-propenoate, phenyl 2-methyl-2-propenoate and 2-propenoic
 acid (9CI) (CA INDEX NAME)

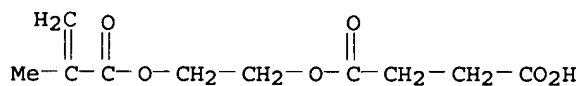
CM 1

CRN 126969-77-5
 CMF C11 H11 Cl O2



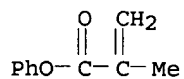
CM 2

CRN 20882-04-6
 CMF C10 H14 O6



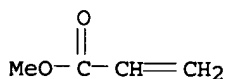
CM 3

CRN 2177-70-0
 CMF C10 H10 O2



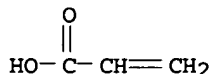
CM 4

CRN 96-33-3
 CMF C4 H6 O2



CM 5

CRN 79-10-7
CMF C3 H4 O2



IC ICM G03G005-05
CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST electrophotog material vinyl polymer **binder**; offset **printing plate** electrophotog **plate**
IT Electrophotographic plates
(containing inorg. photoconductive particles and vinyl resin blend **binders** for offset **printing plate** preparation)
IT Lithographic plates
(offset, electrophotog. materials, containing inorg. photoconductive particles and vinyl resin blend **binders**)
IT 9003-42-3 25951-87-5 26335-61-5 28062-47-7 28572-98-7
29531-62-2 39888-87-4 40081-37-6 72923-41-2 72923-42-3
79042-18-5 81772-37-4 118786-81-5 118786-83-7 120823-88-3
127397-47-1 128267-71-0 128294-80-4 128294-83-7
128294-84-8 128294-85-9 128294-87-1 128294-89-3
128383-28-8 128383-29-9 128383-30-2 128383-31-3
131004-74-5 131808-83-8 131808-84-9 131808-85-0
131808-86-1 131808-87-2 131808-88-3 131808-89-4
131808-90-7 131808-91-8 131837-97-3 131914-87-9
133370-55-5
RL: USES (Uses)
(**binders** containing vinyl resins and, for inorg. photoconductive particle for electrophotog. photoreceptors)
IT 9003-20-7, Poly(vinylacetate) 9003-53-6, Polystyrene
9003-63-8, Poly(butylmethacrylate) 9011-14-7,
Poly(methylmethacrylate) 25085-83-0, Poly(benzylmethacrylate)
26634-88-8, Styrene-ethylmethacrylate copolymer
RL: USES (Uses)
(**binders** containing vinyl resins and, for inorg. photoconductive particles for electrophotog. photoreceptors)
IT 1314-13-2, Zinc oxide, uses and miscellaneous
RL: USES (Uses)
(electrophotog. photoconductive materials containing particles of, dispersed in vinyl resin **binders** for offset **printed plate** preparation)
IT 60-23-1D, reaction product with (meth)acrylic copolymers, esters with acrylates 60-24-2D, reaction product with (meth)acrylic copolymers, esters with acrylates 68-11-1D, reaction product with (meth)acrylic copolymers, esters with acrylates 70-49-5D, reaction products with (meth)acrylic copolymers 106-91-2D, esters with (meth)acrylic copolymer-thioalkyl reaction product 107-96-0D, reaction products with (meth)acrylic copolymers 147-93-3D, reaction products with (meth)acrylic copolymers 920-46-7D, esters with (meth)acrylic copolymer-thioalkyl reaction product 2051-76-5D, esters with (meth)acrylic copolymer-thioalkyl reaction product 2638-94-0D, reaction product with (meth)acrylic copolymers, esters with acrylates 3375-50-6D, reaction products with (meth)acrylic copolymers 55428-59-6D, reaction products with (meth)acrylic copolymers 126969-33-3D, reaction products with (meth)acrylic copolymers

RL: USES (Uses)

(electrophotog. plates with **binder** resin blend containing)

- IT 26284-14-ODP, reaction product with mercaptoethanol, ester with methacryloyl chloride 26335-61-5DP, reaction product with thioglycolic acid, ester with glycidyl methacrylate 126969-71-9DP, reaction product with thioglycolic acid, ester with glycidyl methacrylate 131808-63-4DP, reaction product with aminothioethanol, ester with acrylic anhydride 131808-64-5DP, reaction product with azobis(cyanovaleric acid), ester with glycidyl methacrylate

RL: SPN (Synthetic preparation); PREP (Preparation)

(preparation and graft copolymn. of, **binders** for inorg. photoconductive particles for electrophotog. photoreceptors from)

- IT 131808-65-6 131808-66-7D, reaction product with mercaptoethanoic acid 131808-66-7D, reaction product with mercaptoethanoic and propanoic acids 131808-67-8D, reaction product with azobis(cyanovaleric acid) 131808-68-9 131808-69-0 131808-70-3 131808-71-4 131808-72-5 131808-73-6 131808-74-7 131808-76-9 131808-77-0 131808-78-1D, reaction product with mercaptosuccinic acid 131808-80-5D, reaction product with mercaptobenzoic acid 131808-81-6D, reaction product with mercaptoethylene phosphate 131808-82-7D, reaction product with mercaptoethylsulfonic acid 131837-95-1 131914-67-5D, reaction product with mercaptoethanoic acid 131914-68-6D, reaction product with mercaptopropanoic acid 131914-70-0D, reaction product with mercaptoethyl phosphate 131914-71-1D, reaction product with mercaptoethanoic acid 131914-72-2D, reaction product with mercaptobenzoic acid 131914-73-3D, reaction product with mercaptopropanoic acid 131914-74-4D, reaction product with mercaptoethanoic acid 131914-75-5D, reaction product with mercaptobenzoic acid 131914-76-6D, reaction product with mercaptobenzoic acid 131914-78-8D, reaction product with mercaptobenzoic acid 131914-79-9D, reaction product with mercaptobenzoic acid 131914-80-2D, reaction product with mercaptobenzoic acid 131914-82-4D, reaction product with mercaptobenzoic acid 131914-83-5D, reaction product with mercaptobenzoic acid 131914-84-6 131914-85-7D, reaction product with mercaptosuccinic acid 131961-10-9D, reaction product with mercaptobenzoic acid 131961-11-0D, reaction product with mercaptobenzoic acid

RL: USES (Uses)

(resin **binders** containing, for inorg. photoconductive particles for electrophotog. photoreceptors)

L55 ANSWER 28 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN

1988:446116 Document No. 109:46116 Electrophotographic offset printing plate precursor. Kato, Eiichi; Ishii, Kazuo; Itakura, Ryosuke; Sera, Hidefumi (Fuji Photo Film Co., Ltd., Japan). Ger. Offen. DE 3714542 A1 19871105, 17 pp. (German). CODEN: GWXXBX. APPLICATION: DE 1987-3714542 19870430. PRIORITY: JP 1986-100996 19860502.

- AB An electrophotog. offset printing precursor having improved photoconductive layer smoothness, electrostatic characteristics, oil-desensitization characteristics, reproduced image quality, and printing characteristics is composed of a conductive support with ≥ 1 photoconductive layer containing photoconductive ZnO and a **binder** resin containing ≥ 1 functional group that upon decomposition forms ≥ 1 OH and ≥ 1 CO₂H group. Thus, a conductive paper support was coated with a ball-milled mixture containing an acrylic acid-Bu methacrylate-2,2,2-trifluoroethyl

methacrylate-2-(trimethylsilyloxy)ethyl methacrylate copolymer (mol. weight 68,000), ZnO, Rose Bengal, phthalic anhydride, and PhMe, dried, stored 24 h at 20° and 65% relative humidity, and used to produce an offset **printing plate** having a clear image and capable of producing 10,000 prints without background stain.

IT 115157-55-6

RL: USES (Uses)

(electrophotog. plate with **binder** from, for offset lithog. plate fabrication)

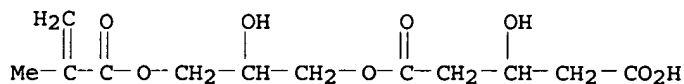
RN 115157-55-6 HCAPLUS

CN Pentanedioic acid, 3-hydroxy-, mono[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl] ester, polymer with butyl 2-methyl-2-propenoate and 2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

CRN 115157-54-5

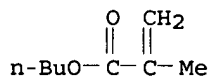
CMF C12 H18 O8



CM 2

CRN 97-88-1

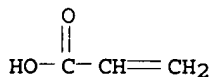
CMF C8 H14 O2



CM 3

CRN 79-10-7

CMF C3 H4 O2



IC ICM G03G013-28

ICS G03G005-05

ICA C08L031-02; C08L033-04; C08L033-24; C08L035-02; C08L037-00; C08L039-04

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST electrophotog offset **printing plate** precursor;
binder offset **printing** electrophotog **plate**

IT Acrylic polymers, uses and miscellaneous

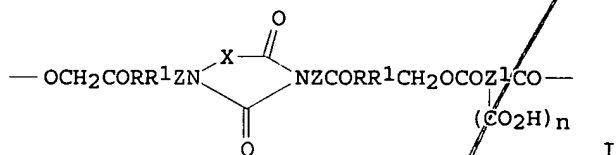
RL: USES (Uses)

(electrophotog. plates with **binders** from, for offset

- lithog. plate fabrication)
- IT Electrophotographic plates
(with **binder** forming carboxy and hydroxy groups upon decomposition for offset lithog. plate preparation)
- IT Lithographic plates
(offset, electrophotog. plates with **binder** resin forming hydroxy and carboxy groups upon decomposition for fabrication of)
- IT 115157-55-6 115157-57-8 115157-58-9 115215-06-0
RL: USES (Uses)
(electrophotog. plate with **binder** from, for offset lithog. plate fabrication)

L55 ANSWER 29 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
1982:152850 Document No. 96:152850 Water-dispersible energy curable heterocyclic group-containing polyesters. Wendling, Larry A. (Minnesota Mining and Manufacturing Co., USA). Eur. Pat. Appl. EP 40002 A1 19811118, 26 pp. DESIGNATED STATES: R: CH, DE, FR, GB, IT, NL. (English). CODEN: EPXXDW. APPLICATION: EP 1981-301614 19810413. PRIORITY: US 1980-148776 19800512.

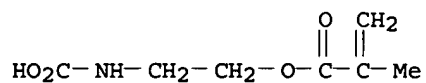
GI



- AB H2O-dispersible, photocurable polyesters useful in **printing plate** production and in graphic arts work are tough, abrasion and solvent resistant, and consist of a repeating unit I (R = H, COR2, CONHR3 where R2 = alkenyl, C2-5 alkyl substituted by Ph or CO2H and R3 = aliphatic or aromatic hydrocarbyl having ≥ 8 C atoms; R1 = H, Me; X = divalent group required to complete a 5- or 6-membered heterocyclic ring; Z = a single bond or alkylene group; Z1 = the divalent or trivalent residue of hydrocarbyl di- or tricarboxylic acids; n = 0-1). These polyesters, which have reduced curing speed and reduced development problems, can be used to produce a plate which does not require a **binder**. Thus, 12 μ m polyester support was coated with a THF solution containing 1,3-diglycidyl-5,5-dimethylhydantoin-itaconic acid polymer and 2,2-dimethoxy-2-phenylacetophenone 2 weight%, dried to give 2.5 μ m layer, imagewise exposed to a Hg lamp (140 W; at 6 cm) for 30 s through a stencil, and developed with 10% aqueous EtOH to give an image with an excellent resolution
- IT 81406-34-0D, reaction products with 2-methacryloyloxyethyl isocyanate 81406-35-1D, reaction products with 2-methacryloyloxyethyl isocyanate
RL: TEM (Technical or engineered material use); USES (Uses)
(photoimaging composition containing, for **printing plate** production and graphic arts)
- RN 81406-34-0 HCAPLUS
- CN Butanedioic acid, methylene-, polymer with 5,5-dimethyl-1,3-bis(oxiranylmethyl)-2,4-imidazolidinedione, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

CM 1

CRN 96571-20-9
CMF C7 H11 N O4

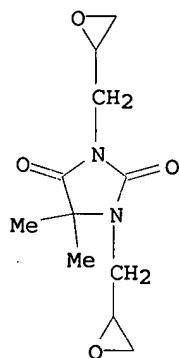


CM 2

CRN 81313-14-6
CMF (C11 H16 N2 O4 . C5 H6 O4)x
CCI PMS

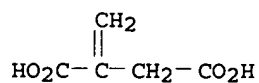
CM 3

CRN 15336-81-9
CMF C11 H16 N2 O4



CM 4

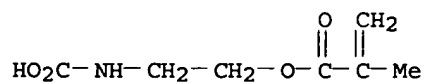
CRN 97-65-4
CMF C5 H6 O4



RN 81406-35-1 HCAPLUS
CN Butanedioic acid, methylene-, polymer with 5,5-dimethyl-1,3-bis(oxiran-2-ylmethyl)-2,4-imidazolidinedione, (2Z)-2-butenedioate, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

CM 1

CRN 96571-20-9
CMF C7 H11 N O4

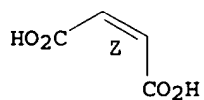


CM 2

CRN 110-16-7

CMF C4 H4 O4

Double bond geometry as shown.



CM 3

CRN 81313-14-6

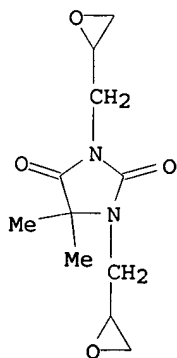
CMF (C11 H16 N2 O4 . C5 H6 O4)x

CCI PMS

CM 4

CRN 15336-81-9

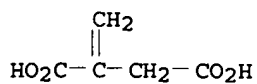
CMF C11 H16 N2 O4



CM 5

CRN 97-65-4

CMF C5 H6 O4



IC C08G059-26; C08G059-42; C08G063-68; G03C001-70

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST photopolymer imaging **printing plate**;
glycidylhydantoin itaconic acid polyester photoimaging; graphic arts photocurable polyester

IT **Printing plates**
(photocurable polyesters containing hydantoin groups and methylene groups for fabrication of)

IT Polyesters, uses and miscellaneous
RL: TEM (Technical or engineered material use); USES (Uses)
(photocurable, water-dispersible, containing hydantoin groups and methylene groups, for **printing plate** production and graphic arts)

IT 103-71-9D, reaction products with diglycidyl dimethylhydantoin-itaconic acid copolymer 30674-80-7D, reaction products with diglycidyl dimethylhydantoin-itaconic acid copolymer 81313-14-6 81313-15-7 81406-32-8 81406-33-9 **81406-34-0D**, reaction products with 2-methacryloyloxyethyl isocyanate **81406-35-1D**, reaction products with 2-methacryloyloxyethyl isocyanate 81406-36-2D, reaction products with Ph isocyanate 81406-72-6
RL: TEM (Technical or engineered material use); USES (Uses)
(photoimaging composition containing, for **printing plate** production and graphic arts)

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